

Operations Manual
for the
F50
Thin-Film Mapper

Revision 8.12.1.0
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Welcome

What is the FILMapper software used for?

The FILMapper software is used to run a variety of instruments, including the F50, F54, F57, F60, and F64 as well as our SS-XY10-Auto-100mm stage. These systems can be used to measure the thickness of dielectrics, semiconductors, and thin metal films. Measured films must be optically smooth and between 40 Å and 3 mm thick (depending upon system configuration). Optical constants (n and k) can also be measured on a variety of dielectric films. Commonly measured films include semiconductor process films such as oxides, nitrides, resists, and polysilicon, flat panel display films such as polyimides, resist, and cell gaps, and the various coatings used in CD and DVD manufacture. Films that can not be measured include very rough films and opaque dielectric films.

Warning: Accurate measurements require suitable recipe settings and a valid baseline. Improper system setup or an aged lamp may also lead to errors. It is the user's responsibility to ensure that this instrument is being used properly for its intended purpose. Please contact Filmetrics support for assistance with any questions.

Safety, Maintenance, and Care



This symbol indicates information or instructions that must be read and carefully followed to prevent hazards, injury to the operator, or damage to the instrument.



This symbol indicates a potential shock hazard. Areas marked with this symbol should be serviced by a trained service technician.



This symbol indicates that the product conforms to the WEEE (Waste in Electrical and Electronic Equipment) Directive 2002/96/EC.



This symbol indicates that the product meets the applicable EU safety, health and environmental protection directive requirements.



This label indicates the Model Number and Serial Number of the instrument. This information may be necessary when contacting Filmetrics for assistance.



Disclaimer: Use of this instrument in a manner inconsistent with the information and directions included in this manual may impair the protections designed into the product resulting in danger to the operator or damage to the instrument.



Installation Location: When deciding on a location for the instrument, ensure that the instrument is installed in a well-ventilated location. Enclosing the unit, or blocking the vent holes, may impair the performance of the instrument or damage the internal components.

Cleaning: The need for periodic cleaning of the system is based on the cleanliness of the environment in which the system is installed. Only the external surfaces are to be cleaned. Cleaning and maintenance of all internal components is to be performed by a trained service technician. Do not use aerosol, or spray, cleaners as they may contaminate the sensitive optical surfaces on the instrument.



Before performing any service on the instrument ensure that the main power is disconnected.

Cleanroom, or low lint, wipes should be used to wipe down the system. A mixture of Isopropyl Alcohol (IPA) and De-ionized Water (DI H₂O) at 70% DI H₂O: 30% IPA is to be used for cleaning. Undiluted IPA may be used, if the 70:30 DI and IPA mixture is not available, but extra care must be taken. Avoid using stronger solvents, such as acetone, as these may compromise the surface finish.

Avoid excessive pressure on any surface when cleaning. Excessive force may bend a component, which would damage the system, or cause the system to be out of alignment.

Start with the top of the system and work down. Use slow motions, in a straight line, from the back to the front of the surface being cleaned. Change the cleaning wipe periodically to avoid re-depositing material back onto the surface being cleaned. Allow all cleaned surfaces to dry completely before restoring power to the system.

CE Mandated Warnings



Please read the following instructions carefully to prevent potential shock or fire hazards. This manual should be retained for future use



Bitte lesen Sie die nachstehende Anleitung sorgfältig durch, um Stromschlag und Feuergefahr zu vermeiden. Diese Betriebsanleitung soll für späteren Gebrauch sorgfältig aufbewahrt werden.



Preghiamo di leggere accuratamente, le sequenti Istruzioni, per evitare Prossimi Incendi e Correnti.



Shock Hazard - Do Not Enter
Achtung Hochspannung - Nicht Berühren
Attenzione Corrent-Forte - Prego non toccare



The front panel's switch is not the power disconnect device. The power cord should be removed after use.

Der Kippschalter an der Vorderseite unterbricht nicht die Stromzuführung. Das Stromkabel soll nach Gebrauch aus dem Gerät herausgezogen werden.

L'interuttore nella parete frontale non blocca le Corrente. La Corrente viene.



Never expose the unit to water or liquids. Avoid direct sun.

Bringe das Gerät nicht mit Wasser oder anderen Flüssigkeiten in Berührung. Vermeide direkte Sonneneinstrahlung.

Evitare contatto con acqua oppure liquidi Infiammabili al Macchineggio. Anche entrate di Sole.



Do not insert any objects into the unit.

Keinen Gegenstand in das Gerät einbringen. Do non inseriamo any obietta into gli unità.

Non mettere oggetti dentro la Macchina.



Do not use near open flame or heat.
Das Gerät nicht in der Nähe einer offenen Flamme oder Hitze benutzen.
Non mettere la Macchina vicino a fuochi oppure Riscaldamenti.



The unit should never be enclosed or blocked.
Das Gerät darf nicht eingeschlossen oder blockiert werden.
La Macchina non chinderla per nessun motivo.



Connect unit only to a properly measured supply with a reliable earth ground. Use only the three wire cord which is provided with the unit.
Schließen Sie das Gerät nur an eine ordnungsgemäss vermessene Stromversorgung an. Verwenden Sie nur ein dreiadriges Kabel, wie es auch mit dem Gerät ausgeliefert wird.
Montare solo con misura normata. Adoperando solo 3 cavi elettrici così come e fornita la Macchina.

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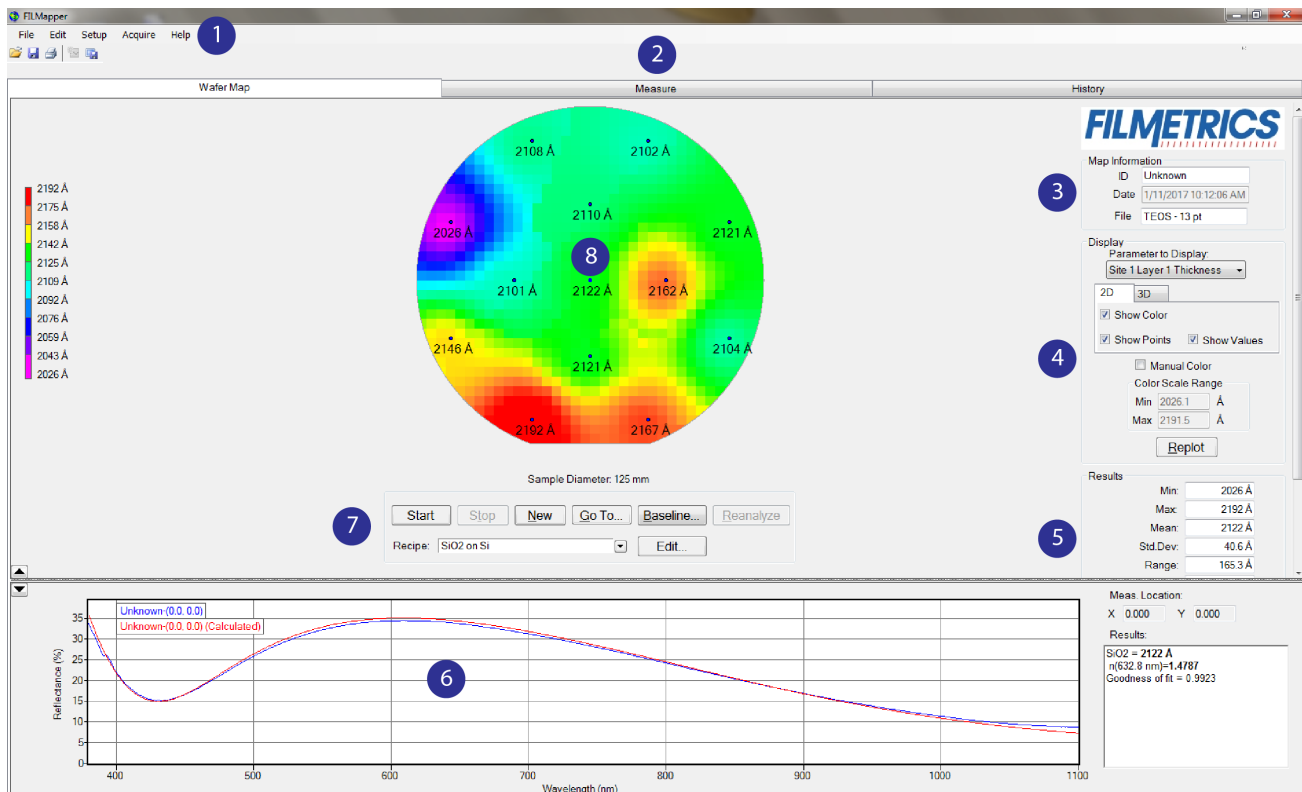
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1. Software Overview

The way that light reflects off a thin film is determined by the characteristics of the film, such as its thickness, optical constants, and roughness. The F50 is able to determine thin-film characteristics by first carefully measuring the amount of light reflected from the thin film over a range of wavelengths (i.e., by measuring the reflectance spectrum). It then analyzes this data by comparing it to a series of calculated reflectance spectra. Most of the features of the FILMapper software that runs the F50 can be divided into reflectance acquisition and reflectance analysis functions. The following pages outline the main features of the FILMapper software.

The [Wafer Map Tab](#) is used to initiate mapping and to display measurement results. The map configuration and the film properties to be mapped are specified in the [Edit Recipe > Wafer Map](#) dialog box.

1.1 The Wafer Map Tab



1. Standard Windows menus; [File](#), [Edit](#), [Setup](#), [Acquire](#), and [Help](#).
2. Select between the **Wafer Map**, [Measure](#), and [History](#) windows.
3. Information about the *Operator* can be entered here for tracking purposes. Sample information is automatically determined when the wafer map is saved based upon the settings under the **Measure** tab.
4. This section is used to determine how the map is displayed. The **Replot** button must be clicked to enact any changes selected.
 - i. **Parameters to Display**: Allows the user to select which parameter (thickness, index, roughness, etc.) to display on the map. Only parameters currently being solved for will be listed.
 - ii. **2D/3D**: Allows the user to select between two dimensional and three dimensional maps.
 - iii. **Show Color**: Enables or disables the color bar on the left hand side of the map.
 - iv. **Show Points**: Enables or disables displaying the measured points on the map.
 - v. **Show Values**: Enables or disables displaying the measured values at each point.
 - vi. **Manual Color**: Allows the user to input a manually selected color scale.
5. Statistical analysis for the set of measurements taken.
 - i. **Minimum** parameter value recorded for selected wafer, x_{min} .
 - ii. **Maximum** parameter value recorded for selected wafer, x_{max} .
 - iii. **Mean** (average) parameter value of all measurement locations, .

$$= \sqrt{\frac{\sum(x - \bar{x})^2}{n - 1}}$$

iv. **Std.Dev.** (Standard Deviation), or 1σ , is calculated using the following equation:

where \bar{x} is the mean and n is the number of measurements.

v. **Uniformity** as a percentage. The equation used in the uniformity calculation is determined under [Setup > Options > Map](#).

vi. **CTE** is the center to edge thickness variation calculated using a least squares linear fit of the average thickness of 10 radial regions. If the CTE is positive (> 0), then the thickness is greater around the wafer edge. If the CTE is negative (< 0), then the thickness is greater near the center of the wafer.

vii. The **Wedge** value is the product of the slope at the angle specified by the **Wedge Angle** and the sample diameter (for rectangular samples the length of the longest edge is used in place of diameter).

viii. The direction of maximum positive slope (increasing measured values) is given by the **Wedge Angle** where $x=1, y=0$ is 0° (3 o'clock) and $x=0, y=1$ is 90° (12 o'clock).

ix. **Valid** indicates how many locations have valid results out of the total number of measurement locations based on the minimum valid GOF set under [Alarms](#) in the recipe.

6. Spectrum for the currently selected measurement point. This window can be expanded or collapsed using the arrows on the left hand side of the graph window.

7. These options control the wafer map process.

i. **Start** or Restart the mapping cycle. Not available if there is no valid baseline or a map in progress.

ii. **Stop** the mapping cycle.

iii. **New** clears the measurement results and displays the points to be measured as determined by the settings in [Edit Recipe > Wafer Map](#) tab.

iv. **Go To** a specified location on the wafer.

v. Initiate a **Baseline**.

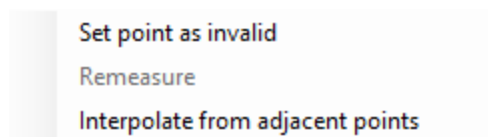
vi. **Reanalyze** the current map if the recipe has been changed or a new recipe has been selected.

vii. Used to select saved recipes.

viii. Opens the [Edit Recipe](#) window.

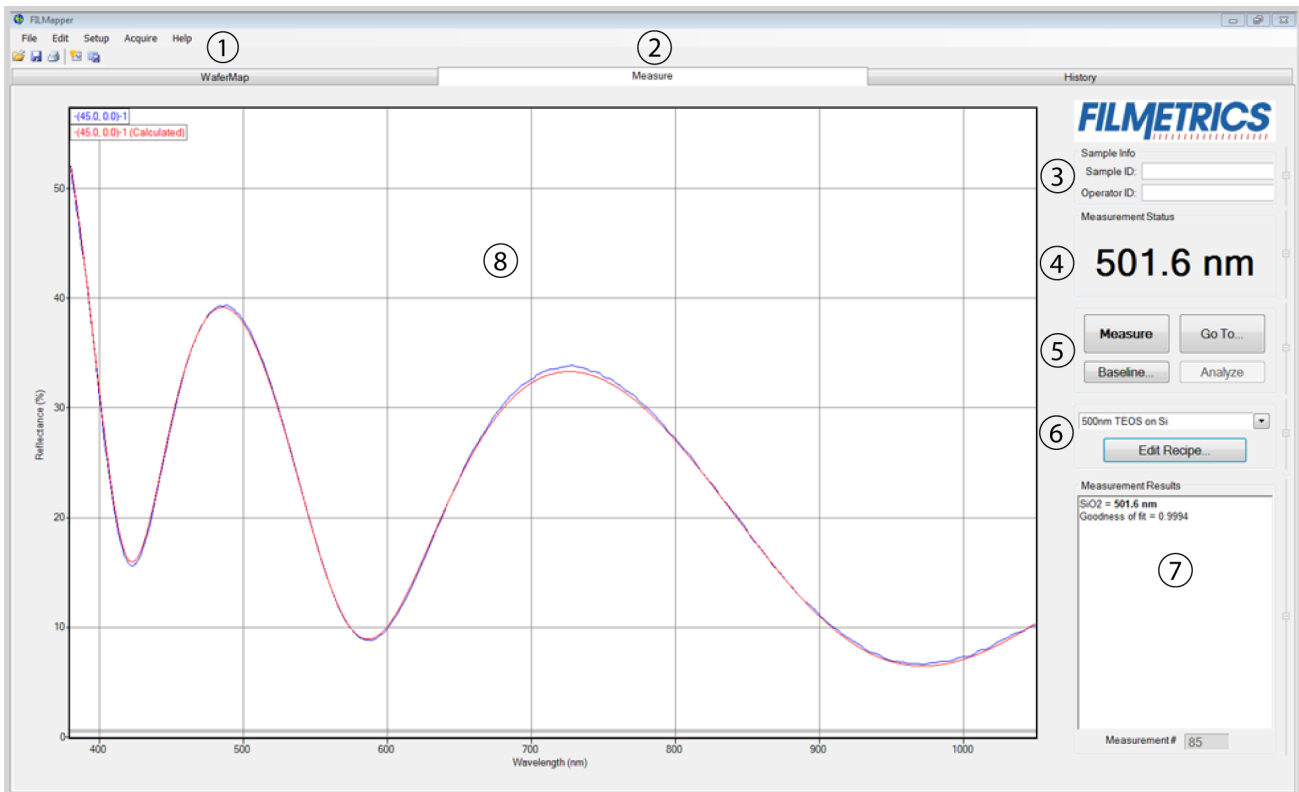
8. Graphical display of the wafer with points of measurement as well as a color scale for thickness summary.

Based upon the options selected, left clicking on a point will either move the stage to that exact location or the nearest point on the map. Right clicking opens the following menu, which allows you to either mark a currently measured point as invalid, remeasure an individual invalid point using the current recipe, or interpolate the value of an invalid point using adjacent values.

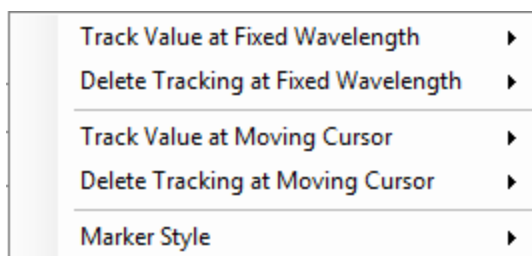


The top of the image is the edge closest to the stage mirrors.

1.2 The Measure Tab

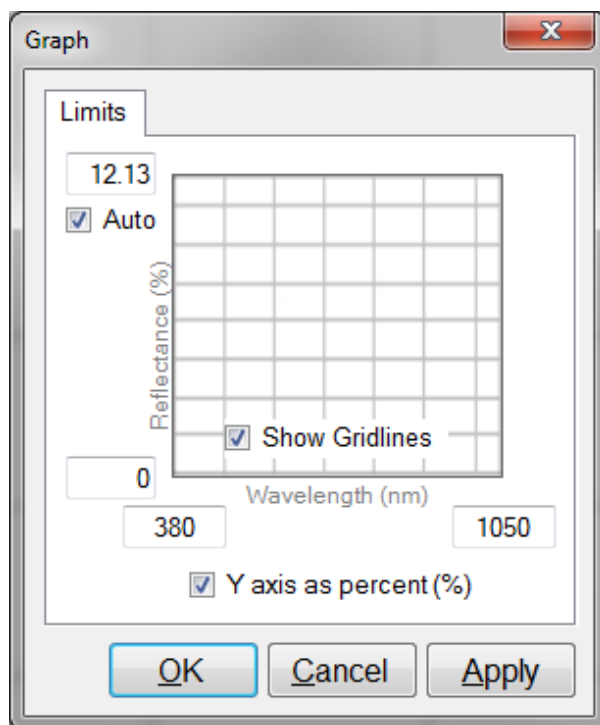


1. Standard Windows menus: [File](#), [Edit](#), [Setup](#), [Acquire](#), and [Help](#).
2. Click on these tabs to select between the [Wafer Map](#), [Measure](#), and [History](#) windows.
3. Information about the **Operator** and **Sample** can be entered here for tracking purposes.
4. Displays the thickness of the film being solved for, as well as whether a sample is good or bad based on the settings selected in the [Alarms](#) tab.
5. **Measure** a sample, [Go To](#) a point on the wafer, [Baseline](#) the system, or **Analyze** an already opened spectrum. If the **Measure** button is grayed out, the system will require a baseline before further measurements may be taken.
6. Select saved recipes from the drop-down list, or open the [Edit Recipe](#) dialog box.
7. Details about the calculated thickness, as well as any additional parameters that were solved for, including **Roughness**, n and k , and **Nonuniformity**, and the [Goodness of Fit \(GOF\)](#) are displayed here.
8. Graphical display for spectra. A click of the right mouse button while the cursor is within the graphical display opens the menu below for easy reading of cursor values in the **Measure Tab**. Use the keyboard up/down and right/left arrows to move the marker to a desired location.



The graph limits can be changed by double-clicking on the graph display. The text boxes along the bottom of the graph control the wavelength range, in nanometers, displayed on the screen. For systems with multiple spectrometers, the software will automatically resize to match anytime the selected spectrometer is changed.

The two boxes on the left represent the *Reflectance (%)* range, with the max being set in the upper box and the min being set in the lower. The boxes on the right are for *Transmittance (%)*. Check the **Auto** checkbox to activate y-axis autoscaling. The lower value is always 0 for autoscaling; the maximum y-axis upper limit is 5000. The axes can be set to display in percent or as a decimal value (100% = 1).



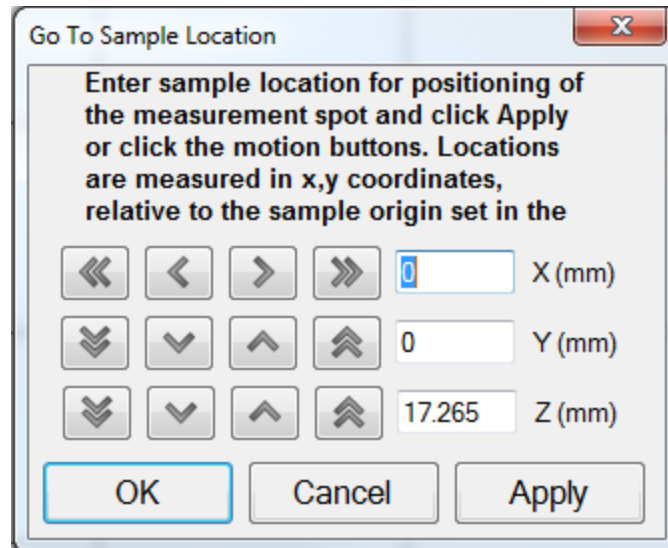
Graph Options can be accessed and edited by double-clicking on the main graph window.

8. Controls and settings for the camera are available here. By clicking **Show Window**, the video image will launch in separate non-modal window. This allows the user to maximize the graph space available by either minimizing the camera window, or moving it to a separate monitor if available.



1.3 Go To

The **Go To** function allows the user to manually locate the system in the x, y, and, with capable systems, the z direction. Measurements may be entered as discrete coordinates or by clicking on the arrow keys to move the stage accordingly. When using the arrow controls, the single arrows allow a slower movement speed while the double arrows are for faster motion.



1.4 The History Tab

The screenshot shows the FILMapper software interface with the History tab selected. The interface is divided into three main sections: Wafer Map, Measure, and History. The History section contains a table of measurement data and a graph of reflectance versus wavelength.

Measurement History Summary:

Stats	L1 d (Å)	L1 R (Å)	Sub R (Å)	GOF
Mean	1100.0	11	1705.9	4.417
Median	5073.5	10.3	18.5	.00000
Std Dev	30253	3.9	2934.7	48937
Min	0	4.5	4.6	.00000
Max	196750	19.5	5094.6	.99997
Range	196750	15	5090	.99997

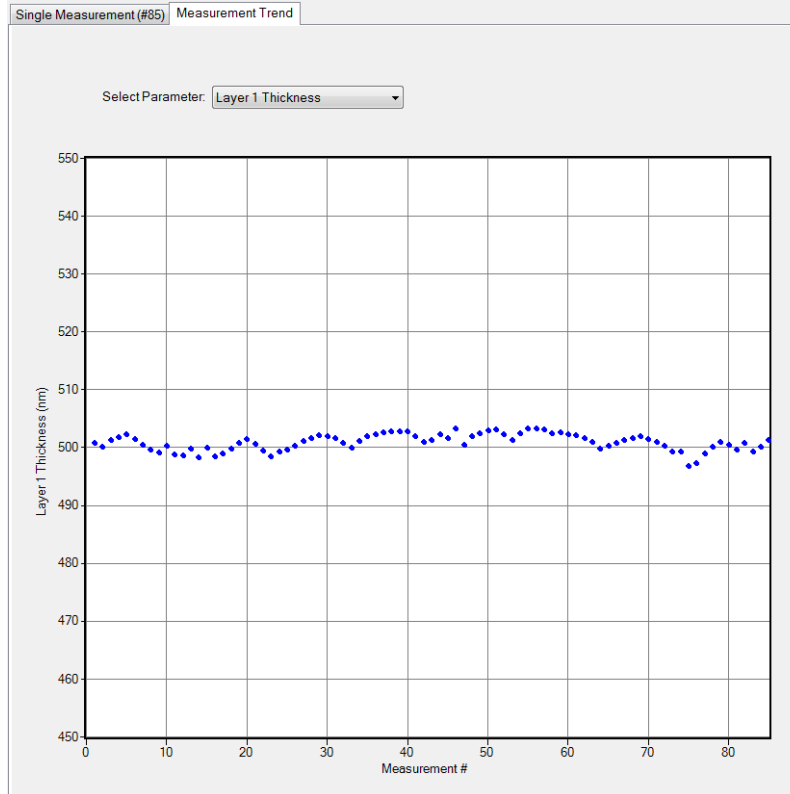
Measurement History Table:

Meas #	L1 d (Å)	GOF	Result	Recipe	Date/Time	Elapsed Time (s)	User ID	Sample ID	Val
761	7181.7	99941		SiO2 on Si	11/3/2010 5:51:46 AM	9.92		Unknown-327	1
762	7178.5	99900		SiO2 on Si	11/3/2010 5:51:47 AM	10.19		Unknown-328	1
763	7180.4	99912		SiO2 on Si	11/3/2010 5:51:47 AM	10.45		Unknown-329	1
764	7181.4	99929		SiO2 on Si	11/3/2010 5:51:47 AM	10.72		Unknown-330	1
765	7177.5	99935		SiO2 on Si	11/3/2010 5:51:47 AM	10.98		Unknown-331	1
766	7179.4	99912		SiO2 on Si	11/3/2010 5:51:48 AM	11.25		Unknown-332	1
767	7179.4	99917		SiO2 on Si	11/3/2010 5:51:48 AM	11.52		Unknown-333	1
768	7180.7	99929		SiO2 on Si	11/3/2010 5:51:48 AM	11.78		Unknown-334	1
769	7180.1	99913		SiO2 on Si	11/3/2010 5:51:48 AM	12.05		Unknown-335	1
770	7178.3	99889		SiO2 on Si	11/3/2010 5:51:49 AM	12.31		Unknown-336	1
771	7181.4	99934		SiO2 on Si	11/3/2010 5:51:49 AM	12.58		Unknown-337	1
772	7178.1	99898		SiO2 on Si	11/3/2010 5:51:49 AM	12.83		Unknown-338	1
773	7180.2	99912		SiO2 on Si	11/3/2010 5:51:49 AM	13.09		Unknown-339	1
774	7178	99889		SiO2 on Si	11/3/2010 5:51:50 AM	13.36		Unknown-340	1
775	7181.3	99931		SiO2 on Si	11/3/2010 5:51:50 AM	13.63		Unknown-341	1
776	7180.9	99927		SiO2 on Si	11/3/2010 5:51:50 AM	13.89		Unknown-342	1
777	7180.3	99913		SiO2 on Si	11/3/2010 5:51:51 AM	14.16		Unknown-343	1
778	7182	99945		SiO2 on Si	11/3/2010 5:51:51 AM	14.42		Unknown-344	1
779	7179.1	99908		SiO2 on Si	11/3/2010 5:51:51 AM	14.69		Unknown-345	1
780	7180.9	99919		SiO2 on Si	11/3/2010 5:51:51 AM	14.94		Unknown-346	1
781	7177.2	99878		SiO2 on Si	11/3/2010 5:51:52 AM	15.22		Unknown-347	1
782	7181.9	99929		SiO2 on Si	11/3/2010 5:51:52 AM	15.48		Unknown-348	1
783	7176.9	99867		SiO2 on Si	11/3/2010 5:51:52 AM	15.75		Unknown-349	1
784	7177.4	99884		SiO2 on Si	11/3/2010 5:51:52 AM	16.02		Unknown-350	1
785	7180.2	99925		SiO2 on Si	11/3/2010 5:51:53 AM	16.28		Unknown-351	1

Measurement Trend Graph:

The graph shows Reflectance (%) on the y-axis (0 to 45) versus Wavelength (nm) on the x-axis (400 to 1000). The data points are plotted as a red dashed line, and a blue solid line represents the fit. The fit equation is $\text{SiO}_2 = 7182.1 \text{ \AA}$ with a Goodness of fit = 0.99946.

1. Standard Windows menus, including; [File](#), [Edit](#), [Setup](#), [Acquire](#), and [Help](#).
2. Click on these tabs to select between the [Wafer Map](#), [Measure](#), and **History** windows.
3. Used to alternate between the **Single Measurement** and **Measurement Trend** tab. Selecting the **Measurement Trend** tab will allow the user to see a plot of the measurement results versus measurement number. A drop-down list allows the user to select between which parameter is displayed.

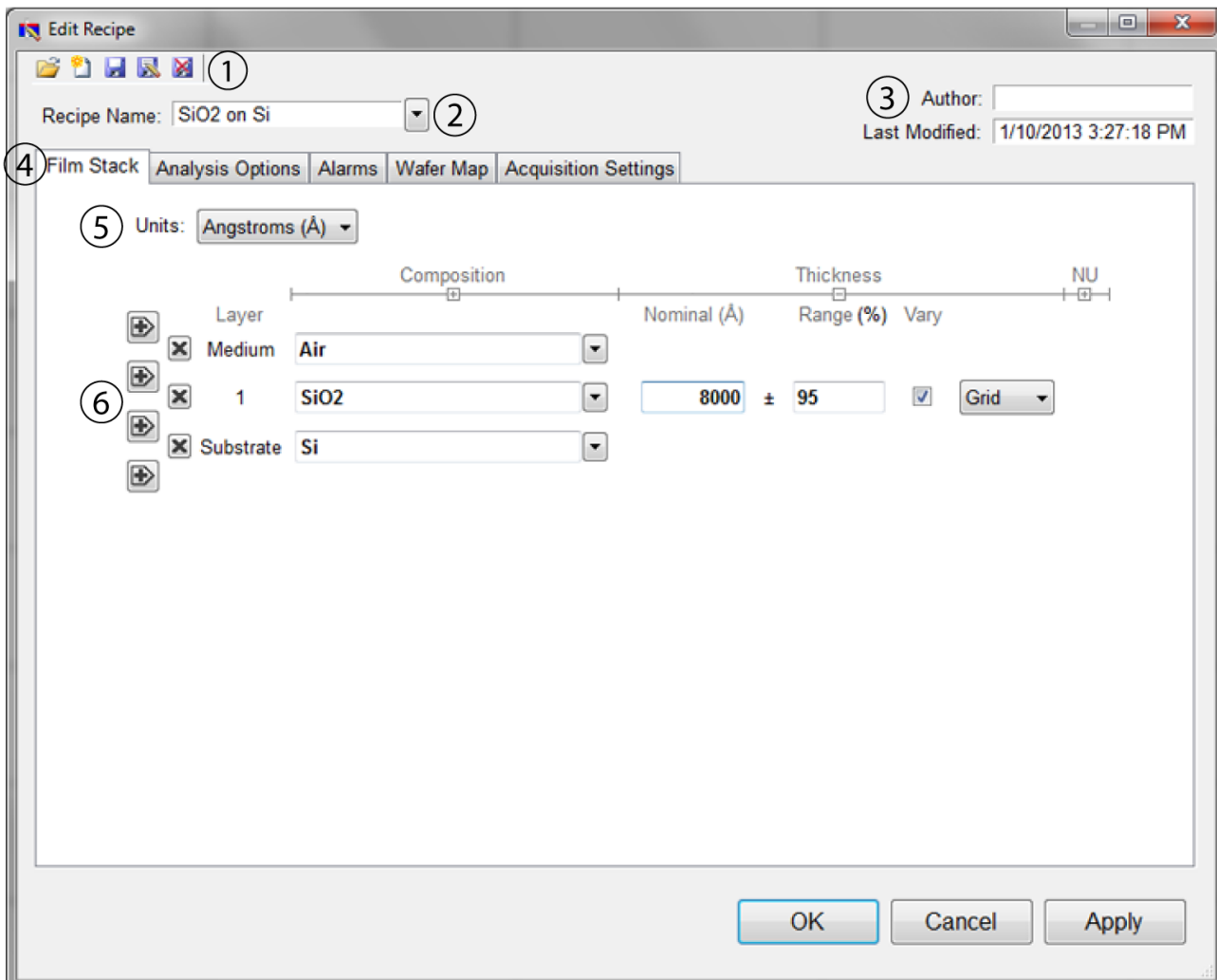


When the **Measurement Trend** tab is selected in the **History** window, the right side of the screens graphs the results.

4. Shows the measurement results for the selected spectrum (must be in **Single Measurement** mode).
5. Displays the selected spectrum in **Single Measurement** mode or the measurement trend plot in **Measurement Trend** mode.
6. Displays statistics for all measurements included in the history file. This data can be selected for copying and pasting outside of the software.
7. This list contains all spectra currently included in the history file. Left clicking on a column header will re-sort the data in ascending or descending order based on the selected column. Right clicking anywhere in this box will allow the user to open the **Edit Columns** control panel.

1.5 The Edit Recipe Window

The **Edit Recipe** window is used to define the film stack and to set analysis and acquisition parameters.



1. These buttons allow you to, in order from left to right:
 - i. Open a saved recipe.
 - ii. Start a new recipe.
 - iii. Save the current settings.
 - iv. Save the current settings as a new recipe
 - v. Delete the current recipe.
2. Opens a drop-down list for quick access to saved recipes.
3. **Author**, as defined by [user login name](#) and recipe modification date is indicated here.
4. Allows the user to select between the **Film Stack**, [Analysis Options](#), [Alarms](#), [Wafer Map](#), and [Acquisition Settings](#) tabs.

5. The desired thickness units are chosen here. The choices include angstroms (\AA , 10^{-10} m), nanometers (nm, 10^{-9} m), kilo-angstroms ($k\text{\AA}$, 10^{-7} m), microns (μm , 10^{-6} m), microinches, mils, millimeters (mm, 10^{-3} m), and [Custom Units](#).

6. This is where the materials and parameters to be solved are defined.

1.6 Menu Controls

This section describes the various functions available through the standard Windows File Menus.

[File Menu](#)

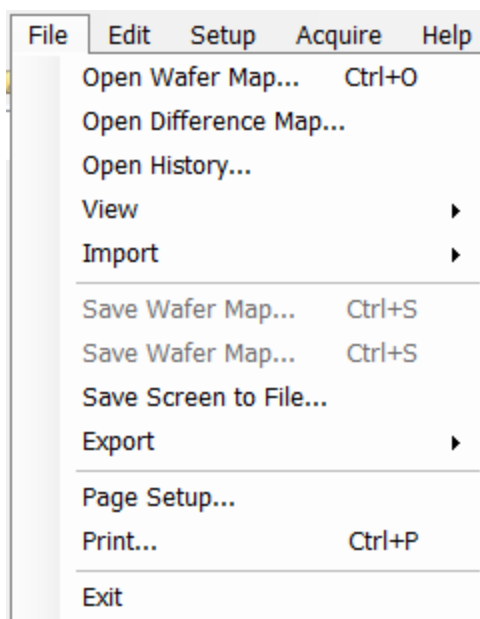
[Edit Menu](#)

[Setup Menu](#)

[Acquire Menu](#)

[Help Menu](#)

1.6.1 File Menu



Open Spectrum... (Measure Tab only)

This command is used to open stored reflectance spectra, which are then displayed and can be analyzed for film properties.

Open History...

Previously saved [History](#) data containing measurements and statistics can be loaded with this command.

Open Wafer Map... (Wafer Map Tab only)

This command is used to open stored wafer maps, which are then displayed and can be analyzed for film thickness.

Open Difference Map... (Wafer Map Tab only)

This command allows users to display thickness differences between 2 maps (Map2-Map1). Film structure and map pattern must be the same for both map recipes. Press the **Select Map** button to browse for the map files.

Import: Recipe...

Import recipes that were previously exported or created with an older version of FILMapper.

Import: Material...

Import materials not currently in the software either created by the user or provided by Filmetrics.

Import: License...

When the user purchases an upgrade for the system, Filmetrics will send a license file to the user. The license must be imported into the software before upgrades are effective.

Save Measured Spectrum... (Measure Tab only)

This command is used to save spectra for export or later analysis. Files can be saved in four different formats:

*.fmspe: This file can only be opened in FILMapper 6.0 or greater and is the preferred way to save spectra. Additional information from data acquisition is stored in this file.

*.spe: This file can be opened in all versions of FILMapper.

*.csv: This is a comma-delimited file that can be opened directly in Excel.

*.txt: This is a tab-delimited file and can be opened with a text editor.

Save Screen to File... (Measure Tab only)

This command takes a screenshot of the FILMapper window.

Save Wafer Map... (Wafer Map Tab only)

This command is used to save measured wafer maps for export or later analysis. Files can be saved in two different formats:

*.ficwm: This file can only be opened in FILMapper 7.10 or later, and is the preferred way to save maps. This file will contain all of the data captured in measurement process including individual spectra, results, images and more.

*.fimap: This file can be opened in all versions of FILMapper.

Save n and k to files... (Measure Tab only)**Export: Recipe...**

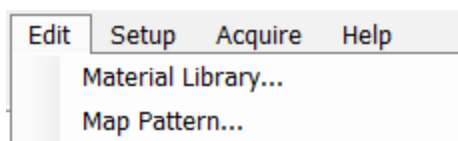
Recipes can be exported for use on other computers running FILMapper. The exported file will also automatically include any material files required by the recipe. To duplicate an analysis, all that is needed is the exported recipe and the spectrum being analyzed.

Export: Recipe for FILMapper 4...

This command will convert a recipe for use with FILMapper 4. This will not include material files or recipe features only available in later versions of FILMapper.

Export: SystemInfo File...

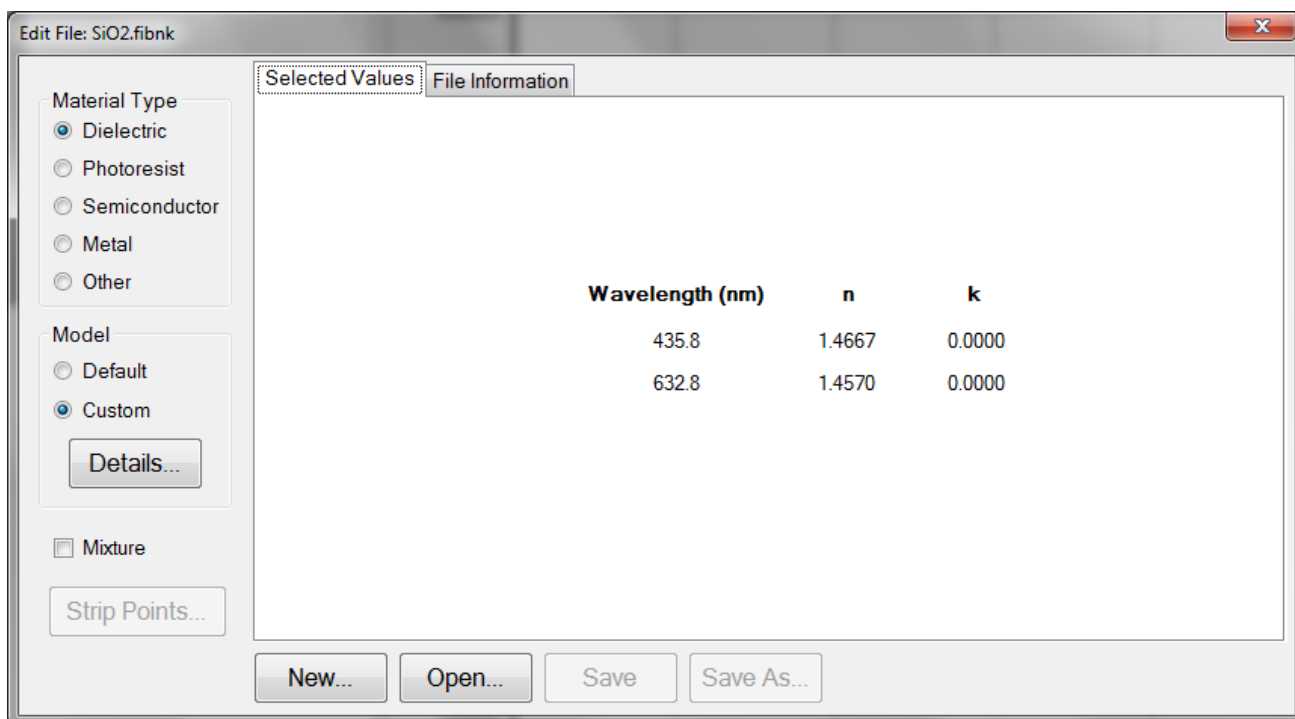
For certain software upgrades, the user will be required to send the SystemInfo file to Filmetrics which can be exported using this command.

1.6.2 Edit Menu

This menu allows access to the [Material Library](#), as well as the [Map Pattern](#) editor.

Material Library

The material library is used to display information about existing materials as well as create new ones. Material files shipped with FILMapper have the file extension ".fibnk" and will only display limited information. User created material files, ".fitnk", can be plotted on a graph or viewed in table form.

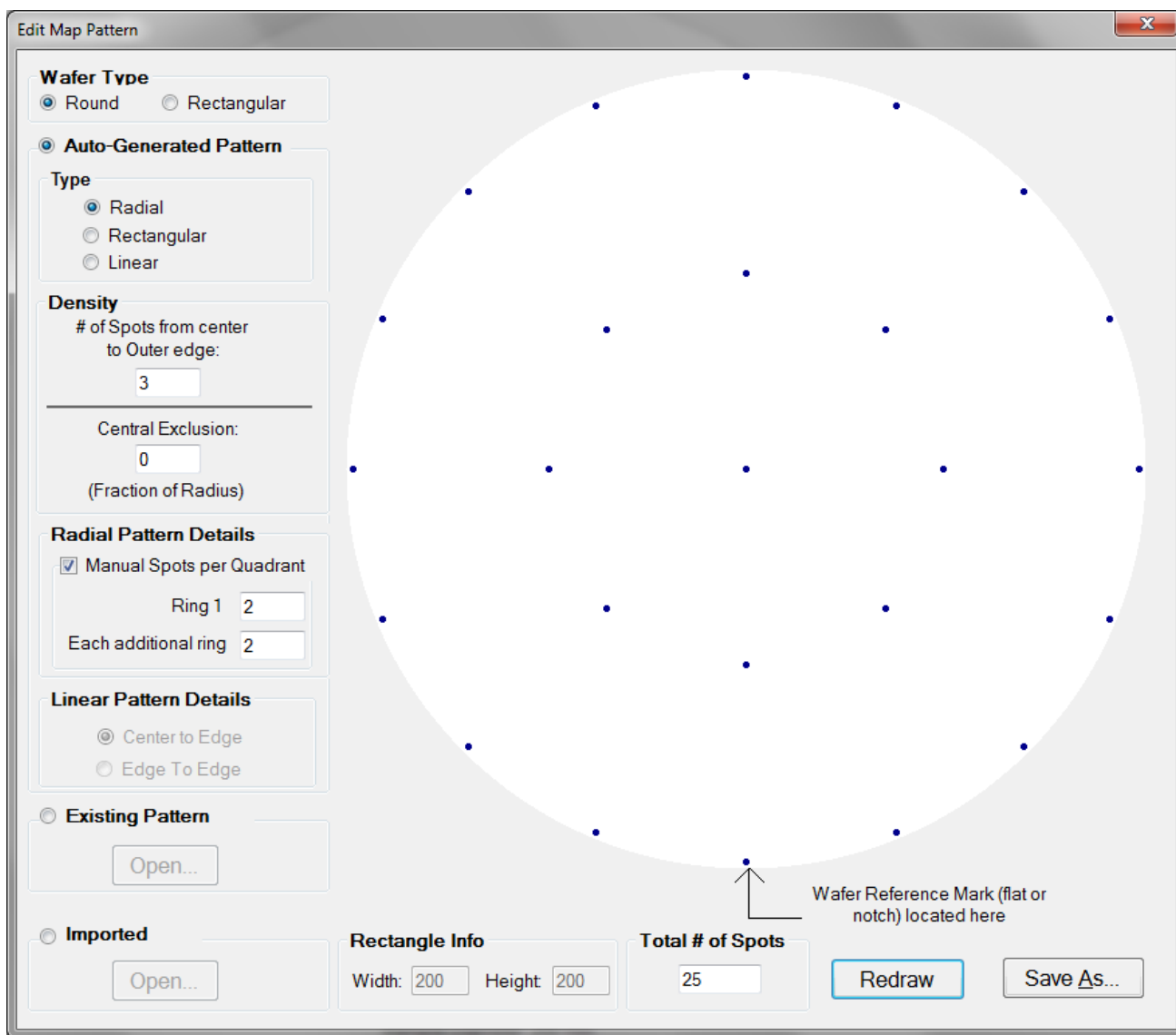


A new material may be entered into the material library manually if refractive index (n) and extinction coefficient (k) are known as a function of wavelength for the new material.

To create a new material file:

1. Select **Edit > Material Library...** menu item. The **Edit Material** dialog box will appear.
2. Click **New...** to create a new material.
3. Select the type of material you are ready to create (Dielectric, Photoresist, Semiconductor, Metal, or Other).
4. Optimize the functionality of the file by entering index values over the entire wavelength range of the system. The wavelength unit is nanometers. Enter index information every 20 to 50 nm, depending on the complexity of the data. In areas where n or k is quickly changing, more densely spaced points should be entered.
5. Alternatively, select the **Model > Custom** radio button and click the **Details** button. A **Custom Model Information** dialog box will appear. Select the appropriate model. Enter in the known coefficients and click **OK**. Cauchy coefficients are displayed in microns. If they are entered in Å, FILMapper will automatically detect this and convert them to microns.
6. Click the save button to save the material. You will be asked for a filename, and you may select one of two file types:
 - *.fitnk: Creates a unified file with both n and k information. Compatible with FILMapper 6 and beyond.
 - *.nnn: Creates a *.nnn file and, if there is k in the material, a *.kkk file to contain material data. For files with both n and k , the two files must have the same filename, for example xmaterial.nnn and xmaterial.kkk, in order for FILMapper to properly identify them. Compatible with all versions of FILMapper.

Map Pattern...(Wafer Map tab only)



The **Edit Map Pattern** dialog allows the user to specify the measurement pattern on the wafer. Patterns can be generated automatically through the dialog, or pre-existing patterns can be opened or imported for review.

When generating patterns automatically, the user must first determine if the wafer shape is round or rectangular under the **Wafer Type** option. The pattern type specifies the pattern geometry within the wafer shape. With **Round** selected, the user can enter the expected wafer diameter into the **Round Info** text box at the bottom of the dialog window. If rectangular is selected, the **Rectangle Info** will allow the input of both height and width data of the sample. All measurements are assumed to be in millimeters. FILMapper is able to automatically scale the wafer map to match other wafer sizes if a different wafer size is input during recipe creation in the [Edit Recipe > Wafer Map](#) dialog.

The pattern density and central exclusion features specify the exact distribution of the measurement points on the wafer. A greater density leads to an increased number of measurement spots, and can only be increased in whole numbers. **Central Exclusion** can be used when the user doesn't want a point in the exact center of the wafer. The exclusion must be <1 in order to function properly. The **Radial Pattern Details** options are only enabled when the type is set to **Radial**. Enabling the Manual Spots per Quadrant option will allow the user to modify the number of measurement spots even further by increasing the number of spots per each concentric ring.

Rectangular patterns allow the user to modify spot density, or with the addition **Fixed** option allows the user to manually enter the number of spots per each row and column.

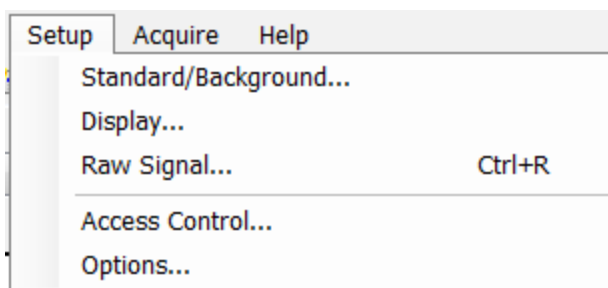
Linear patterns by default are set to measure from **Center to Edge**, but can be set to **Edge to Edge** using the **Linear Pattern Details** options.

An updated version of the map pattern can be displayed by clicking **Redraw** after changing any of the above values. **Save as** will save the new map pattern in the FILMapper\Patterns\Custom folder under a user determined name.

If the x-y coordinates for a specific pattern are known, the FILMapper software can recognize a text file of these coordinates. See [Editing Map Files Using Excel](#) for more details on creating custom maps.

All custom patterns must be saved in FILMapper\Patterns\Custom folder. To select the new pattern in the **Edit Recipe > Wafer Map** tab, select the **Custom Coordinate System** and the name of the pattern from the drop-down box.

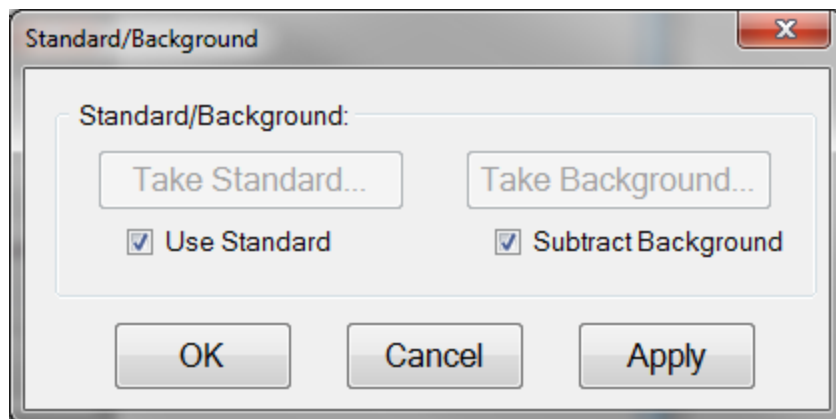
1.6.3 Setup Menu



This menu contains the settings for manually obtaining the [Standard/Background](#) information, [Display](#) options, and the [Raw Signal](#) dialog. This is also where user access can be set through the [Access Control](#) option, as well as modifying some system [Options](#).

Standard/Background

This control is used when manually taking and enabling/disabling the **Reflectance Standard** and **Background** compensation.

**Take Standard**

This button allows the reflectance standard portion of the baseline measurement to be taken without having to re-take the background measurement.

Take Background

This button allows the background portion of the baseline measurement to be taken without having to re-take the reference measurement.

Use Standard

This checkbox allows the reflectance standard portion of the baseline correction to be enabled or disabled. This box is only available if a baseline has already been completed.

Subtract Background

This checkbox allows the background subtraction portion of the baseline correction to be enabled or disabled. This box is only available if a baseline has already been completed.

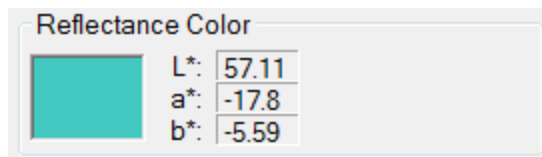
Display

Display

✕

Color Measurement Settings: Color Space

The color of a spectrum can be displayed and quantified on the main screen if a color space coordinate system is selected.



When a **Color Space** is selected, the color of the spectrum and the coordinates appear on the **Measure Tab**.

Color Measurement Settings: Observer

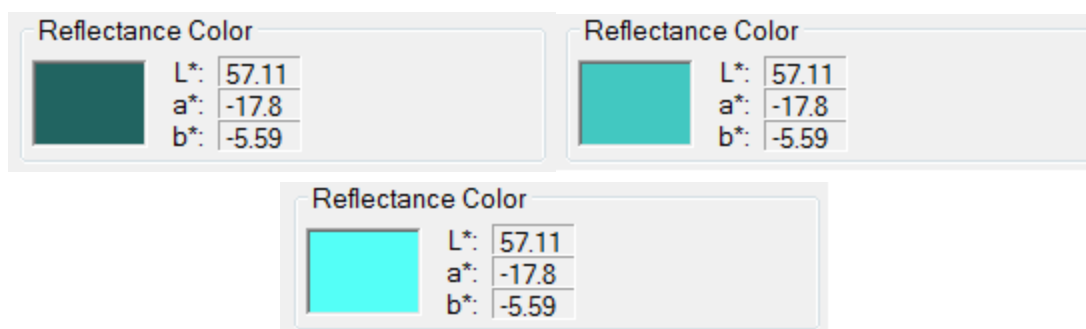
When a specific color space is chosen for display, this option allows the user to choose between the CIE 1931 2 degree observer and the CIE 1964 10 degree observer. Note that this variable is associated with the CIE eye-response convention (see, for example, http://en.wikipedia.org/wiki/CIE_1931_color_space) and is unrelated to the illumination or collection angle of the measurement.

Color Measurement Settings: Illuminant

This setting refers to the [standard illuminant](#) being used by the software to help determine the results of the color analysis.

Color Measurement Settings: Fixed Luminance

The user can fix the luminance of the displayed color. Since antireflective coatings, for example, are inherently transmitting, the spectra have very little luminance and the coating color may appear black on the screen. Adjusting the luminance does not affect the color space coordinate results.



Spectrum colors of the same spectrum with fixed luminance of 10%, 40%, and 70%, respectively.

Color Measurement Settings: Restrict Wavelength

Restrict the wavelength range analyzed when performing color analysis. When disabled the analysis defaults to

Number of Spectra

This sets the maximum number of spectra (up to 10) displayed simultaneously on the main FILMapper screen. If the maximum number of spectra is reduced to fewer than the number already on the screen, the most recently selected spectra will remain.

You may also use the **Show Dual Spectrum Graphs** option to display two measurement graphs concurrently. The data will remain the same across both graphs (spectra and modeled fit), but you can set the graph options for both windows independently. This can be used to focus on a specific area of interest on a spectra while still seeing the effects on the dataset as a whole.

Spectra Transformation

For spectra with both reflectance and transmittance information present, you can have the software display them as separate spectra (none), added together (sum), or the absorbance (1-R-T).

Graph Options

The background of the graph can be set to white or black using this option, as well as allowing the software to auto-position the legend box to avoid or minimize overlap with the displayed spectra.

Measurement Results: Significant Digits

The user can select the number of significant figures, from 1 to 7, that the results are displayed in. For example, with the units set to *Angstroms* and 4 significant digits, The software would report a thickness of 7213 Å. If significant digits is switched to 3, it will instead display the thickness as 7210 Å.

Displayed Controls

These checkboxes are used to determine which controls are shown on the right hand side of the FILMapper window. Some options may not be available based on current system configuration.

Access Control

FILMapper incorporates password protection to limit access to the measurement software and settings. When the software is initially installed access control is turned off. The software will automatically boot up with *Engineer* level access that enables access to all features of the program except turning on and off access control and adding and deleting users.

Turning on access control requires Supervisor level access. The software is delivered with one user, a supervisor, in the list of authorized users as shown below:

UserID: filmsuper

Password: filmetricsfff

To turn on access control log in as filmsuper using the password shown above. The **Activate Access Control** checkbox should be selected enabling access control functions. User ID and Password are case-sensitive.

To add an operator level user, select operator from the **Access Level** list box then type a user name and an initial password for that user. Then click the **Add User** button. To add an engineer or a supervisor user follow the same procedure, but first pick the appropriate access level from the list box before pressing the **Add User** button.

To delete a user, enter the **UserID** and press the **Delete User** button.

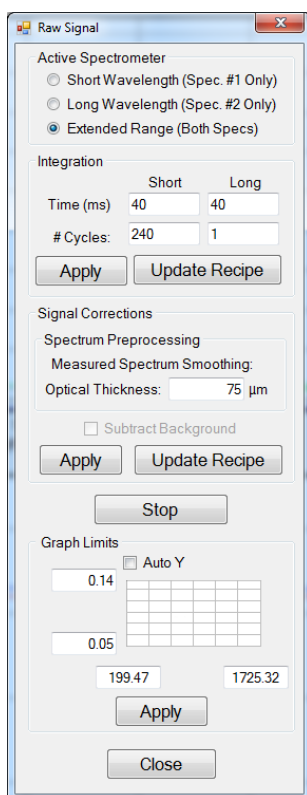
Operator and Engineer level users can change their passwords when they are logged in by entering their password into the password box and pressing the change button. Supervisor-level users can change their password or the password of any other user by selecting the appropriate access level, entering the appropriate **UserID** and the new password and pressing **Add User**. If the program finds that a user already exists, it will delete the old entry for that user and create a new entry.

We recommend that you create a new supervisor level user and delete the filmsuper user for maximum security. If all supervisor level users forget their passwords, it will be necessary to re-install the software and add all the users again.

Raw Signal

Raw Signal

The **Raw Signal** dialog box allows the user to plot the raw (no baseline corrections applied) spectrometer signal on the main graph. This is useful when adjusting the focus or when setting integration times manually.



Active Spectrometer

For systems with multiple spectrometers (EXR and UVX) these radio buttons allow you to select between collecting data from the short wavelength, long wavelength, or both spectrometers. Note that the software will automatically adjust the x-axis of the graph to match maximum wavelength range the selected spectrometer configuration.

Integration

The user can set the integration time and the number of integration cycles for the spectrometer. Increasing cycles can be used to help smooth the data being returned to FILMapper. Clicking **Apply** will show the changes in the main graph window. Clicking **Update Recipe** transfers the listed integration time and cycles to the current recipe.

Signal Corrections.

Spectrum Preprocessing allows the user to apply a smoothing function to the displayed spectra. See [Editing Film Recipes > Data Selection](#) for more details.

Subtract Background can be used to remove the inherent background signal from the displayed raw signal spectrum.

Start/Stop

This button starts/stops the acquisition of the spectrometer signal.

Graph Limits

This allows the user to either manually set or autoscale the graph limits. Click **Apply** after any changes to display them on the main FILMapper window.

Options

The **Options** menu allows the user to enable, disable, or modify several different settings within FILMapper.

[General Settings](#)

[Wafer Map](#)

[Data Recording](#)

[Calibration](#)

General Settings

The **General Settings** tab is used to enable, disable, and modify various options in the software.

Save Screen: Include Menu Bar

Hide or show the menu bar when using *Save Screen to File*.

Spectra on Graph: Confirm before delete

Enable or disable whether the software displays a warning before clearing all spectra on the screen when the *Clear Graph* button is pressed.

Automatically increase max. number of Spectra on Graph

Enable or disable automatically increasing the number of spectra displayed on the graph when opening multiple saved spectra.

Confirm before increasing

You can also set whether to show a confirmation message before increasing the number of spectra.

Printing: Active Curve only

Toggle whether the software prints out all currently loaded spectra, or only the active curve when using the *Print* feature.

History: Confirm before delete

Enable or disable whether the warning dialog before you delete entries in the history file.

Edit Columns...

Open a dialog that allows you to control which columns are visible in the [History](#) tab.

Prompt for Baseline reminder

Reminder Interval (0-540) hours

Enable or disable the baseline reminder feature, and if enabled to set the reminder interval.

Selected Camera:

Enable any connected SampleCams by selecting their serial number from the dropdown list. Disable the camera by selecting *None*.

Warn user if automatically stopping video

Enable or disable whether the software warns you if an error causes the camera to stop.

Automatically reinitialize camera on error

Click to enable automatic camera reinitialization should an error occur. If you have a SampleCam it is generally suggested that you keep this feature enabled.

Reflectance Standard Signal Thresholds

Warn if less than % of highest recorded intensity

Warn if greater than % of previous measurement

Set your *Reflectance Standard Signal Threshold* values. These determine at what percentage of the initial signal intensity the software will display a warning during the [Baseline](#) process. This feature is used to track lamp health, proper baseline procedure, and other parameters.

Uniform Spectrum Data Point Spacing

Standard Spacing Fine Spacing

Enable or disable the *Uniform Spectra Data Point Spacing* function. When enabled, saved spectra will have their values set to a multiple of 1, 2 or 5. *Standard Spacing* sets the spacing equal or greater than the smallest interval in the data, while *Fine Spacing* sets the spacing to shorter than the smallest interval.

Share Settings with all users

For systems with multiple user accounts, enable or disable sharing settings across all users. A folder to store the settings file may be selected.

Share Settings with selected users

For systems with multiple user accounts, enable or disable sharing settings across any users who have selected this option. A folder to store the settings file may be selected. This option is only available if *Share Settings with all users* isn't enabled.

Custom Recipes Path:

This feature allows the user to select a different location for their *Recipes* folder, for example to a shared network drive. This can be useful for syncing recipes across multiple instruments in varying locations.

Custom Material Path:

Selecting **Reset** will instruct the software to look in the default location for the *Recipe* folder.

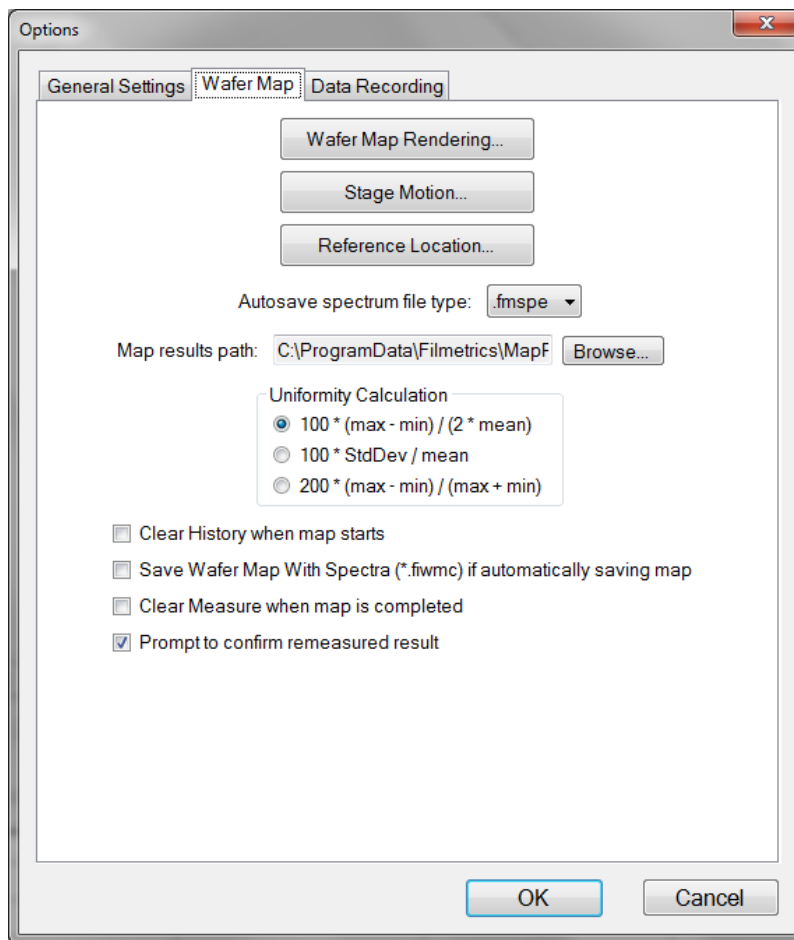
This feature is similar to the one above, only it allows you to choose a different location for your *Materials* folder.

Display disconnect OK reminder at shutdown

Enable or disable whether the software prompts you when it is ok to disconnect the instrument at software shutdown.

Click to restore all settings to their default values.

Map



The **Map** tab allows the user to select the various options related to mapping process. **Wafer Map Rendering** allows the user to choose between either a full **Color** map, or a **Luminance** map which varies from white to dark blue. Users can also set whether or not to display invalid points, whether to use a linear interpolation between points, and what size font the results display as on the map.

Stage Motion allows the user to enable high speed motion controls, for faster mapping when the vacuum is in use. You can also set the speed of the stage when the motion buttons are used.

Reference Location allows the user to choose where the system should look for the built-in reflectance reference. The default setting is automatic (mechanical 0,0), though a custom location can be defined. Note that this value is unaffected by the [Offset Map Origin](#) feature in the recipe.

Focus Height Calibration can be used to manually re-home the z-motion of the system, and also to set an offset for focus height.

Stage Center Calibration is used to ensure that the sample is fully centered on the stage, and is most important when working with patterned samples. Instructions on how to use the function are included in the software.

When [Automatic Data Saving](#) is enabled under the [Edit Recipe > Wafer Map](#) tab, the options here are used to determine in what format the spectra are saved, and where on the computer they are saved.

Uniformity Calculation allows the user to determine the equation used to calculate the uniformity result in the wafer map.

The final four options allow the user to automatically clear the history whenever a new map is started, and if the option is enabled in the [recipe](#) to save map files as the .fiwmc file type. The user may also tell the system to automatically clear any spectra from the [Measure](#) tab when maps are completed. Finally, the user may select whether to be prompted before reanalyzing data under the **Map** tab.

Data Recording

The **Data Recording** tab contains controls for the various methods by which FILMapper may automatically save collected data.

Automatically append results to file

Data File:

Save once per spectrum

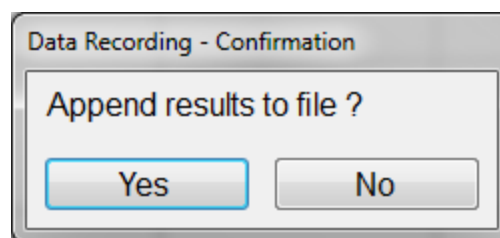
Confirm before saving

Enabling *Automatically append results to file* will instruct the software to create an excel file at a specified location in which a running tally of measured results are kept.

This feature is different from the [History](#) tab in that it only records results, not the spectra files as well. It does not however have an upper limit on the number of spectra that can be recorded.

Enabling *Save once per spectrum* will only append results when the **Measure** button is pressed or a saved spectra is opened in the software. Any changes in the recipe applied to existing spectra will not be recorded. When this feature is disabled, any time a spectra is analyzed the result is entered into the file.

When *Confirm before saving* is turned on, the software will provide a prompt before appending data to the excel file.



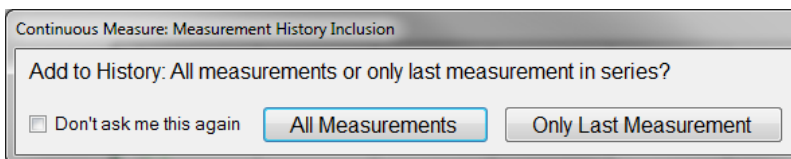
Continuous Measure: Measurement History Inclusion controls which spectra are included in the **History** tab when the [Acquire > Measure Continuously](#) feature is used.

Continuous Measure: Measurement History Inclusion

Prompt user to select History inclusion mode

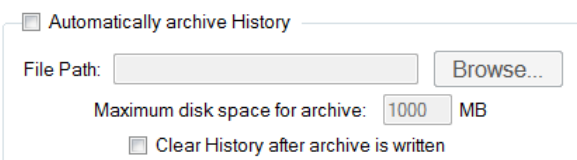
Add all measurements to History

If the software is set to *Prompt user to select History inclusion mode*, a dialog will pop up prior to beginning the continuous measure asking the user whether to save all measurements while measuring continuously, or only the last measurement. The only last measurement feature can be useful on less ideal surfaces (rough, non-uniform, etc.) where the user may have to search around the sample surface for a spectrum capable of being analyzed.



Clicking **Don't ask me this again** will disable the prompt, and the user will have to navigate back to this menu to re-enable the feature.

The user can also select between having the software provide a prompt for which data to include in the history file when using **Acquire > Continuous Measure** or to record all measurements to the **History** tab.



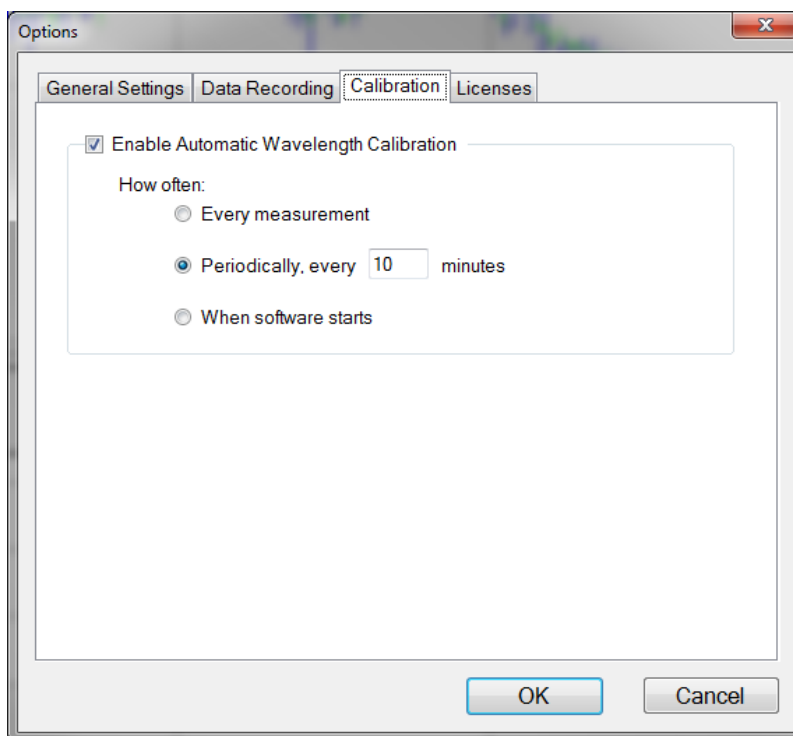
The *Automatically archive History* feature can be used to have the software save a copy of the history file whenever it hits 1000 measurements.

The history files are saved in the following format (YYYY-MM-DD-X) where YYYY is the year, MM is the month, DD is the day, and X is a serialized number based on how many history files have been saved on a given day.

A value can be entered in megabytes for the maximum disk space to be allocated for the saved archives. This will keep the software from using up all available hard disk space if the feature is enabled and then forgotten. Should the software hit the allocated max, it will delete the oldest files in the selected folder until enough space is available for the new history file.

Clicking **Clear History after archive is written** will instruct the software to automatically clear the history results after 1000 measurements have been reached, and then begin counting towards the next group. When it is disabled the history feature will work in the normal mode upon reaching 1000 measurements (newest measurement is added as Meas #1000, Meas #1 is deleted). It will write the next history file upon reaching 1000 measurements again, not each time the *Meas#* counter shows 1000.

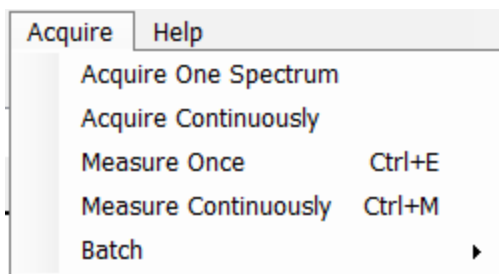
Calibration



The F50 uses an integrated atomic-emission-line light source to update the wavelength calibration of the measurement system's spectrometer. By allowing a system to self-calibrate, automatic wavelength calibration provides significant compensation for calibration drift that could be caused by large temperature changes or by moderate mechanical shock.

The **Wavelength Calibration** tab allows to user to choose how often they would like the system to automatically calibrate the wavelength response of the system. Users can choose to calibrate with every measurement, periodically, or whenever the software boots up. This action is performed in the background and does not require any user input beyond setting the interval.

1.6.4 Acquire Menu



Acquire > Acquire One Spectrum

This function collects a single spectrum and displays it on the screen. No analysis is performed until the recipe is changed or the **Analyze** button is clicked.

Acquire > Acquire Continuously

This feature collects real-time data from the spectrometer. It is useful when searching for a specific location to measure (for example, locating a more uniform area of the sample or one that exhibits interference fringes). Stop continuous data acquisition by selecting **Acquire Continuously** again.

Acquire > Measure Once

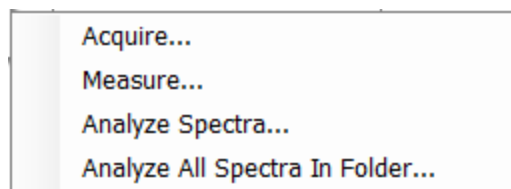
This feature collects a spectrum, analyzes it and displays it on the screen. This is the same as pressing the **Measure** Button.

Acquire > Measure Continuously

This feature collects real-time spectrum data and analyzes it – similar to repeatedly pressing the **Measure** button. A measurement interval time can be set in the recipe using the [Advanced](#) options underneath the [Acquisition Settings](#) tab. Stop continuous data acquisition by selecting **Measure Continuously** again, or by pressing Ctrl+M.

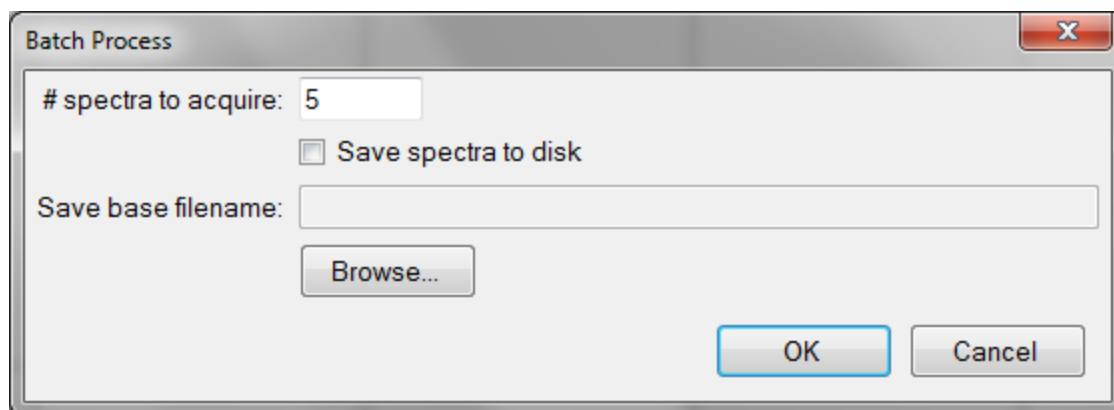
Batch Acquire

The Batch functions allow you to act on groups of spectra, rather than each individual spectrum



Acquire > Batch > Acquire

This option allows you to acquire a pre-selected number of spectra. You can also choose to save the batched spectra as they are acquired.



Acquire > Batch > Measure

This option allows you to acquire and analyze a pre-selected number of spectra. You can also choose to save the batched spectra as they are acquired.

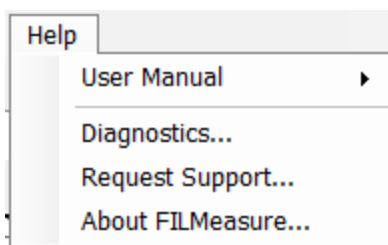
Acquire > Batch > Analyze Spectra

This option allows the user to select multiple spectra for analysis by the current recipe. If there are more spectra to be analyzed than the software is set to [Display](#), the analyzed spectra can easily be retrieved from the [History](#) tab.

Acquire > Batch > Analyze All Spectra in Folder

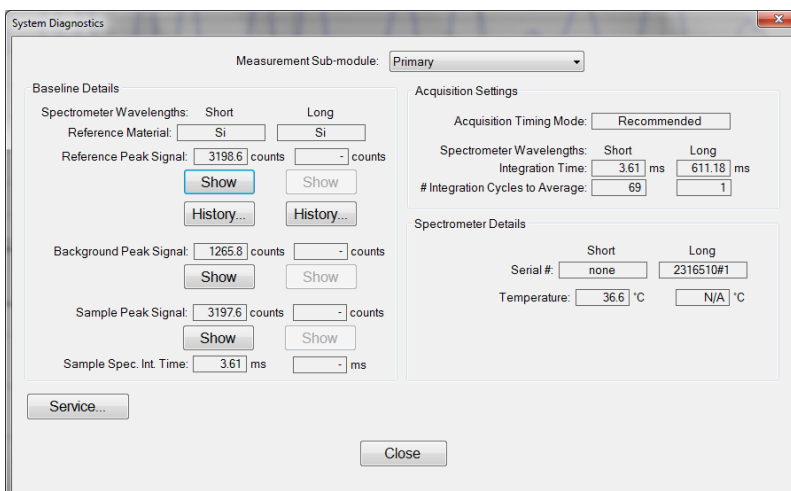
This option will analyze every spectrum in a folder with the currently selected recipe. If there are more spectra to be analyzed than the software is set to [Display](#), the analyzed spectra can easily be retrieved from the [History](#) tab.

1.6.5 Help Menu



Diagnostics

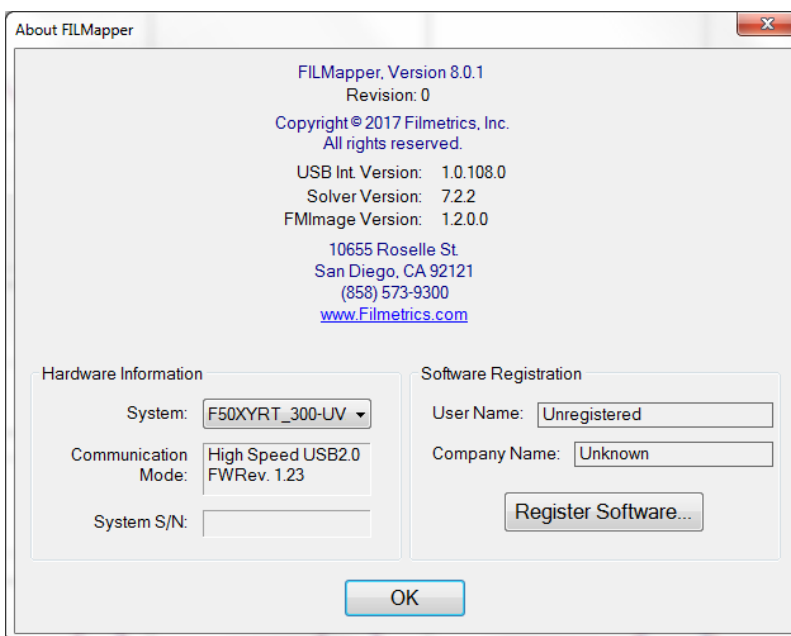
The diagnostics window gives information regarding the data taken during the baseline. Reference and background counts are shown (this is useful to see how much signal the system is getting; good reference signals typically are between 2500-3500 counts).



Help > Diagnostics shows the user information regarding the data taken during the baseline routine.

Help > About FILMapper

Information about the hardware and software versions and the system serial number can be found here. Please have this information available when calling Filmetrics for technical assistance.



Help>About FILMapper... window

1.7 Taking a Baseline

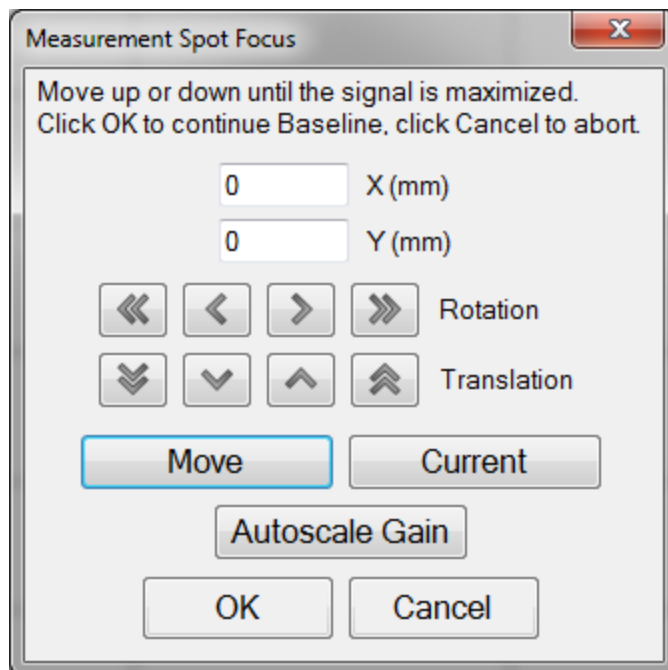
The baseline measurement allows the FILMapper software to take into account the response inherent to the reflectance measurement hardware. It does this by first measuring a supplied sample, then a reflectance standard, and finally taking a “dark” reading. The light source should be allowed to stabilize at least ten minutes before the baseline is taken. When measuring films less than 1000 Å thick, the baseline should be periodically re-taken every 20-30 minutes. For thicker films, a new baseline can be taken less often.

Baseline measurements may be started two ways:

1. Select the **Baseline** button in the [Wafer Map](#) or [Measure Tab](#), which will guide the user through the baseline procedure, or
2. Select [Setup>Standard/Background...](#) from the menu bar in the **Measure Tab** for manual access to the baseline functions.

The first step of the baseline measurement is to take a spectrum from your sample. This done by placing the sample on the stage, and if necessary moving the stage over the sample using the [Go To](#) function. With the sample in place under the light path, you can then press the **Take Sample Reflectance** button. For systems with no z motion, the software will automatically move to the next step of the baseline.

Systems with manual z motion will prompt the user with the **Measurement Spot Focus** dialog (pictured below) and display a continuous raw signal measurement in the main graph window. Click the arrow controls to move the stage, or type in specific coordinates and click **Move**. Turn the z-height micrometer on the stage to adjust focus until signal is maximized. If the [raw signal](#) curve is too low or too high to identify changes in signal, click **Autoscale Gain** to automatically adjust the integration time and better analyze the raw signal spectra. Once the system has been focused, click **OK** to continue.



The next step is to take a spectrum of a reflectance standard. For systems with no z-motion, use the reflectance standard that is closest in height to your sample. This is to account for the fixed focus point, which you can read more about [here](#). For systems with manual z motion, place a reflectance standard of similar reflectance to the test sample on the sample stage. The reflectance standard that is used should be selected from the **Reference Material**: list. For reference materials not in the list, reflectance versus wavelength values may be entered into a comma-delimited text file with the extension “.rrr” (stored in the Material subfolder). Click **Take Reflectance Standard**. Systems with manual z motion will again be prompted with the *Measurement Spot Focus* dialog box.

The background scan will be taken automatically for systems with r-theta stages (F50, F54). On XY stages, place the BG-Microscope in the light path and click **Take Background**.

When thin films (< 2000 Å, approximately) or n and k are being measured, a full wafer reference map will be required, and automatically measured. To determine if full wafer reference data is required, FILMapper checks the active **Recipe** settings. The pattern defined in that recipe will be used for the full wafer reference. If the map pattern, edge exclusion, or wafer diameter is changed, a new full wafer reference will be initiated. The full wafer reference map can be enabled or disabled underneath the [Edit Recipe>Wafer Map](#) tab.

After acquiring a baseline, the instrument is ready to begin making measurements. To verify that the system is working properly, you may select **Acquire>Single Acquire** from the **Measure Tab** menu bar, with the reflectance standard in place. You should see the reflectance spectrum of the reflectance standard.

2. Editing Film Recipes

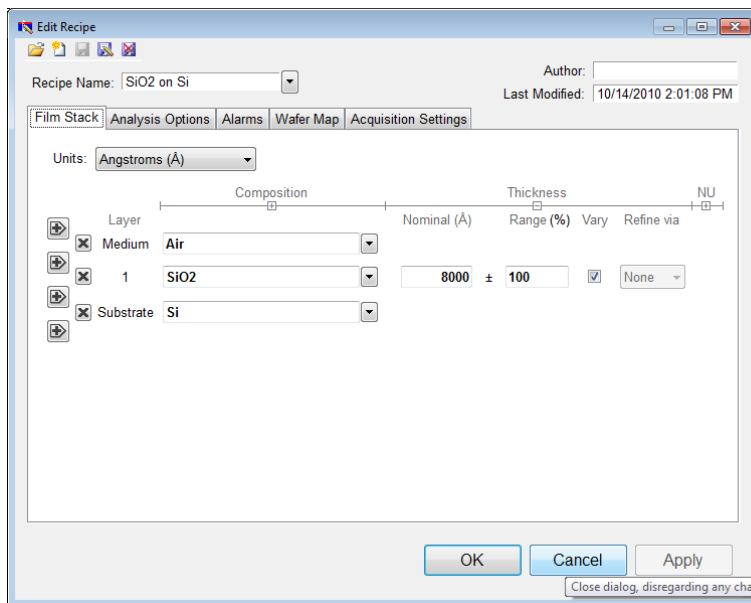
The description of the nominal film structure, as well as the measurement parameters, is specified in the [Edit Recipe](#) dialog box. Hundreds of different film structures and their measurement specifications may be saved.

The **Edit Recipe** dialog box is accessed with the **Edit Recipe...** button on the [Measure Tab](#), or the **Edit...** button on the [Wafer Map Tab](#). The **Edit Recipe** dialog box lists an initial guess at the specifications of the film structure to be measured. These specifications include the number of films in the structure, the layer order of the films in the structure, the specifications of individual films (thickness and index), and the film parameters to be measured.

2.1 Adding, Changing, or Deleting a Structure

When the [Edit Recipe](#) dialog box is opened, it shows the stored specifications of the structure selected from the **Recipe Name:** list, along with any changes made since the recipe was loaded. Changes to the structure selected can be permanently stored by making the desired changes and then clicking on **Save**. Changes can also be stored as a new recipe by clicking on **Save As**. A structure may be deleted (removed from the **Recipe Name:** list) by clicking on the **Delete** button.

2.2 Film Stack



The **Film Stack** tab is used to define the film structure and desired measurement units, as well as the starting guesses and constraints for thickness, n , and k . This is also where you determine your analysis method; [Grid](#), [FFT](#), or **None**, as well as any [Nonuniformity](#) that may be present in the sample. The [+] and [-] below **Composition**, **Thickness** and **Nonuniformity** can be used to expand or hide solving options.

2.2.1 Setting Up a Film Stack

When measuring a layer, the parameters (thickness, n , and k) of the known films (including the incident medium and substrate) must be entered into the proper fields in the [Edit Recipe](#) dialog box, as well as initial guesses for the values to be measured. The refractive index (n) and extinction coefficient (k) values for common materials can be selected from the drop-down menus on the right-hand side of the listed materials, or by left-clicking on the material and using the [Search](#) function. Note that if a generic index is selected, the software will instead prompt for a new index value.

If a material is being measured is not present in the material library there are three possible approaches to complete the recipe:

- a) Choose a material in the library that is similar.
- b) If the material is transparent (an insulator), select “**Enter Refractive Index Value**” from the material list and enter a value for the refractive index (n will automatically be varied by FILMapper to account for dispersion effects, with the entered value being n at 632.8 nm).
- c) Create a new material file using the [Edit > Material Library...](#) dialog box. Enter the refractive index values for n and k as a function of wavelength and save the files so that they may be selected as in the recipe. See [Creating and Editing \$n\$ and \$k\$ Files](#) for more information.

2.2.2 Choosing the Films to be Measured

To measure a film's thickness, mark the check box on the right-hand side of the **Thickness** field under the **Film Stack** tab in the [Edit Recipe](#) dialog box. When no boxes are checked, the theoretical spectrum for the specified layer stack and thicknesses entered in the recipe will be displayed.

As with most measurements, the uncertainty of the measured data increases as the number of simultaneously measured values increases. Thus it is best to provide as much information about the film structure as possible.

2.2.3 Constraints

By setting constraints, the user can limit the possible values of the measured film properties. The constraints are set in conjunction with the values entered in the **Range** dialog box for **Thickness**. For example, if the initial guess of the measured thickness of a film is 100 nm and the thickness constraint is set at 50%, FILMapper will only consider possible thicknesses in the range 50 nm to 150 nm.

Measurement results that are equal or nearly equal to the min or max thickness limit will be marked as invalid, unless the minimum GOF limit is 0 (using the above example, a result of 50 nm would show as invalid). This feature is intended to make sure that the user is alerted to results that may not be accurate as the correct solution is not available in the currently provided range. To clear the invalid result, simply use a larger constraint or change the nominal thickness value.

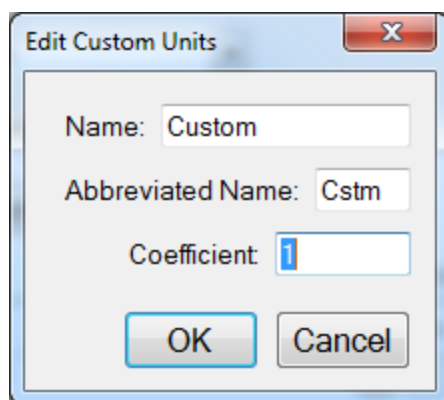
The constraints for n and k are set using the n and k dialog boxes under **Composition**. These boxes are only visible when the **Thickness** or **Composition** options are expanded.

You can select between constraining by a percent of the thickness guess, or by absolute thickness units by clicking on the % or measurement unit above the constraints dialog box. Constraining the measurement range can speed up analysis and can also help exclude non-physical solutions.

2.2.4 Units

The **Units** drop down menu allows the user to easily switch between their desired measurement unit, ranging from angstroms up to inches. The software will automatically convert between units when a different unit is selected (e.g. 1 micron will be converted to 1000 nm).

The **Custom Unit** function allows you to create your own custom unit for measurements if the metric you'd like isn't already available in the drop-down list.



The **Edit Custom Units** dialog box.

To determine the correct coefficient to use, you must first know the relationship between your unit and nanometers. For example, if your units are mg/ft² and it's been determined that 1 mg/ft² works out to a film thickness of 150 nm, then you would calculate your coefficient as follows, where X is the coefficient.

$$1 \frac{mg}{ft^2} * X \frac{nm}{mg/ft^2} = 150nm$$

$$X_{nm} = \frac{150nm}{1nm}$$

$$X = 150$$

Custom units can be saved as part of the **Recipe** file, and only one custom unit can be saved per recipe.

2.2.5 Composition

When measuring the n and k of a film, the general dependence of these values upon wavelength must be specified. This dependence is determined by the type of material to be measured. For example, insulators, semiconductors, and metals all have a unique type of n and k wavelength dependence.

Dozens of models for these different dependencies have been proposed and used over the years. FILMapper uses a few of the most versatile and accepted models. For insulators the Cauchy model is used, for semiconductors either the Amorphous or Bridge-Lorentzian model, and for metals the Drude model.

There are also a number of special-purpose models for specific applications. These models and starting coefficients values are selected automatically when a material is chosen from the **Material** lists in the [Edit Recipe](#) dialog box. Other models may also be specified by selecting them from the **nk Model** drop-down menu under the **Composition** tab which is accessed by right clicking on the **Meas** checkbox when solving for optical constants is enabled.

2.2.6 Grid Search for Thickness

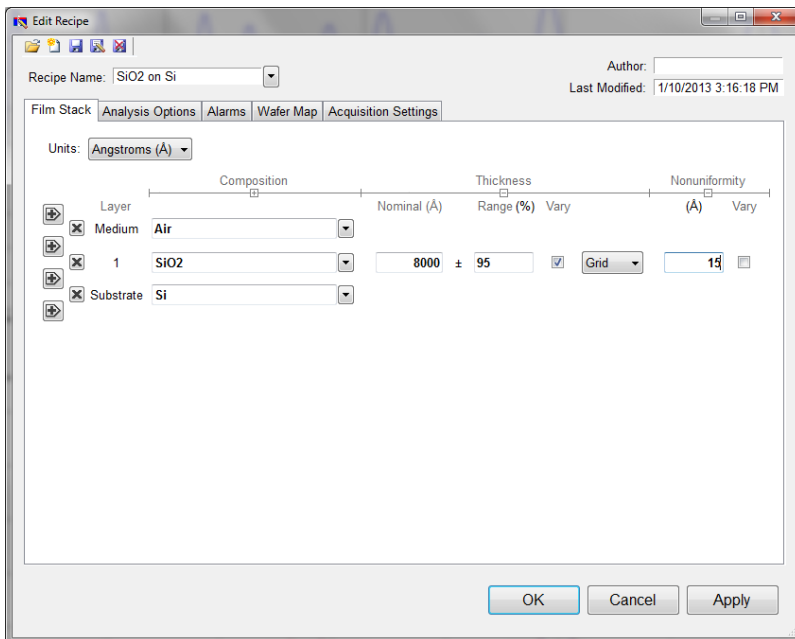
There are a number of methods that FILMapper can use to determine thickness. Each is a different trade-off between speed, accuracy, and robustness (i.e., the ability to find the best solution among many that are nearly as good). Because thickness can vary over many orders of magnitude and many near-solutions may exist, it is often best to use a very robust method to get close to the best solution, and then let a more accurate method take over.

One very robust method is the **Grid** method, which can be activated by selecting the **Grid** option in the **Refine via** drop-down menu. The **Grid** method searches the entire allowed thickness range (as defined by the initial guess and the constraints) to find the best initial thickness. However, on some very complex multilayer spectra, it is possible for the Grid method to give the wrong answer. In such cases it is best to use the [Fourier Transform\(FFT\)](#) method to determine initial thicknesses, or to provide them manually.

2.2.7 Fourier Search for Thickness

The **FFT** option in the **Refine via** drop-down list is an alternative option to let FILMapper choose an initial thickness for analysis. The Fourier Transform method analyzes the oscillations present in the spectrum and determines the film thicknesses based on the periodicity of those oscillations. It is generally somewhat less robust than the [Grid](#) method, but is better at finding the correct thickness in cases where the shape of the initial theoretical spectrum is different than the measured data (i.e., the reflectance spectrum is non-ideal in some way) or occasionally in cases where there is more than one film thickness is being measured.

2.2.8 Nonuniformity

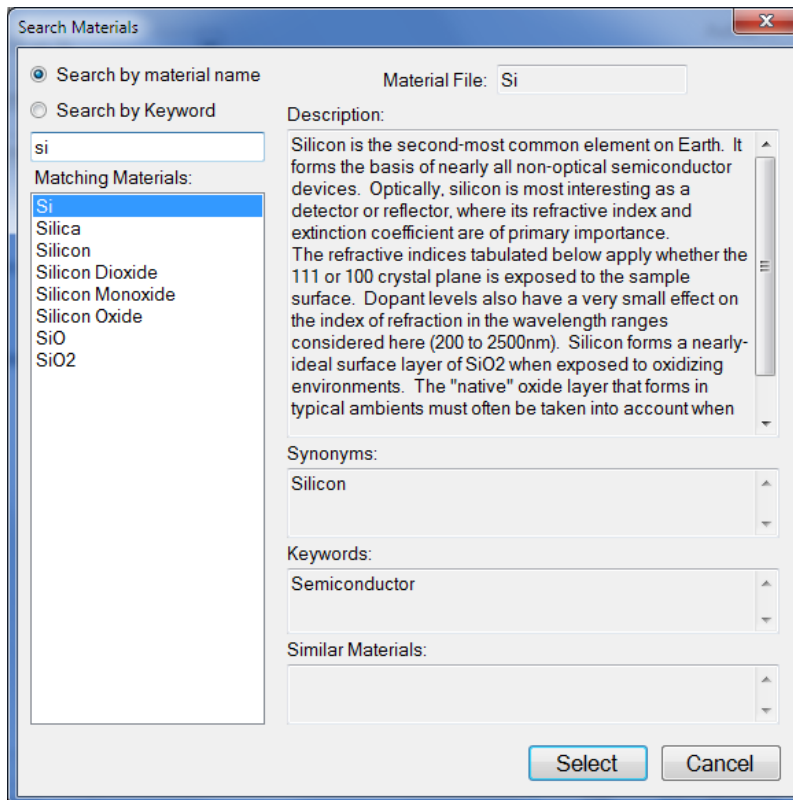


The **Edit Recipe** > **Film Stack** tab with the **Nonuniformity** option expanded.

Selecting this option enables modeling of thickness nonuniformity within the measurement spot. An initial guess for **Nonuniformity** must first be made, and then solving can be enabled or disabled by toggling the **Vary** box. If solving is not enabled, the software will assume the value provided for nonuniformity.

Note: Solving for nonuniformity can greatly increase solving time.

2.2.9 Search



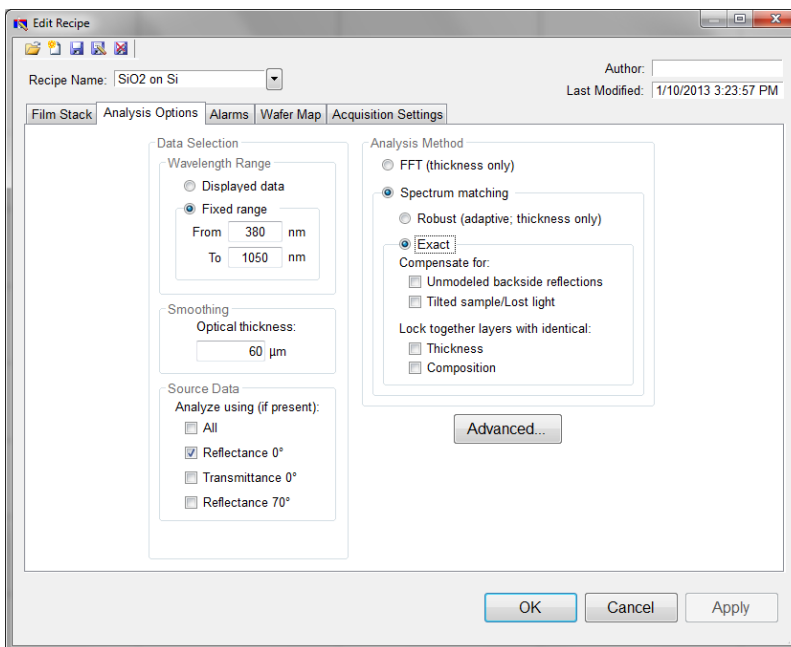
The **Search Materials** dialog box is accessible by left-clicking on a material name in the [Edit Recipe > Film Stack](#) tab, or by selecting **Search...** from the material selection drop-down list.

Note: When clicking on a generic index file, the software will instead provide you with a dialog to enter a new index value.

This feature allows the user to search for materials by using either the material name, or a keyword for a certain class of materials. The search function will also show a brief **Description** of the material selected, as well as any **Synonyms** or **Keywords** related to the material file. When files have a **Synonym**, that means they are referencing the same material file under different names. For example, if Silicon is selected the file that will be shown in the **Film Stack** is Si, not Silicon, as that is the file both names are referencing. The **Similar Materials** box will list any materials that may have similar optical properties.

2.3 Analysis Options

Correct setting of the following options will help ensure accurate measurements. Many of the options are set automatically when film information is supplied in the [Edit Recipe](#) dialog box, and all of them can be saved so that subsequent measurements can be made as quickly and easily as possible. If [Robust \(Adaptive; Thickness Only\)](#) or [FFT \(Thickness Only\)](#) is checked, only the [Data Selection](#) settings will be accessible.



2.3.1 Data Selection

Wavelength Range

This sets the wavelength range that is to be analyzed. It may be set as either the entire range displayed on the graph or a fixed range as defined by the user. Wavelength range may also be changed by clicking and dragging the ends of the gray bar near the bottom of the graph area in the main FILMapper window. Moving the bar will cause the software to reanalyze the data in the newly selected wavelength range.

Smoothing

This function performs wavelength-dependent boxcar averaging on the measured spectra. This can improve signal-to-noise levels and can filter out oscillations that correspond to optical thicknesses (defined as thickness * refractive index) equal or greater than the specified value. This value should be lowered to increase smoothing, and raised to decrease smoothing. To eliminate smoothing, enter a very high value (1000 μm , for example).

Source Data

If more than one data set is present, this option tells the software whether to analyze the 0 degree reflectance data, 0 degree transmittance data, 70 degree reflectance data, or some combination of the three.

Note: While every Filmetrics system is capable of opening and analyzing spectra with 70 degree reflectance data, only the [F10-RTA](#) is capable of collecting this data.

2.3.2 Enable FFT (Thickness Only)

The **FFT (thickness only)** solver is one of three analysis methods available in the FILMapper software.

This solver is best suited for films greater than 250 nm thick, as well as multi-layered films. It is also an effective option when the index of refraction of the film isn't well known. While this feature is selected there will be fewer options under the [Analysis Options](#) tab. You cannot solve for index, roughness, or nonuniformity with the **FFT (thickness only)** solver enabled. More information on the solver can be found [here](#).

2.3.3 Enable Robust (Adaptive; Thickness Only)

The **Robust (adaptive; thickness only)** solver is the second of three analysis methods available within FILMapper. It is best suited for measuring the thickness of single-layer films greater than 150 nm thick.

This method can oftentimes successfully measure films when the data is affected by non-ideal properties, such as thickness nonuniformity, grading, and birefringence. Much like the **FFT (thickness only)** solver, enabling **Robust (adaptive; thickness only)** will limit the options available in the [Analysis Options](#) tab. You also cannot solve for roughness, nonuniformity or index with the **Robust (adaptive; thickness only)** solver enabled.

2.3.4 Exact Spectrum Matching

The **Exact Spectrum Matching** is the third of three analysis methods available in FILMapper. This solver can be used to measure thickness, thickness nonuniformity, and roughness of single and multilayer films, and can additionally solve for index.

Unmodeled Backside Reflections

When measuring films on transparent substrates, reflectance off of the backside of the substrate may occur. Selecting **Compensate for: Unmodeled backside reflections** allows the software to shift the intensity of the calculated reflectance curve to account for the additional light. This feature should not be used when measuring very thin films (< 100 nm).

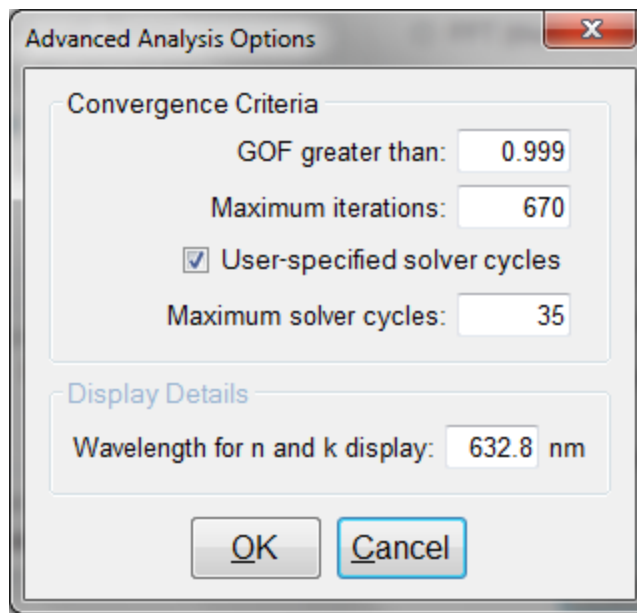
Tilted Sample/Lost Light

Samples with non-coplanar surfaces scatter some of the light away from the collection optics. This option automatically compensates for the light lost due to nonplanarity.

Lock Identical Layers

Samples comprised of repeating layers can be more accurately measured by activating this option. By activating these options, all properties of any layers that initially have the same material or thickness are locked together.

2.3.5 Analysis Options: Advanced



Advanced Analysis Options for Spectrum Matching.

Convergence Criteria

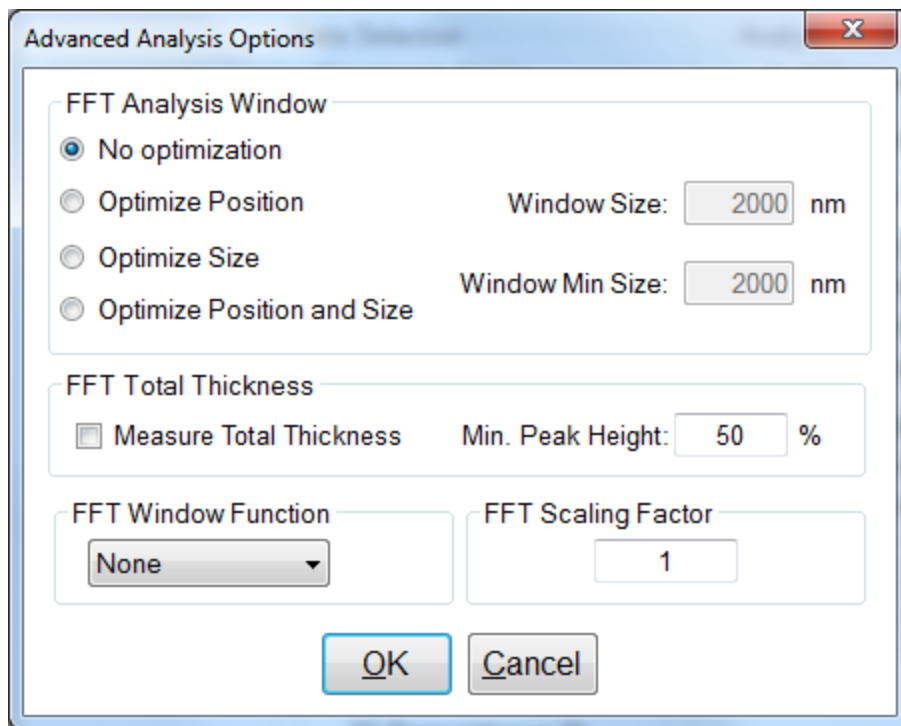
This sets the minimum **GOF** between the measured and calculated spectra that is attained before the measurement routines consider the solution final. In most cases a value of 0.999 is sufficient. For cases where the desired **GOF** is not attainable, the value in the **Maximum Iterations** field limits the number of iterations performed by the analysis routine.

Solver Cycles

This option will enable multiple solver cycles, with the number of cycles being defined by the number entered in the text box. When using this option, the software will run through the model for a solution once, and then try again starting from the solution previously found. This can help find the best solution amongst a number of near-best solutions, which can be the case when solving for a large number of parameters (several thicknesses and/or refractive index). A greater number of cycles will lead to a longer solving time.

Display Details

This feature controls the wavelength at which n and k are displayed in the **Measurement Details** portion of the main screen. These values are only displayed if solving for n or k is selected in the **Film Stack** tab.



Advanced Analysis Options for FFT Analysis.

FFT Analysis Window

When the FFT solver is selected, the advanced options give you access to various settings to help optimize analysis performance. When **Optimize Position** is selected, the solver will check for the best possible GOF value in different areas across the spectrum in a wavelength range defined by the entered window size. For example, if a window size of 200 nm is selected, the solver will look at six different 200 nm sections of the spectrum, and then select the range that provides the best GOF.

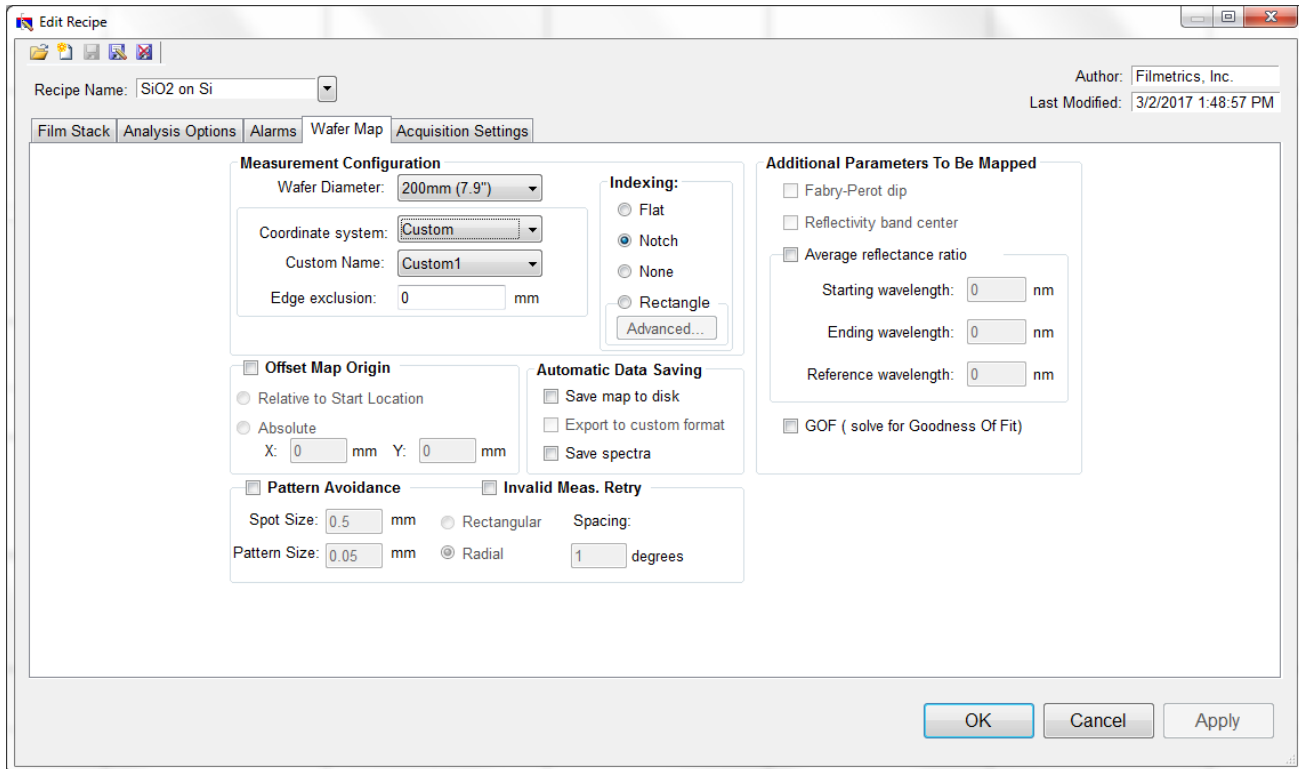
If **Optimize Size** is selected, the solver will instead begin with a minimum window size as defined by the user. It will then start at the center of the analysis range, and then extend equally in both directions six times to find the best GOF. When **Optimize Position and Size** is selected, the software does both functions, resulting in measuring thirty-one different combinations of location and analysis range.

The **FFT Total Thickness** is used when only the total thickness of a multi-layer stack is of interest. In these cases the user would define a single layer recipe, and enable the total thickness option. The solver will then perform a special analysis and look for the peak that corresponds with the thickest measured value within the current parameters of the recipe, checked against a minimum peak height. This value is used to insure that only a true thickness peak, and not a side lobe of another peak is identified as the correct result.

The **FFT Window Function** allows you to select between four different window functions to apply to the FFT analysis. By default this feature will be disabled (*None*). Descriptions of different mathematical functions can be found [here](#)

The **FFT Scaling Factor** is used for non-ideal samples, where there may be an alignment in the x-axis of the FFT plot, but not the y-axis. This may occur for many reasons such as a very rough, non-uniform, or in some other way non-ideal film. By adjusting the scaling factor, you can increase or decrease the amplitude of the modelled fit to improve your GOF values.

2.4 Map



This wafer map tab allows the user to specify various settings in relation to how the map is generated. This includes the size and type of wafer to be analyzed, the configuration of the measurement spots, which parameters should be mapped, where **AutoFocus** functionality should be used if available, as well as data saving protocols. It also allows the user to define settings for pattern avoidance and accounting for invalid measurement spots. This is also where the preferences for the full wafer reference are set.

2.4.1 Measurement Configuration

Wafer Diameter: Diameter of wafer to be measured – choose from list. When using rectangular patterns, this option will switch to **Width** and **Height**, with text boxes to enter the appropriate values.

Coordinate System: Polar, Rectangular, Linear, or Custom.

Number of Points or Custom Name: Choose from the list the number of points to be measured or select the name of the custom pattern file.

Edge Exclusion: Distance from outermost points to the edge of the wafer.

Indexing: Changes plot on screen to show appropriate index mark. The wafer should be oriented on the stage with the index mark on the edge opposite the mirrors (i.e the top of the wafer in the map results is near the mirror).

Advanced Settings: When using a rectangular map, the advanced rectangular map settings option is enabled for use. This menu allows the user to define the sample origin point in one of five locations; top-left, top-right, center, bottom-left, or bottom-right. **Automatic Alignment** can be used to help find the edges of the sample.

2.4.2 Offset Map Origin

This feature is intended to allow the end user to determine the origin point the system will use for the measurement map. If no option is selected, the software will default to centering all maps around the (0,0) measurement location. Once selected there are two options available:

1. **Relative to Start Location** - Whenever the **Start** button is clicked, the software uses the current (x,y) position as the origin for the map. This position is not saved as part of the recipe.
2. **Absolute** - set a specific (x,y) location as the origin of the map.

2.4.3 Automatic Data Saving

If a filename is entered in the upper right corner of the **Wafer Map View>Map Information** field, then a new folder with that name will appear in the `FILMapper\Map Results` folder. If no name is specified, all saved data will appear in the `Map Results` folder.

Save Results to Disk: Automatically saves the map after completion of measurement. Depending on the settings underneath [Setup>Options>Wafer Map](#), the software will either save the maps as a .fimap or a .fiwmc file.

Save Spectra: Saves the spectrum acquired at each point as a separate file. Each file is saved in measurement order, "0" being the first measurement. File extension is .fmspe by default, but can be set underneath the tab **Setup > Options > Wafer Map**. Each spectrum may be opened in the [Measure Tab](#).

2.4.4 Pattern Avoidance

The pattern avoidance feature enables the system to target areas on a patterned wafer that do not scatter light (i.e. avoid trench areas). If a measurement shows low reflectance, the stage will move to a nearby location where a pad is expected (as defined by the settings described below). This feature should not be selected when measuring blanket wafers.

Spot Size: The size of the measured spot.

Pattern Size: The size of the features to be avoided.

Rectangular, Radial: The pattern layout geometry.

Spacing: The center-to-center separation of elements making up the pattern.

2.4.5 Invalid Measurement Retry

Activating this feature allows the software to try up to four additional measurement locations, within the **Spot Size** specified if the first measurement turns up as invalid. Invalid measurements are defined by the minimum valid GOF in the **Alarms** tab. If a valid measurement is found, the result will be shown on the resulting map. If no valid measurement is found in any location, the spot will be marked invalid. This function is especially helpful when measuring non-uniform samples.

2.4.6 Additional Parameters To Be Mapped

Average Reflectance Ratio: This maps the average reflectance ratio, which is defined as the average reflectance between the **Starting Wavelength** and the **Ending Wavelength**, divided by the reflectance at the specified **Reference Wavelength**. The [Goodness Of Fit](#) can also be included as a parameter to be mapped. For systems with automated z-motion, the focus height can be tracked as well.

2.4.7 GOF (Solve for Goodness of Fit)

Enabling this feature saves [GOF](#) results with the map. To see the GOF map, use the drop down above the *Manual Color Range* box under the [Wafer Map Tab](#).

2.4.8 Full Wafer Reference Mode

This option allows you to choose whether or not to enable *Full Wafer Reference Mode*, or to let the software decide based on the parameters set to be solved for. A full wafer reference is suggested when mapping for optical constants, or very thin films (< 50nm).

2.5 Alarms

Recipe Name: SiO2 on Si

Author:

Last Modified: 1/10/2013 3:23:11 PM

Film Stack | Analysis Options | **Alarms** | Wafer Map | Acquisition Settings

Minimum Valid GOF:

Activate alarms

Thickness Limits (Å)

Layer	Nominal	Min	Max
Medium			
1	<input type="text" value="6000"/>	<input type="text" value="5800"/>	<input type="text" value="6200"/>
Substrate			

OK Cancel Apply

Minimum Valid GOF

Constraining the **Minimum Valid GOF** will exclude measurements where the calculated **GOF** does not reach the specified limit. A warning or **“Invalid”** result will appear if the GOF constraint is not met. Specify 0 to have all solutions reported.

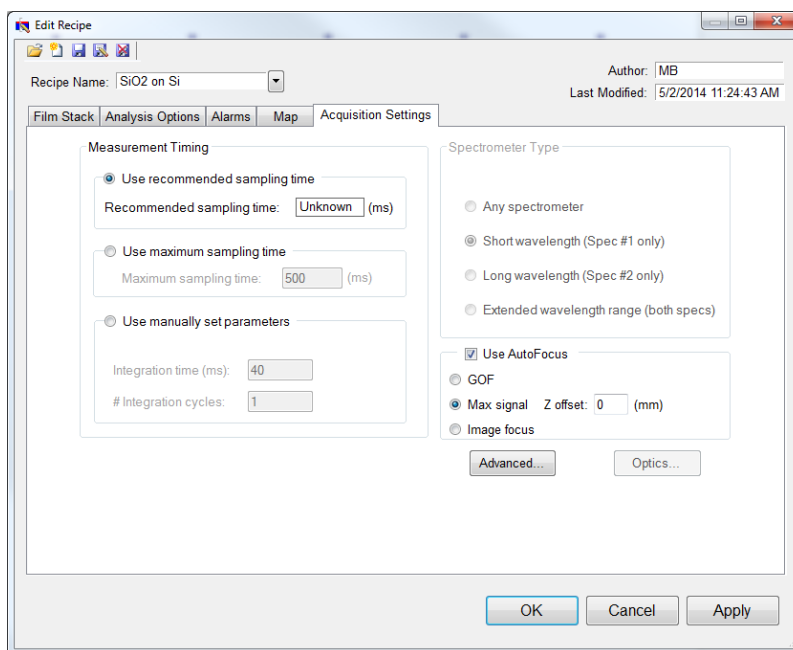
Activate Alarms

When **Activate Alarms** is selected, an alarm will trigger if the measured thickness of the sample is outside the specified **Thickness Limits**. Measurements that fall within the thickness limits will be indicated by a green box surrounding the measurement result in the **Measurement Status** window under the **Measure Tab**. A measurement that falls outside of the selected limits will instead show a red box surrounding the measurement result.

Thickness Limits

Setting the minimum and maximum allowable thickness limits will trigger an alarm if the measured thickness is outside the limits when **Activate Alarms** is selected.

2.6 Acquisition Settings



This menu lets the user control **Measurement Timing**, **Spectrometer Type** (on EXR and UVX systems), **AutoFocus** settings, and **Advanced Acquisition Settings**.

2.6.1 Measurement Timing

Use Recommended Sampling Time

Selecting this option uses the sampling time that has been automatically calculated by the software during the baseline procedure. The displayed value is the total sampling time and not necessarily the integration time. To see the integration time and number of integration cycles go to the [Help > Diagnostics](#) menu.

Use Maximum Sampling Time

Users can set a maximum sampling time by selecting this option. By increasing sampling time the user may see a decrease in signal noise, but at the trade-off of a longer acquisition time. Integration time and cycles will still be determined by the FILMapper software.

Use Manually Set Parameters

Users can set both the integration time per acquisition cycle and the number of integration cycles over which to average. When using this option, the total sampling time is equal to the integration time multiplied by the number of integration cycles.

To set the integration time manually, set the sample on the stage and select [Setup>Raw Signal...](#) If the proper integration time is unknown, an initial value of 40ms is a good starting guess. The vertical scale of the spectrum extends from zero to 4000. Thus, a good working level is when the peak height of the sample being measured, or the reflectance standard, whichever is greater, is 3000-3500 counts. If the maximum signal is too low, increase the integration time. Too large an integration time will result in excessive dark current, so it is sometimes necessary to accept a smaller signal level to limit the dark current.

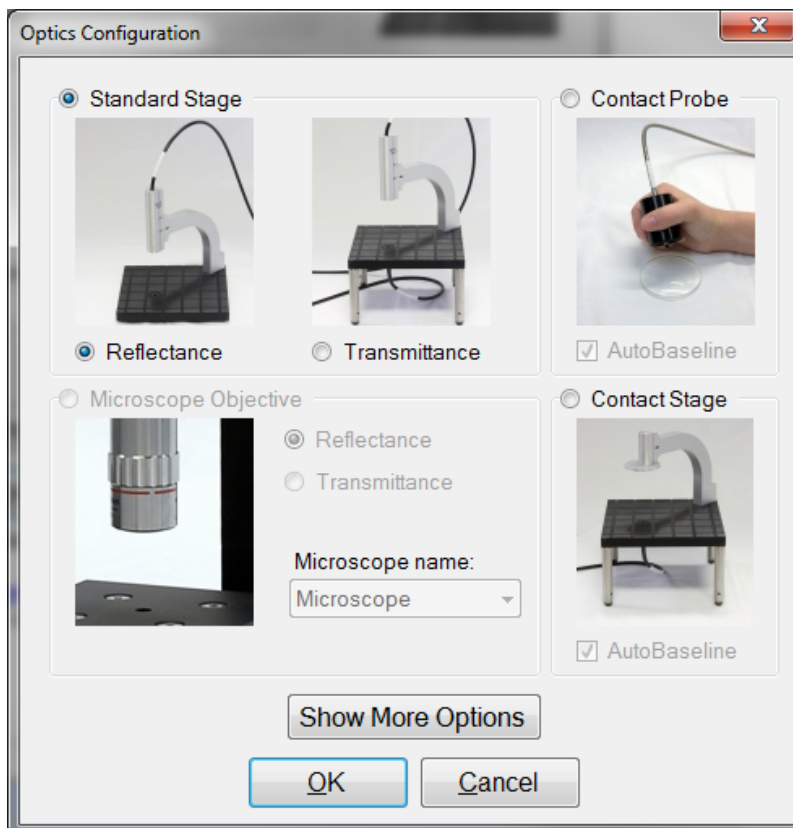
Notes:

- 1. If the reference measurement saturates, the software will display a detector saturation error. Analyzing a saturated spectrum will result in spurious final measurements. Take a new baseline with a lowered integration time.*
- 2. If the integration time is changed, it will be necessary to perform the baseline procedure, or re-acquire the reflectance standard and background scans.*

2.6.2 Spectrometer Type

EXR and UVX systems have two spectrometers (VIS-NIR and UV/VIS-NIR respectively). Here the user can choose to use only one or both spectrometers.

2.6.3 Optics Configuration



The **Optics Configuration** dialog box is accessible through the [Acquisition Settings](#) tab under the [Edit Recipe](#) window. It is important to make sure that you remember to select the proper configuration for your measurements in order to obtain the best possible results. Not all options are available with all systems.

2.6.4 AutoFocus

For systems with automated z-motion, FILMapper is capable of autofocusing on the sample and reflectance standard when making measurements. There are three different options available to users:

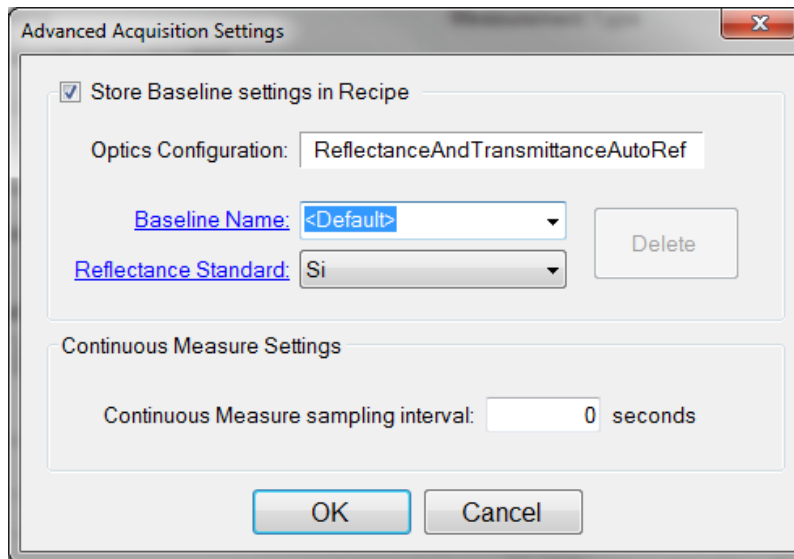
GOF: This autofocus function is intended to optimize focus based on the best goodness of fit measured off the sample. It is important to make sure that the recipe selected accurately matches the intended application to minimize measurement time.

Max Signal: This autofocus technique works by maximizing the raw signal returned from the spectrometer to determine best focus. It is the fastest of the three options.

Image Focus: Only for systems with the integrated camera, this technique focuses based on the image from the SampleCam.

Regardless of technique used, it is suggested to first use the manual focus controls to bring the system to a rough focus the first time you run a sample to minimize search time for the autofocus function.

2.6.5 Advanced Acquisition Settings



Store Baseline settings in Recipe

This option allows the user to save the selected **Optics Configuration**, **Baseline Name**, and **Reflectance Standard** used with each individual recipe.

Continuous Measure Settings

This option allows the user to set an interval, in seconds, between measurements when using the **Measure > Continuous Measure** command from the [Acquire Menu](#). By default this is set to 0.

3. Making Measurements

Accurate measurements with the F50 rely on using the proper measurement setup. The basic steps for any F50 measurement are:

- 1) Selecting and/or editing the [Film Stack](#) to be measured.
- 2) Taking a Baseline measurement.
- 3) Clicking on the **Measure** button to acquire and analyze the measured spectrum.

Each example below will take you through this sequence of steps. In each example it is assumed that the hardware has been set up as described in the **Quick Start Guide**, and that you have first read through the [Software Overview](#) section to familiarize yourself with the basic controls.

The [Focusing the Fiber](#), [Measurement Assumptions](#), [Hints for Improved Accuracy](#), and [Troubleshooting](#) sections describe techniques that should be followed for the most accurate measurements.

3.1 Focusing the Fiber

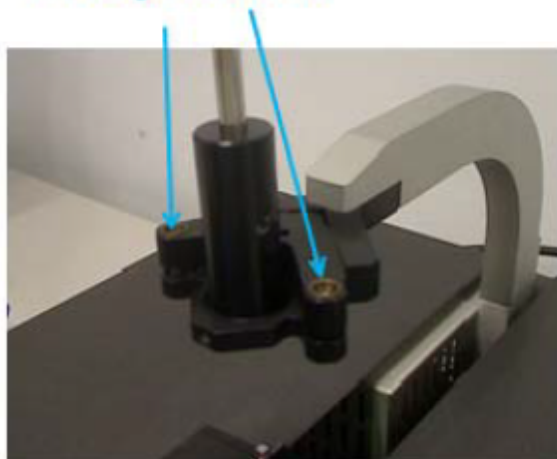
In order for the system to properly make measurements, the light must first be properly focused to the height of the reflectance reference to be used. When the fiber-optic is fully inserted into the lens tube, the Lens Assembly in the F50 is designed to provide optimal focus for samples the same thickness as the silicon reflectance standard. If the top surface of the object to be measured is a different height than the reflectance standard to be used, please follow the procedure below to focus the fiber-optic.

- A. Turn on the light source
 - B. Start FILMapper.
 - C. Go to the [Setup>Raw Signal...](#) dialog box, set the integration time for 20 milliseconds, and click **Apply**.
 - D. Place a reflective sample, such as a silicon or BK7 reflectance standard, on the sample stage. You will now see the raw signal from the spectrometer. If the signal exceeds 4000 counts, reduce the integration time (step C).
- ** Note ** Focus position is dependent on sample thickness. Make sure the surface you intend to measure is at the same height as the reference surface of the reflectance standard. It may be necessary to place a flat object, a washer for example, under the sample or reflectance standard in order to match surface heights.**
- E. Move the fiber-optic cable slightly up the lens tube until maximum signal is obtained. Integration time may also need to be reduced as the signal increases.

The recessed set screw on the back of the lens tube is actually a spring-loaded ball plunger and does not require tightening. Users should be aware that the fiber may slip out of focus if the stage or cable is moved. If one focus height is often used, the set screw can be tightened to reduce the chance of inadvertent slipping once an optimal focus position is found.

F. Adjust the tilt of the lens by rotating the screws on the KM-F50 to maximize the raw signal, as in the previous step.

Tilt adjustment



G. Close the **Setup > Raw Signal...** dialog box. Focusing is now complete.

There is also a video demonstration of this procedure on YouTube, which can be found [here](#). An active internet connection will be needed to view the video.

Focusing for Systems With Automated Z-Motion

Focusing on systems with the automated z-motion controller is very similar to that of the fiber with lens assembly or microscope based systems, only with the controls for height adjustment included in the software.

1. Turn on the light source for the system.
2. Start FILMapper.
3. Go to the [Setup>Raw Signal...](#) dialog box, set the integration time for 20 milliseconds, and click **Apply**.
4. Place a reflective sample, such as a silicon or BK7 reflectance standard on the sample stage. You will now see the raw signal from the image sensor. If the signal exceeds 4000 counts, reduce the integration time .

5. Adjust the focus to maximize the measured signal using the focus controls in the software.
6. If micropositioners are present on the optical assembly, F3-XXT systems for example, they may be adjusted at this time . Alternate making adjustments between the two knobs until signal is maximized. As the system is very sensitive to the tip/tilt adjustments being made with the micropositioners, it is important that adjustments are made slowly and in small increments.
7. Close the **Setup>Raw Signal...** dialog box. Focusing is now complete.

You will be prompted to focus the system during the [Baseline](#) during both the sample and reference steps. For the most accurate results, it is important to refocus to your sample after the **Baseline**.

3.2 Example A - Mapping Thickness Only

Measuring the Thickness of SiO₂ on Silicon

For this example we will demonstrate only the measurement of SiO₂ on silicon, but this type of measurement has an extremely broad range of applications, including photoresists, hardcoats and polysilicon, to name just a few.

[Continue to Step 1...](#)

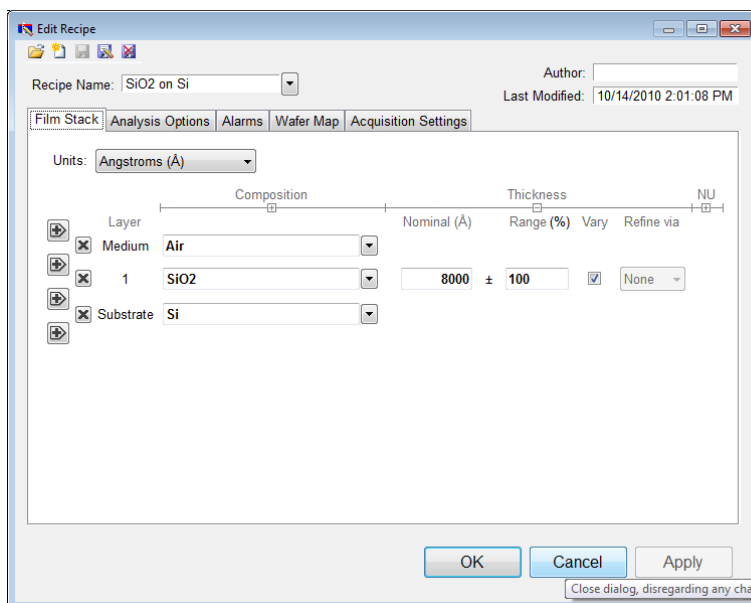
Example A - Preparing the Film Stack

Step 1: Select the film stack

Select the film stack to be measured, in this case “SiO₂ on Si”, from the **Recipe**: list box on the main screen. If the stack to be measured does not exist, a new stack must be defined (see “[Editing Film Recipes](#)”).

Step 2: Edit the film stack

To edit the stack, click the [Edit Recipe](#) button to open the dialog box. Check to see that the film sequence matches that of the actual sample. If not, different films can be selected. Also enter your best guess for the thickness of the film to be measured, and check that only the SiO₂ layer thickness is being measured.



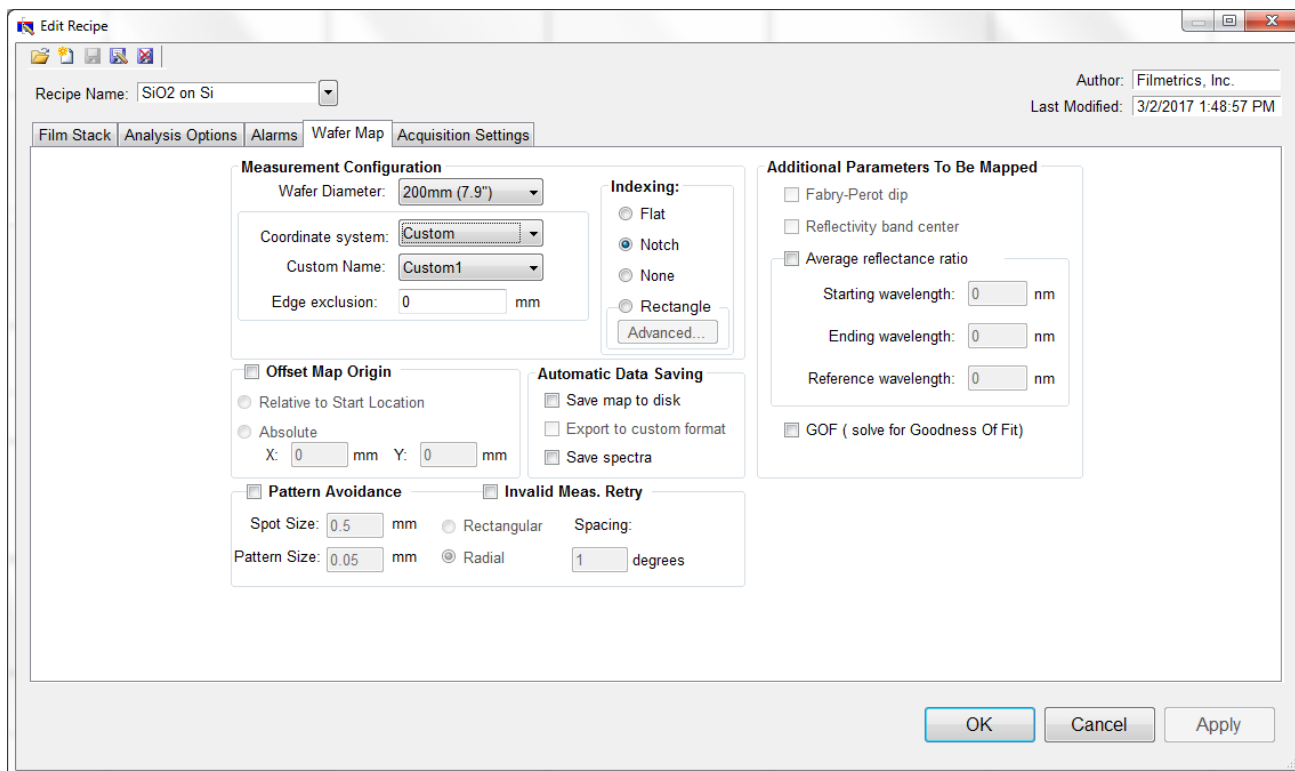
Example **Edit Recipe>Film Stack** window for measuring SiO₂ on Si

[Continue to Step 3](#)

Example A - Preparing the Map and Baseline

Step 3: Edit the mapping routine

Edit the [Edit Recipe>Wafer Map](#) tab for the desired set of measurement spots on the wafer.



Example [Edit Recipe>Wafer Map Tab](#) for specifying mapping parameters.

Step 4: Take a Baseline Measurement

Take a baseline measurement by clicking on the **Baseline** button. A dialog box will appear to step you through the process. In the **Acquire Reference** dialog box, make certain to select the reference material that will be used ("Si" in this case). Then put the reference sample on the measurement stage and click **OK**. The dark measurement will automatically be made after this reference measurement.

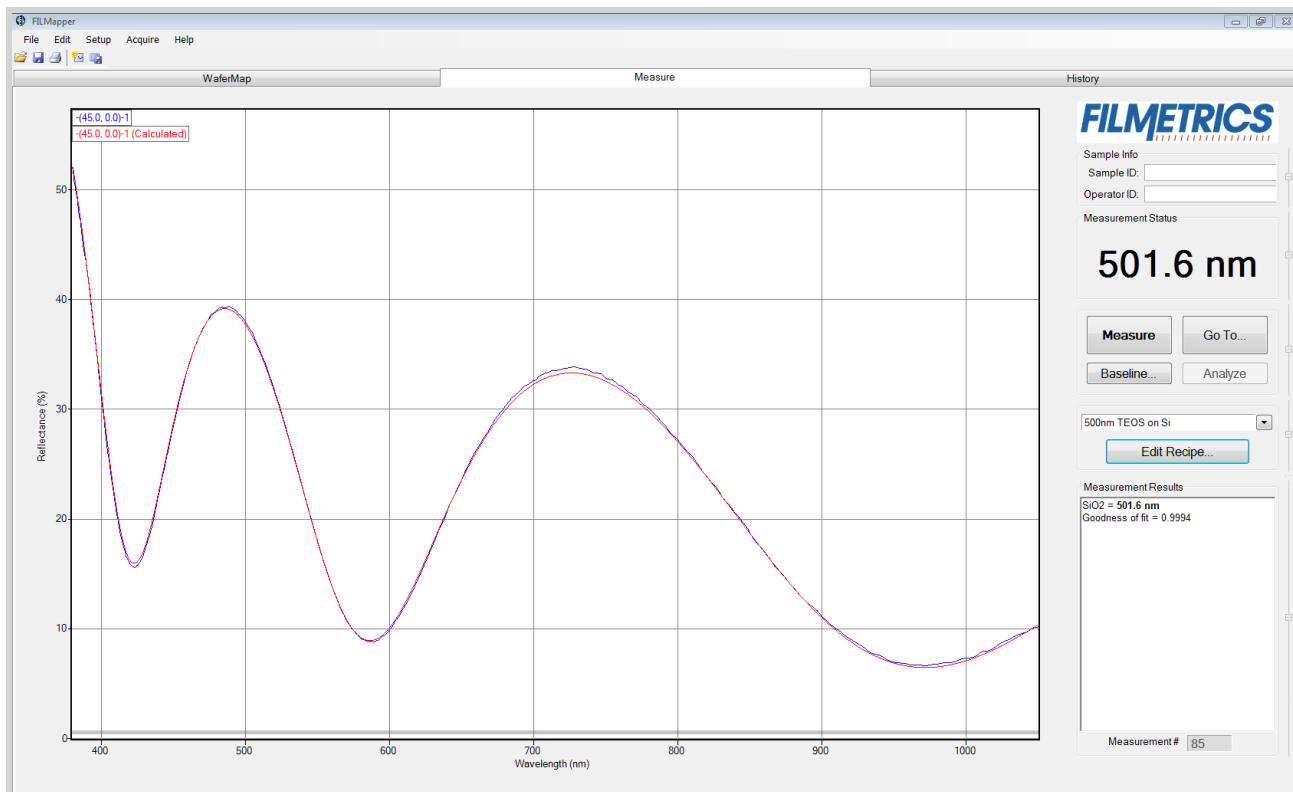
[Continue to Step 5](#)

Example A - Making the Measurements and Map

Step 5: Make the Measurement at a Single Spot (only necessary on the first of a set of wafers)

Place your sample on the stage. After choosing an appropriate spot on the wafer using the [Go To...](#) button, return to the [Measure Tab](#) and make the thickness measurement by clicking on the **Measure** button. For this example you can simulate this measurement by moving to the included thickness standard using the **Go To** command.

FILMapper will then acquire the reflectance spectrum and calculate the corresponding thickness. If the measurement was successful, the minima and the maxima of the calculated reflectance (the red line on the graph) will coincide in wavelength with the minima and the maxima of the measured reflectance (the blue line on the graph.) In most cases they will not overlap, but will be separated in amplitude.

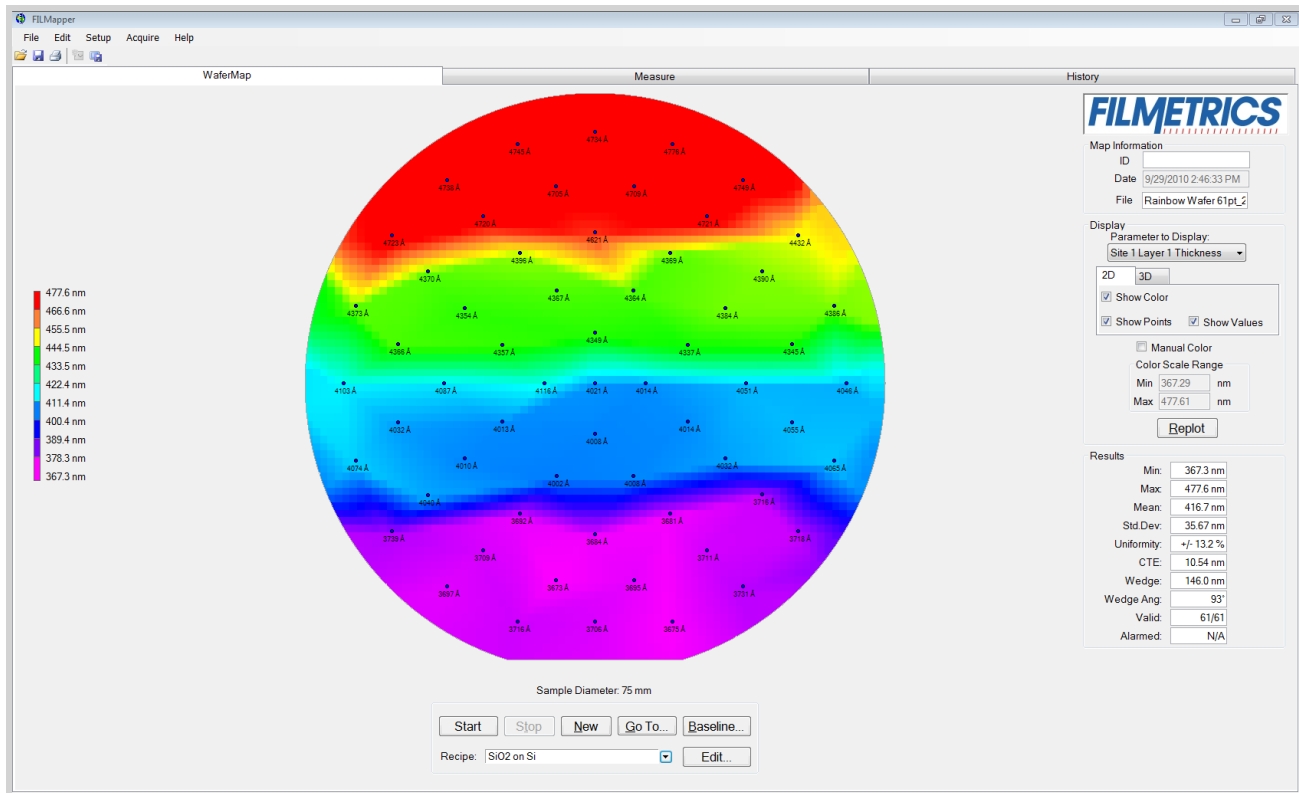


Measured and calculated reflectance spectra when measuring the thickness of SiO₂ on silicon.

If the calculated (red) and measured (blue) minima and maxima do not coincide, then the measurement was not successful. There are several possible causes of an unsuccessful measurement. The most common for this type of measurement are described in the [Troubleshooting](#) section.

Step 6: Map the Wafer

Having received an encouraging answer for the thickness at the specified spot, run the wafer mapping routine by clicking on the **Map** tab, and pressing **Start**. The program will begin to display the thicknesses on the wafer as the measurements are being made. After the mapping is complete, a thickness color map will be generated and statistical analysis for the current set of measurements will be presented.



Color wafer map of SiO₂ on silicon.

To switch the color map display between multicolor and a single-color shading, go to the [Setup>Options>Wafer Map Rendering...](#) menu item.

3.3 Example B - Mapping Thickness and Optical Constants

Measuring the Thickness of Si₃N₄ on Silicon

For this example we will demonstrate mapping thickness and optical constants (n and k) of Si₃N₄ on silicon.

[Continue to Step 1...](#)

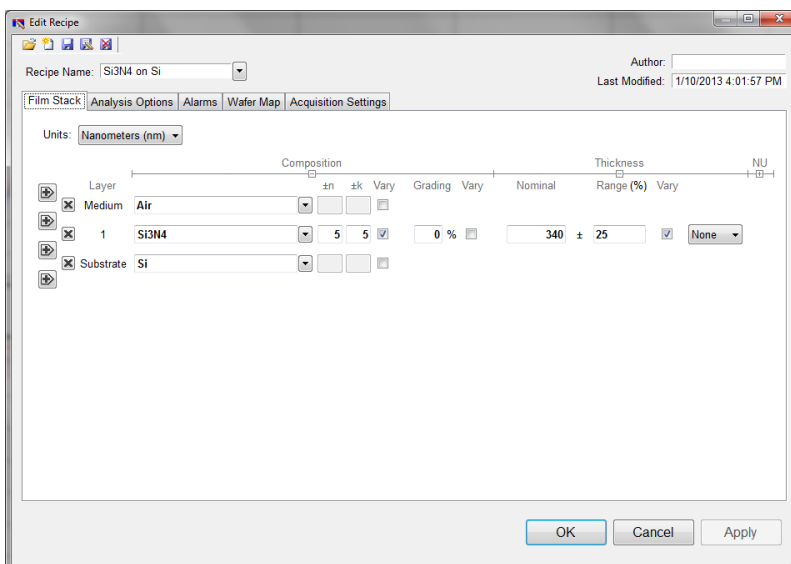
Example B - Preparing the Film Stack

Step 1: Select the film structure

Select the film stack to be measured, in this case “Si₃N₄ on Si”, from the **Recipe**: list box on the main screen. If the structure to be measured does not exist, a new structure must be defined (see [Editing Film Recipes](#)).

Step 2: Edit the film structure

To edit the stack, click the [Edit Recipe](#) button to open the dialog box. Check to see that the film sequence matches that of the actual sample. If not, different films can be selected. Also enter your best guess for the thickness of the film to be measured, and check that the Si₃N₄ layer thickness, n , and k are being measured. Right-click on the Meas. button under composition and confirm that the Si₃N₄ index model is selected.



Example **Edit Recipe** > **Film Stack** window for measuring thickness, n , and k of Si₃N₄ on Si.

[Continue to Step 3...](#)

Example B - Preparing the Map and Baseline

Step 3: Edit the mapping routine

Edit the [Edit Recipe > Wafer Map](#) tab for the desired set of measurement spots on the wafer.

The screenshot shows the 'Edit Recipe' dialog box with the 'Wafer Map' tab selected. The 'Recipe Name' is 'Si3N4 on Si'. The 'Author' field is empty, and the 'Last Modified' date is '1/10/2013 4:01:57 PM'. The 'Wafer Map' tab is active, showing the following settings:

- Measurement Configuration:**
 - Wafer Diameter: 75mm (3")
 - Coordinate system: Polar
 - Number of Points: 25
 - Edge exclusion: 5 mm
- Indexing:**
 - Flat
 - Notch
 - None
 - Rectangle
- Automatic Data Saving:**
 - Save results to disk
 - Export to custom format
 - Save spectra
- Pattern Avoidance:**
 - Pattern Avoidance
 - Spot Size: 0.5 mm
 - Pattern Size: 0.05 mm
 - Invalid Meas. Retry
 - Rectangular
 - Radial
 - Spacing: 1 degrees
- Additional Parameters To Be Mapped:**
 - Fabry-Perot dip
 - Reflectivity band center
 - Average reflectance ratio
 - Starting wavelength: 0 nm
 - Ending wavelength: 0 nm
 - Reference wavelength: 0 nm
 - GOF (solve for Goodness Of Fit)
- Full Wafer Reference Mode:**
 - Automatic
 - Off
 - On

Buttons at the bottom: OK, Cancel, Apply.

Example **Edit Recipe > Wafer Map Tab** for specifying mapping parameters.

Step 4: Take a Baseline Measurement

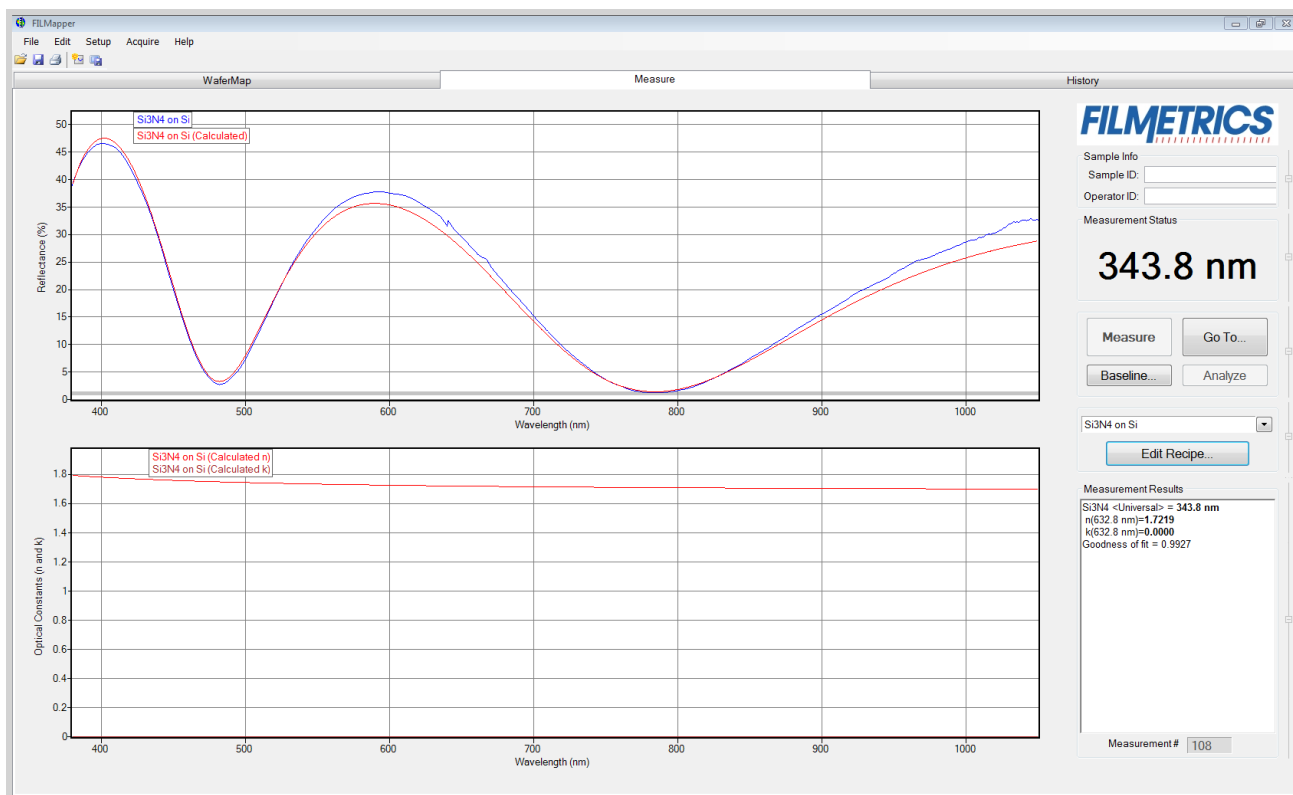
Take a baseline measurement by first clicking on the **Baseline** button. A dialog box will appear to step you through the process. In the **Acquire Reference** dialog box, make certain to select the reference material that will be used ("Si" in this case). Then put the reflectance standard on the measurement stage and click **OK**. The dark measurement will automatically be made after this reference measurement. A full wafer reference measurement will be made (i.e. each point of the pattern specified in the active recipe will be measured).

[Continue to Step 5...](#)

Example B - Making the Measurement and Map

Step 5: Make the Measurement at a Single Spot (only necessary on the first of a set of wafers)

Place your sample on the stage. After choosing an appropriate spot on the wafer using the **Go To...** button, return to the **Measure Tab** and make the thickness measurement by clicking on the **Measure** button. FILMapper will then acquire the reflectance spectrum and calculate the corresponding thickness and optical constants. If the measurement was successful, the minima and the maxima of the calculated reflectance (the red line on the graph) will coincide in wavelength with the minima and the maxima of the measured reflectance (the blue line on the graph.)

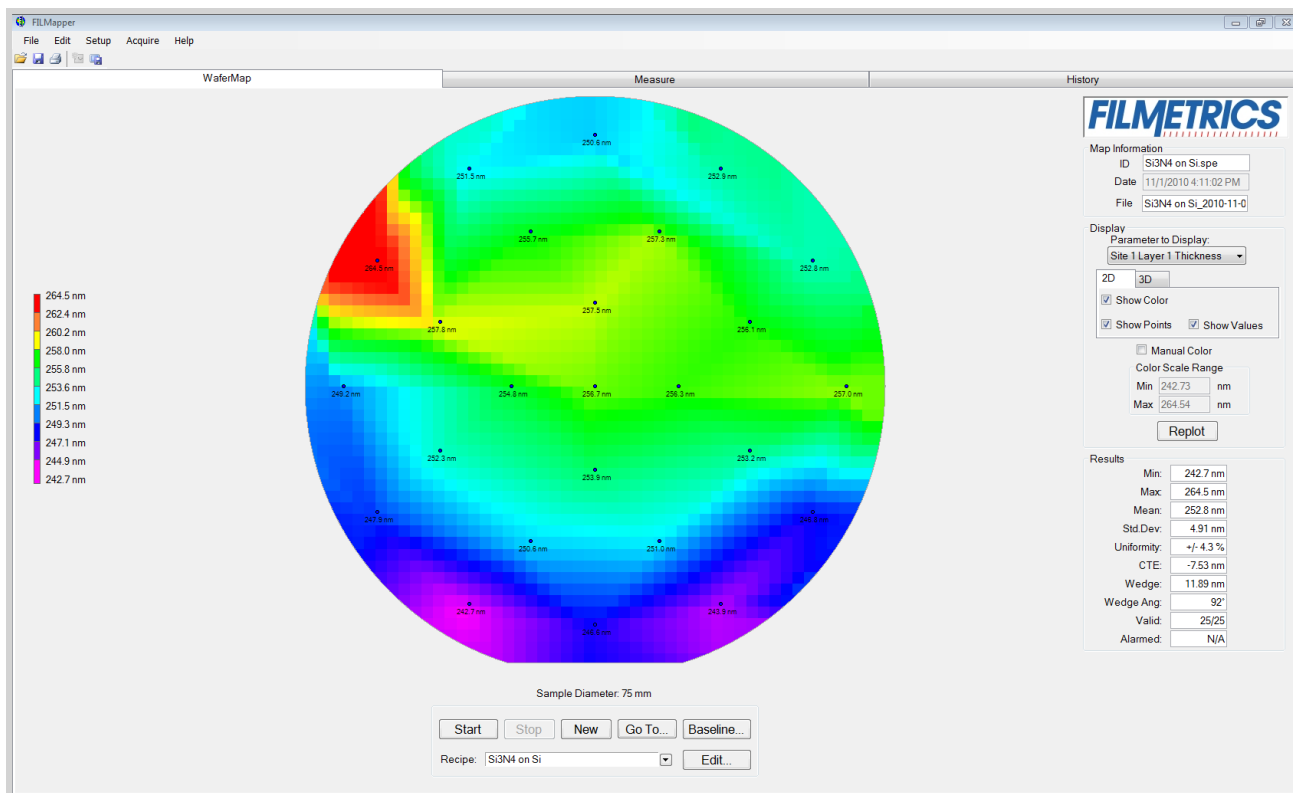


Measured and calculated reflectance spectra when measuring the thickness, n , and k of Si₃N₄ on silicon.

If the calculated (red) and measured (blue) spectra do not fall on top of each other, the resulting thickness, n , and k values are incorrect. If the mismatch between measured data and calculation is only slight, the results reported will only be off by a small amount. If the measured and calculated spectra match, but the results are implausible, there may be a problem with the sample positioning and light collection. Causes and corrective actions to improve the measurement are listed in [Case #5](#) and [Case #6](#) in the [Troubleshooting](#) section.

Step 6: Map the Wafer

Having received an encouraging answer at the specified spot, run the wafer mapping routine by clicking on the **Map** button. The program will revert to the [Wafer Map Tab](#) and will begin to display the thicknesses on the wafer as the measurements are being made. After the mapping is complete, a thickness color map will be generated and statistical analysis for the current set of measurements will be presented. To view other parameters on the color map, select the parameters (i.e. refractive index) from the **Display:** drop-down box.



Map of the refractive index of Si₃N₄ on silicon.

3.4 Measurement Assumptions

The following assumptions must be valid if accurate measurements are to be made with the F50

1. Every film present in the structure is specified in the **Edit Recipe** dialog box. This includes every film present in the sample including so-called adhesion films, oxide films (unless they are less than 20 Å thick), and films on the bottom surface of the substrate if the substrate is transparent.
2. If the film is **Nonuniform**, it has been accounted for in the recipe.
3. The light source has been allowed to warm up for at least 5 minutes if measuring thickness of films greater than 250nm, or 15 minutes if measuring thickness of films less than 250nm, refractive index, or reflectance.

In addition, the following assumptions are made if optical constants and/or very thin films (<500 Å) are to be measured:

4. If any grading is present (i.e. the refractive index and extinction coefficient are constant as a function of depth and constant over the entire spot being measured), it has been accounted for in the recipe.
5. The sample is flat. (The vacuum chuck may help in this case when samples are warped.)
6. No changes to the measurement system (such as fibers being moved) or light source have occurred since the acquisition of the most recent baseline.
7. No significant changes in room temperature (> 5 degrees F) have occurred since acquisition of the most recent baseline.

If any of the above assumptions are not true, it may still be possible to make a measurement, but accuracy may be degraded.

3.5 Hints for Improved Accuracy

This section contains various tips to help improve accuracy in your measurements.

[Roughness.](#)

[Restricting the wavelength range of the analyzed reflection spectra.](#)

[Measuring thickness when the approximate thickness is not well known.](#)

[Measuring photosensitive films.](#)

3.5.1 Roughness

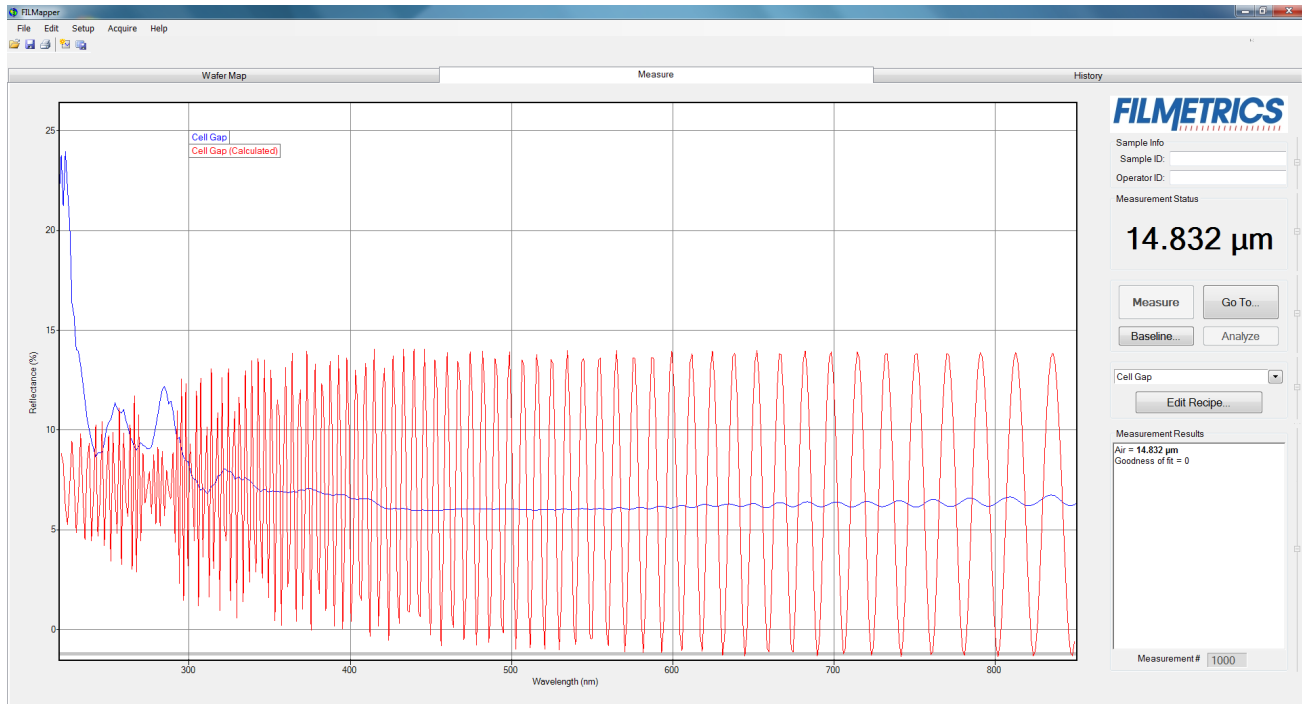
Slight amounts of surface or interface roughness that may be present can decrease the **GOF** value of a measurement. Entering a value or solving for roughness can partially account for this roughness so that a better **GOF** may be achieved. Generally, roughness is only present when the sample surface looks hazy at the measurement spot. The fact that haze can be seen means that there is scattered light. (A perfectly smooth surface will scatter no light, and thus the measured spot will not be visible.) Usually roughness less than 2.5 nm will not be visible, while roughness greater than about 25 nm will be extremely hazy.

FILMapper assumes a Gaussian distribution of the surface height irregularities about the mean and it assumes that the roughness is small compared to the wavelength. FILMapper reports the rms roughness value.

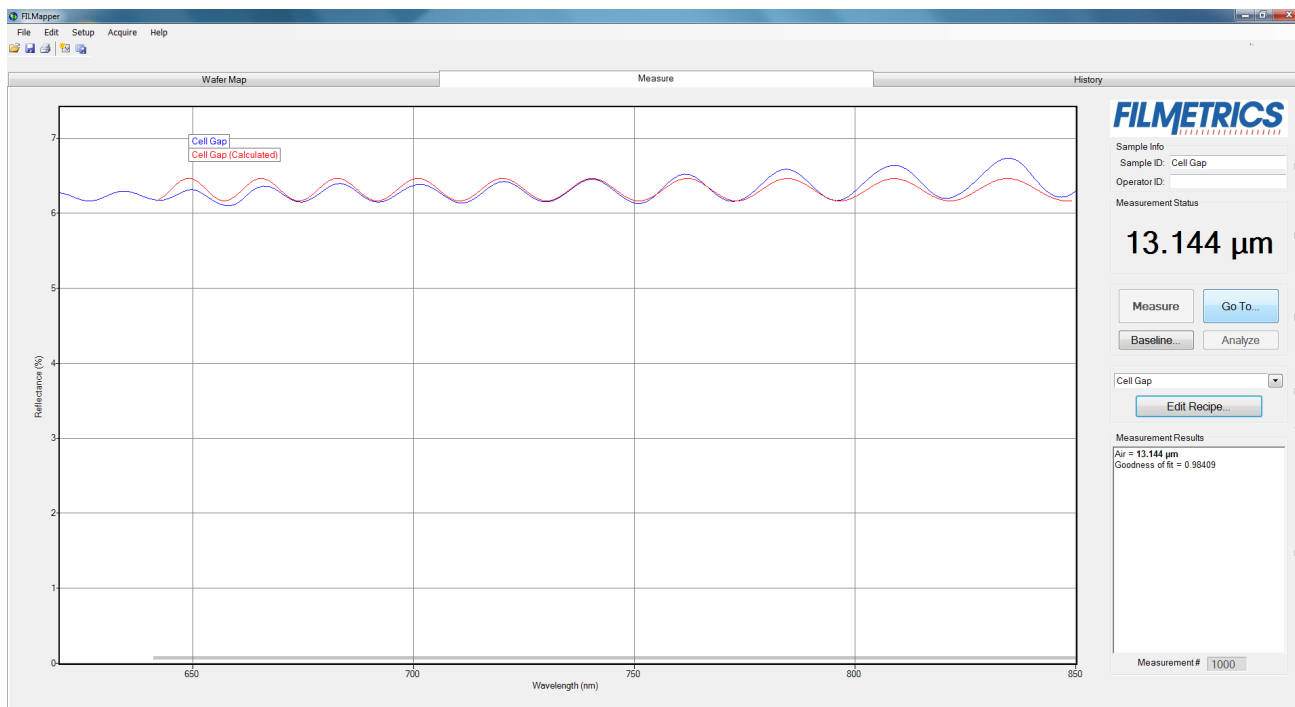
3.5.2 Restricting the wavelength range of the analyzed reflectance spectrum

Occasionally spectra from measured films are adversely affected by factors such as absorbing dyes, birefringence, or nonuniformity – all of which are difficult to model properly. It is often still possible to make accurate thickness measurements of these films by analyzing only unaffected portions of the spectra. The portion of the spectrum that is used to calculate film properties is determined in the recipe underneath the [Analysis Options](#) tab.

You can also adjust the wavelength analysis range in the main FILMapper window using the gray bar at the bottom of the graph. Click and drag either end of the bar to a new position on the x-axis to adjust the analysis range.



Example of a non-ideal film (spectrum with no oscillations at lower wavelengths) that requires reduced wavelength range for accurate measurement.



Example of a reduced wavelength range for measuring thickness of non-ideal films.

3.5.3 Measuring thickness when the approximate thickness is not well known

Unless otherwise specified, FILMapper will determine a film's thickness by finding the best answer within about 1000 Å of the initial (user supplied) value. If the approximate thickness of the film is not known to better than about 1000 Å, then the [Grid](#) method or the [Fourier Transform](#) method of determining approximate thickness may be applied. See [Editing Film Structures](#) for more details.

Measuring photosensitive films

For layers such as unexposed photoresist that cannot be exposed to short-wavelength light, a filter may be inserted in the slot on the light source.

3.6 Troubleshooting

For error messages or hardware problems encountered with your Filmetrics instrument, please use the chart below to best diagnose your problem. For help with modeling, see [Troubleshooting - Thickness Modeling](#).

Question 1: Are you able to start FILMapper without an error message?

No: Continue to [Question 2](#).

Yes: Continue to [Question 1-1](#).

Question 1-1: What sort of problem are you seeing?

1: The lamp doesn't turn on or the fan isn't working properly. See the [Non-Operating Box, Lamp, or Fan Troubleshooting Guide](#).

- 2: I get an error message when I click on something. Continue to [Question 1-1-2](#).
- 3: Measurement results are wrong or unstable, after they had been good. See the [Measurement Results are Incorrect or Unstable Troubleshooting Guide](#).
- 4: Measurement and/or baseline takes longer than it used to. See the [Slow Operation Troubleshooting Guide](#).

Question 1-1-2: If you're still seeing an error after you've power cycled and installed new software, then select the description which most closely describes your error.

- 1: The error occurs during the baseline. See the [Error Message During Baseline Troubleshooting Guide](#).
- 2: Some other error. See the [Error Messages -Miscellaneous Troubleshooting Guide](#).

Question 2: Are you able to launch FILMapper but it shows an error?

Yes: Continue to [Question 2-1](#).

No: Then you need to install the software that come with your new system, or you can request new software. See the [Software Reinstallation Guide](#).

Question 2-1: Does the error message start with "No Filmetrics instruments detected...."?

Yes: See the [Non-Operating Box, Lamp, or Fan Guide](#).

No: Continue to [Question 2-1-2](#).

Question 2-1-2: Does the instrument have a motorized stage?

Yes: See the [Stage Motion Troubleshooting Guide](#).

No: See the [Error Messages - Miscellaneous Troubleshooting Guide](#).

3.6.1 Power Cycling

Over the years we've found that about a third of support issues can be resolved by simply power cycling the Filmetrics system and computer. Follow the simple steps below to power cycle your instrument. Further assistance may be received by contacting us using the methods described in the [Contact Information](#) section.

Step 1: Shut down FILMapper (it's OK in the rare case that you can't).

Step 2: Unplug all electrical connectors from the back of your Filmetrics box.

Step 3: Restart your computer, giving it time to load all drivers.

Step 4: Reconnect the electrical connections to your Filmetrics box. (Make sure that the power cord is getting power, and that any switch near the power connector is turned on.)

Step 5: Restart FILMapper

3.6.2 Software Reinstallation Guide

Follow the steps below to reinstall FILMapper. Further assistance may be received by contacting us using the methods described in the [Contact Information](#) section. *Warning: Upgrading software versions may result in slightly different (<1%) measurement results due to continual improvement of our solving algorithms and material files.*

Step 1: Shut down FILMapper (it's OK in the rare case that you can't).

Step 2: Unplug all electrical connectors from the back of your Filmetrics system.

Step 3: Are you installing this software on a computer which already has FILMapper installed?

Yes: Go to Step 4.

Yes: Jump to [Step 6](#).

Step 4: Make a backup copy of your recipe and material files:

FILMapper versions 1 thru 4: Backup the directory C:\Program Files\FILMapper

FILMapper versions 5 and up:

On Windows XP: Backup the directory C:\Documents and Settings\All Users\Application Data\Filmetrics

Note: The application Data folder may be hidden by default.

On Windows 7/8/Vista/10: Backup the directory C:\Program Data\Filmetrics\

Note: The Program Data folder may be hidden by default.

Step 5: Uninstall the current version of software:

On windows XP: Click Start > Control Panel > Add or Remove Programs > FILMapper > Uninstall

On Windows 7/Vista: Click the Start orb > Control Panel > Programs and Features > FILMapper > Uninstall

On Windows 8: Control Panel > More settings > Programs and Features > FILMapper > Uninstall

Step 6: Run the software installer and follow installer instructions.

Note: you will need administrative privileges to install the software.

Step 7: Reconnect your Filmetrics system.

*Note for Windows XP: The "New Hardware Found" wizard may appear if your instrument has a USB connection. You **must** click "Next and complete the driver installation process. This dialog box may appear multiple times depending on the system configuration.*

Note for Windows 7/8/Vista: An Information balloon may appear over the taskbar while drivers are being installed. Please wait until the balloon indicates the drivers have been installed before starting FILMapper.

Step 8: Run the software to verify the installation was successful.

3.6.3 Non-Operating Box, Lamp, Or Fan

Follow the steps below to troubleshoot symptoms of a non-operating spectrometer, light source, or fan. These are usually caused by having too much or not enough light. Further assistance may be received by contacting us using the methods described in the [Contact Information](#) section.

Step 1: Does the green LED on the right side of the front panel illuminate?

Yes: Jump to [Step 3](#).

No: Go to Step 2.

Step 2: Is the power cord fully inserted into the back of the unit and a powered wall outlet? If your unit has a rear power switch, is it on?

Yes: Go to Step 3

No: Plug into a powered outlet or switch on the unit

Step 3: Does the LED light on the light source switch illuminate when switched on?

Yes: go to Step 4

No: Possible faulty switch or faulty indicator lamp, contact [Filmetrics](#).

Step 4: Is the cooling fan spinning? Determine this by listening to the cooling fan which is located directly below the light source. (You'll need to get close to hear the fans on systems built after 2010.) For F50 systems the chassis cooling fan is louder than the light source cooling fan. You'll need to get close to the light source to hear the light source cooling fan.

Yes: Go to Step 5.

No: The cooling fan needs replacement, contact [Filmetrics](#). *Note: a bad cooling fan can draw enough power to prevent the light source and box from operating properly.*

Step 5: Does the light source illuminate?

Yes: Go to Step 6

No: The lamp has burned out. Please replace the lamp following the instructions [here](#). A spare lamp is included with most systems and additional lamps may be purchased on our website www.filmetrics.com *Note: users can confirm a bad halogen lamp by removing it and checking it for electrical continuity.*

Step 6: The following steps are to troubleshoot a box that is not being detected by the FILMetrics software. This could be a software driver or (rarely) a hardware problem. To see what hardware your computer is detecting, look in the windows device manager. (instructions on how to access the Device Manager are included at the end of this document.)

In the Device Manager, which device do you see?

"Filmetrics Measurement Instrument" or similar: In this case the system should be operation correctly. If not, please contact [Filmetrics](#).

"Unknown Device" or similar: The hardware appears to be operating properly, but the drivers for the hardware are not installed. If you have already power cycled and installed the most current Filmetrics software, please contact [Filmetrics](#) for further assistance.

Neither of the above: The hardware is not working properly. Go to Step 7

Step 7: Try a new USB cable and plug it into a different USB port. Does this fix the problem?

Yes: Either the USB cable or port was bad.

No: The USB controller inside the FILMetrics box may be bad. Please contact [Filmetrics](#).

Accessing Device Manager in Windows 7:

1. Click on the Start Orb.
2. In the Star Search box type: device manager. Press enter.
3. Select Device manager from the list.
4. You should see a Filmetrics Measurement Instrument tab. Expand the tab and the appropriate driver should be listed for the Filmetrics instrument.

Accessing Device Manager in Windows XP:

1. Click Start.
2. Click on Control Panel
3. In the Control Panel double-click the Systems icon.
4. In the Systems Properties window click on the Hardware tab.
5. In the Hardware tab click the Device Manager button.
6. You should see a Filmetrics Measurement Instrument tab. Expand the tab and the appropriate driver should be listed for the Filmetrics instrument.

3.6.4 Error Message during Baseline

Follow the steps below to troubleshoot error messages encountered while taking a baseline. These are usually caused by having too much or not enough light. Further assistance may be received by contacting us using the methods described in the [Contact Information](#) section.

Step 1: Which error message are you seeing while taking a baseline?

Received light signal is too bright: If you are manually setting the integration time (see [Measurement Timing](#)) then you need to reduce the integration time. Otherwise you can reduce the light source intensity by using a flattening or neutral density filter. Optical filters can be purchased on our website, www.filmetrics.com.

Baseline Failure. Reference and background spectra are almost the same: This error is often caused by using the reference sample during the background step or vice versa, and is easily corrected by taking retaking the baseline while providing the proper material for the proper step. If this is not the case, go to Step 2.

Spectrometer peak intensity is x% of previous reference intensity: This error is often caused by using the incorrect reference sample and is easily corrected. Jump to [Step 5](#).

Step 2: Does the light source illuminate?

Yes: Go to Step 3.

No: Check the [Non-Operating Box, Lamp, Or Fan Troubleshooting Guide](#).

Step 3: Check to see if there is a broken or misconnected fiber. With the light source on, confirm that the illumination fiber is screwed into the light source securely, and that plenty of light is exiting the fiber at the far end near where the sample is placed. The light can be seen by placing paper (e.g., business card) near the sample location (do not look directly into the fiber if you are using a UV source). If plenty of light is seen, next check the return fiber by removing it from the spectrometer input and connecting it to the light source (removing the other fiber first). You should see light at the far end as before, but it may be 3-4 times smaller and dimmer. Did you see light at the sample end using both fibers in the light source?

Yes: The fiber appears to be good. Replace the fibers securely in their original positions (there will be a white band on the light source fiber if the two ends are different) and go to Step 4.

No: The fiber optic may be broken. Replacements can be purchased on our website, www.filmetrics.com

Step 4: Does your system have multiple spectrometers (i.e. EXR or UVX)

Yes: Check the **Acquisition Settings** tab under **Edit Recipe** to make sure that your fiber optic configuration matches the enabled spectrometers. Do this by making sure that each enabled spectrometer has a fiber attached to it (or disable a spectrometer that is not being used).

No: If you are still experience problems, please contact us using the [Contact Information](#) section.

Step 5: Was the correct reference selected from the drop-down list?

Yes: Go to Step 6.

No: Re-baseline using the correct reference.

Step 6: Has the light source lamp recently been changed?

Yes: This error is an expected response, no further action required

No: Go to Step 7.

Step 7: Has the optical configuration been altered (i.e. switching from standard spot size to small spot optics or a contact probe)?

Yes: This error is an expected response, no further action required

No: If you are still experiencing problems, please contact us using the [Contact Information](#) section.

3.6.5 Measurement Results are Incorrect or Unstable.

Follow the steps below to troubleshoot when measurement results are incorrect or unstable after the results had been good for some time. Additional help troubleshooting general measurement issues may be found in the [Troubleshooting: Thickness Modeling](#) section. Further assistance may be received by contacting us using the methods described in the [Contact Information](#) section.

Step 1: First confirm that you have selected the correct recipe for the sample that you are measuring (i.e., the same recipe that previously was giving good measurements). *Note that this troubleshooting guide does not cover instances where recipe parameters have been changed.*

Step 2: Confirm that the light source is turned on and that the fibers are securely tightened into the light source and the spectrometer input. Place a piece of paper at the sample measurement location and confirm that you can see a light beam. Can the light beam be seen?

Yes: Jump to [Step 4](#)

No: Go to Step 3

Step 3: Is there light coming out of the light source? (If you are checking a UV light source, put on the goggles that were supplied with the light source before checking.)

Yes: It appears the fiber may be broken. Replacements can be purchased on our website www.filmetrics.com

No: Replace the lamp following the instructions [here](#). A spare lamp is included with most systems and additional lamps may be purchased on our website www.filmetrics.com *Note: users can confirm a halogen bad lamp by removing it and checking it for electrical continuity.*

Step 4: Perform a new baseline, paying particular attention to make sure that you are using the proper reference and that it is clean with the correct side up.

Step 5: Put a sample that is known to be good on the stage and perform a measurement. If the measurement is still not correct, go to Step 6.

Step 6: Your lamp may be weak and needs to be replaced. The best way to tell is to replace it with the instructions found [here](#). A spare lamp is included with most systems and additional lamps may be purchased on our website www.filmetrics.com.

Step 7: It may be that the stage optics have become unfocused. Please refer to the [Focusing The Fiber](#) section.

If you are still experiencing problems with an unstable or incorrect measurement after the preceding steps, please contact us using the methods described in the [Contact Information](#) section.

3.6.6 Slow Operation Troubleshooting Guide

Follow the simple steps below to troubleshoot slow system operation. Further assistance may be received by contacting us using the methods described in the [Contact Information](#) section.

Step 1: When did you experience the slow operation?

During a baseline: Go to Step 2.

When I click Measure: Jump to [Step 7](#).

Step 2: Slow baselines are generally caused by a low light level, which can have several causes. Does the light source illuminate (be sure it is switched on, and that the shutter is open on UV systems)?

Yes: Go to Step 3.

No: Check the [Non-Operating Box, Light, or Fan Troubleshooting Guide](#).

Step 3: Check to see if there is a broken or misconnected fiber. With the light source on, confirm that the illumination fiber is screwed into the light source securely, and that plenty of light is exiting the fiber at the far end near where the sample is placed. The light can be seen by placing paper (e.g., business card) near the sample location (do not look directly into the fiber if you are using a UV source). If plenty of light is seen, next check the return fiber by removing it from the spectrometer input and connecting it to the light source (removing the other fiber first). You should see light at the far end as before, but it may be 3-4 times smaller and dimmer. Did you see light at the sample end using both fibers in the light source?

Yes: The fiber appears to be good. Replace the fibers securely into their original positions on the spectrometer box and light source (there will be a white band on the light source fiber if the two ends are different) and go to Step 4.

No: The fiber optic may be broken. Replacements can be purchased on our website, www.filmetrics.com

Step 4: Does your system have multiple spectrometers (i.e. EXR or UVX)

Yes: Check the Acquisition Settings tab under Edit Recipe to make sure that your fiber optic configuration matches the enabled spectrometers. Do this by making sure that each enabled spectrometer has a fiber attached to it (or disable a spectrometer that is not being used).

No: Go to Step 5.

Step 5: It may be that your lamp is old and needs to be replaced. The best way to tell is to replace it with the instructions found [here](#). A spare lamp is included with most systems and additional lamps may be purchased on our website www.filmetrics.com.

Step 6: It may be that the stage optics have become unfocused. Please refer to the [Focusing The Fiber](#) section. Otherwise, go to Step 7.

Step 7: Unless the slow operation during measurement is a new problem, please confirm that your computer meets the minimum system requirements as listed in the [system specifications](#). If it doesn't, please upgrade your computer. Otherwise, go to Step 8.

Step 8: A measurement that takes a long time generally means that there is a large amount of processing required to find a solution, which is usually caused by a non-optimal recipe setting. Please first confirm that you have selected the correct recipe for the film stack you are measuring. Otherwise, go to Step 9.

Step 9: Open the recipe and make sure that you are not solving for too many parameters. Solving for one or two thicknesses or a thickness and index should only take a second or two, but in some circumstances the solving time can be increased 5-10x for each additional parameter. Solving for nonuniformity (or adding it to increase accuracy of other parameters) can be especially time consuming.

Step 10: If you are solving for more than one thick layer (i.e., >10 um), you can speed up the solving process by reducing the thickness constraint range (which can be safely reduced even more by using an accurate nominal thickness guess) or by switching from using the [Grid](#) solver to the [FFT](#) solver in the recipe.

If you are still experiencing problems with a slow measurement after the preceding steps, please contact us using the methods described in the [Contact Information](#) section.

Stage Motion Troubleshooting Guide

Follow the steps below to troubleshoot stage motion problems. This guide only applies to Filmetrics systems that communicate via USB. Further assistance may be received by contacting us using the methods described in the [Contact Information](#) section.

Step 1: Does the stage move at all when the software starts?

Yes: Jump to [Step 7](#).

No: Go to Step 2.

Step 2: Disconnect the power from the system. Remove the top cover by removing the small screws on the sides and lifting the cover up slightly and pulling forward. Are the connectors fully seated into the headers on the board? (See Figures 1, 2, and 3.)

Yes: Go to Step 3.

No: Insert the connector into the header.

Step 3: Are the motor controller and driver boards fully seated in the respective connector sockets?

(See Figures 1, 2, and 3.)

Yes: Go to Step 4.

No: Insert the board into the socket.

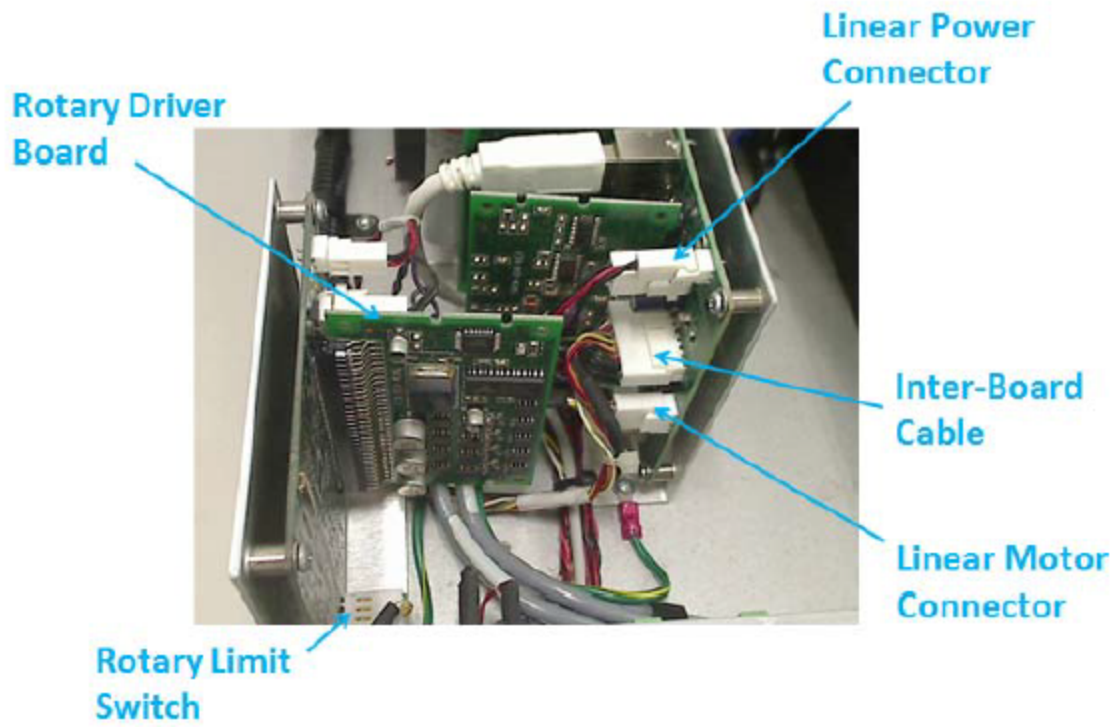


Figure 1

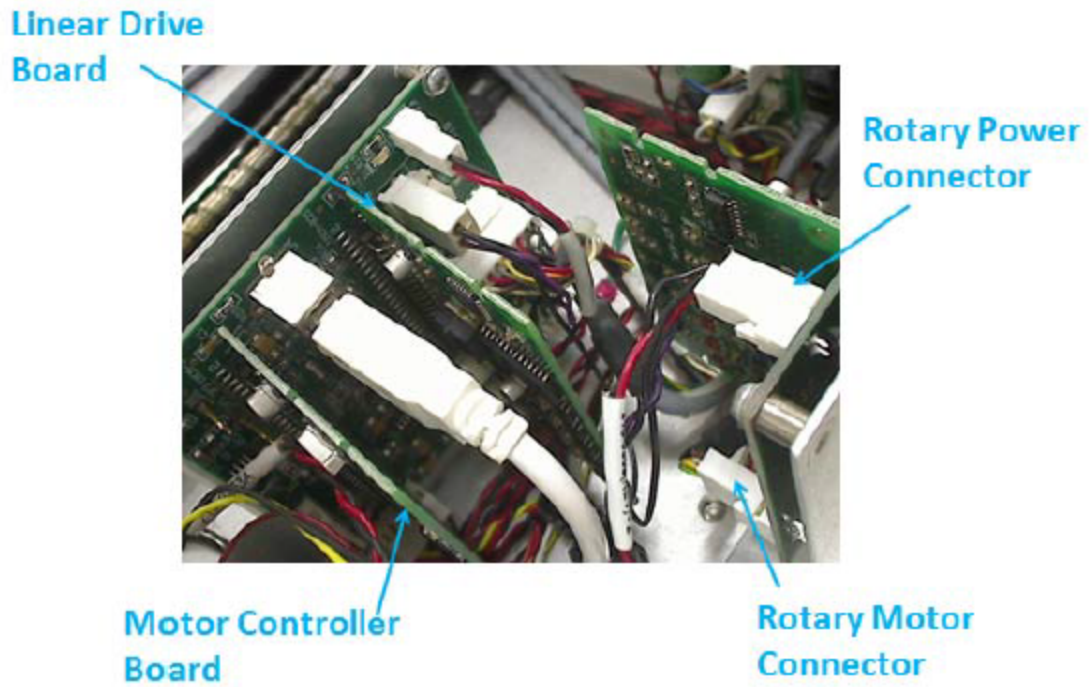


Figure 2

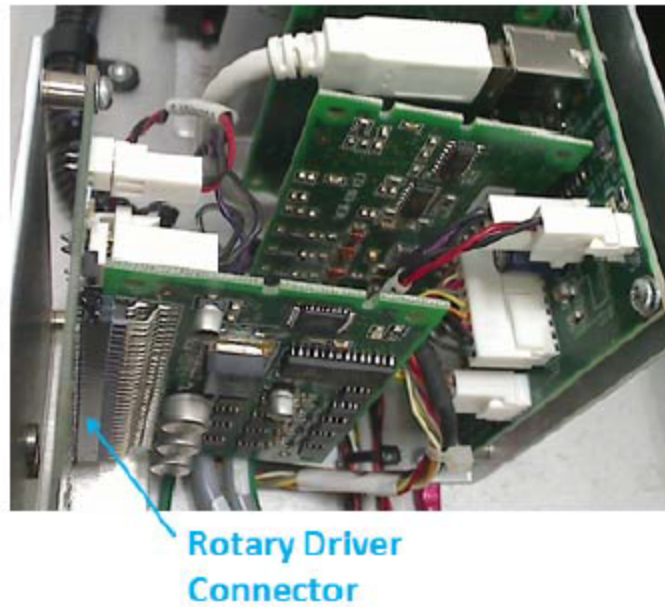


Figure 3

Step 4: Are there any signs of damage inside the enclosure(e.g. burn marks, physical damage, etc..)?

Yes: Report the damage to [Filmetrics](#).

No: Go to Step 5.

Step 5: Turn off power to the system and note the amount of force required to rotate the rotary stage (very little) and the linear stage. Now turn on power. Are both stages now more difficult to move?

Yes: Go to Step 6.

No: The motor driver board and/or the motor controller board probably failed, contact [Filmetrics](#).

Step 6: Start the software. Are the linear motor and rotary motor moving?

Yes: Go to Step 7.

No: There could be a communication problem with the motor controller. This is most commonly caused by wiring, connector, or grounding problems inside the unit. Contact [Filmetrics](#).

Step 7: Is the light source switched on?

Yes: Go to Step 8

No: Switch the light source on.

Step 8: Does the lamp illuminate?

Yes: Go to Step 9.

No: Switch the light source on.

Step 9: Does the light come out of the end of the fiber (test using a piece of paper under the lens)?

Yes: Go to Step 10.

No: The fiber needs replacement, contact [Filmetrics](#).

Step 10: Follow the instructions under the [Focusing the Fiber](#) section, then continue to Step 11.

Step 11: Perform a baseline and move the measurement spot to (0, 0). Does the light spot land on the center of the chuck?

Yes: Jump to [Step 13](#).

No: Go to Step 12.

Step 12: Is there an offset in X-Axis (side-to-side direction) between the light spot and center of the chuck?

Yes: Adjust by loosening the screw on the KM-F50 and gently moving the arm right or left. (See Figure 4-2).

No: Go to Step 13.

Tilt adjustment

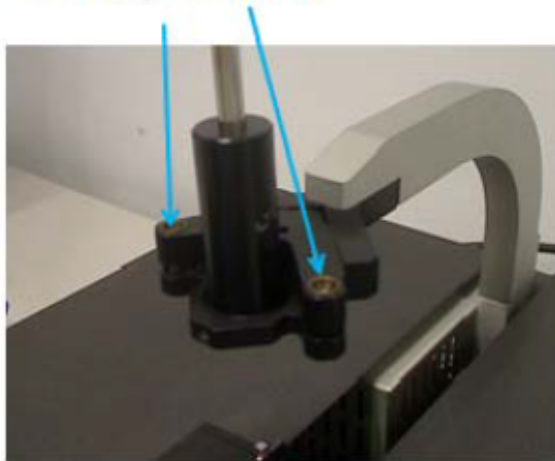


Figure 4-1



Figure 4-2

Step 13: Are there any objects in the base of the actuator that would interfere with the motion?

Yes: Remove the object(s) from the actuator.

No: Go to Step 14.

Step 14: Check if the stage motion follows the sequences below:

1. Small rotation first CCW direction and then CW direction.
2. Small linear move toward the back (to check the limit switch in the back). You should see the optical spot pass the chuck center.
3. Large linear move toward the front of the tool (to check the limit switch in the front).
4. Large linear move toward the back again so that the optical spot moves to the chuck center.
5. Small rotation first CCW then CW to check rotational limit switch.

Is there something wrong with the sequence of stage motion?

Yes: Contact [Filmetrics](#). Please explain the motion sequence. A short video is preferable.

No: This guide relates to issues of stage motion and apparently does not apply to the user's situation. Please contact [Filmetrics](#) for additional support.

3.6.7 Error Messages - Miscellaneous Troubleshooting Guide

This guide provides extended information on error messages a user may encounter on rare occasion while using our software. Further assistance may be received by contacting us using the methods described in the [Contact Information](#) section.

Error during spectrum analysis/ unable to analyze spectrum.

This error is generally caused by a problem with the recipe constraints. Try adjusting the solver wavelength range, thickness constraint range, or starting thickness value. Also make certain that the starting thickness values have been entered using the correct units of measure specified for the recipe.

Spectrum saturated.

This error indicates that the sample measured is more reflective than the spectrometer was expecting. Reflectance data may not be accurate as a result. Take a new baseline to fix this problem.

3.6.8 Troubleshooting: Measurement Results

In all cases it has been assumed that the user has read the [Measurement Assumptions](#) section, and that each criterion has been met.

[Case #1: No oscillations, or portions of oscillations, are present in the measured reflectance spectrum.](#)

[Case #2: The measured reflectance spectrum has periodic oscillations across the entire screen, but its minima and maxima do not match up with the calculated reflectance.](#)

[Case #3: Two or more different, but nearly the same, thickness readings are obtainable from the same measurement location.](#)

[Case #4: Poor matches between the measured and calculated reflectance spectra when measuring thickness and optical constants.](#)

[Case #5: Several different answers, or one unreasonable answer, are found when measuring thickness and optical constants, even though a good match is found between the measured and calculated reflectance spectra.](#)

Case 1: No oscillations, or portions of oscillations, are present in the measured reflectance spectrum.

There can be several possible causes in this case;

1. The film may just be very thin ($<200 \text{ \AA}$), thus presenting no discernible oscillations or only one identifiable minima or maxima. The FFT solver will not be able to accurately analyze films without at least one discernible full oscillation, in general meaning a film less than 0.2 microns thick. Use one of the **Spectrum Matching** solver methods ([Robust](#), [Exact](#)) to analyze very thin films.
2. If the film is very rough, non-uniform in thickness over the measurement area, or has a graded interface it may not support coherent optical interference and thus it may not be able to be measured. Try moving to a different measurement spot for a better signal.
3. An improper baseline measurement was taken, for example a thickness standard is presented as a reflectance standard. Re-baseline the system while taking care to select the proper reflectance standard and reference file.

Case 2: The measured reflectance spectrum has periodic oscillations across the entire screen, but its minima and maxima do not match up with the calculated reflectance.

The most common cause is that the initial thickness guess was considerably different than the actual film thickness, and due to the constraints on possible thicknesses, FILMapper was unable to find the correct answer.

To better understand this, it helps to know that the number of oscillations on the screen is proportional to the film thickness. For example, if the measured spectrum has roughly twice the number of the oscillations that the calculated spectrum has, then the measured film is roughly twice the thickness of the calculated thickness. Using this information, the initial thickness guess and the thickness constraints can be set more appropriately in the [Edit Recipe](#) dialog box. Another possible cause is found in [Case #3](#) (incorrect dispersion).

Case 3: Two or more different, but nearly the same, thickness readings are obtainable from the same measurement location.

When this occurs usually the measured and calculated spectra match somewhat, but not very well across the entire spectra (i.e., the measured and calculated spectra match exactly only over a small wavelength range and then gradually walk off one another outside this wavelength range). When thickness is the only value being measured, this is normally caused by the refractive index of the measured layer not matching that used by FILMapper, especially when the film is greater than one micron thick. Unless more accurate index values can be obtained, the best way to solve this problem is to restrict the wavelength range used in the analysis.

Case 4: Poor matches between the measured and calculated reflectance spectra when measuring thickness and optical constants.

There can be many causes of this problem, including those listed in [Case #1](#) and [Case #2](#) above. Most commonly when a poor fit between the spectra occurs, it is because:

- 1) The components of the film structure are not all included in the [Edit Recipe > Film Stack](#) dialog box. Adjust the recipe accordingly and reanalyze the spectrum.
- 2) Very inaccurate initial guesses for the film thickness(es) have been listed. Try a new nominal starting guess, or expand the thickness constraint range.
- 3) The optical constants listed in the **Edit Recipe > Film Stack** dialog box are far from the actual optical constants in the material. Try selecting a different but similar material file if one is present, for example switching from Acrylic to Acrylic - 2.

4) The film being measured has properties that are not taken into account by FILMapper. Examples of these properties are graded interfaces and non-uniform films. You can enable solving for these conditions in the recipe.

Note: Enabling Nonuniformity solving will increase solving time.

Case 5: Several different answers, or one unreasonable answer, are found when measuring thickness and optical constants, even though a good match is found between the measured and calculated reflectance spectra.

This normally occurs when a large number of properties are being measured on a very thin film. In general, the thinner a film is the less unique information that can be obtained from it. To understand this, see [Theory of Operation](#). To solve the problem, you can either:

- A. Decrease the number of variables solved for.
- B. Increase the amount of data provided to the solver (analyzing reflectance and transmittance at the same time, or using the multi-spectral solver).
- C. Enable multiple **Solver Cycles** under the [Edit Recipe > Analysis Options > Advanced](#) dialog.

4. Understanding and Evaluating Measurement Results

This section covers information on the [Display of Measured Spectra](#) and a more in depth look at the [Goodness Of Fit](#) value.

4.1 Display of Measured Data

Once film stack and measurement information have been entered and a baseline has been taken, measurements may be made by clicking on the **Measure** button. After measurement, the measured and calculated reflectance spectra are displayed on the graph, and the thicknesses of the films are listed in the results box. If any of the thickness values were measured, they are displayed in bold numbers.

The quality and accuracy of the result is determined by how well the measured spectrum matches with the calculated spectrum. In general, thickness information is determined by the number of oscillations, and index information is determined by the amplitude of the oscillations. In the case of the [Robust \(adaptive; thickness only\)](#) solver and [Exact Spectrum Matching](#) solver, a good result is one where the minima and maxima of the measured and calculated spectrum align. For the [FFT \(thickness only\)](#) solver, this is when the measured intensity peaks overlap. See the [Goodness of Fit](#) and [Troubleshooting - Thickness Modeling](#) sections for more information.

4.2 Goodness of Fit

The accuracy of a calculation fit, and thus the reliability of the measurement, can be judged by the match between the measured and calculated spectra, which is quantified by the GOF value. GOF is a number between 0 and 1.

A perfect match between measured and theoretical spectra will result in a GOF of 1. To ensure accurate results the user may set a minimum acceptable GOF value by entering a number between 0 and 1 into **GOF Error** on the [Alarms Tab](#) in the [Edit Recipe](#) dialog box. A warning message will be displayed after each measurement where the GOF falls below the user-specified **GOF Error**. If the GOF is less than 1 there are several possible causes:

- a) **Nonuniformity** – Any variation of layer thickness, or presence of roughness, within the measurement spot will result in a reduction in reflectance. In severe cases the interference peaks may disappear entirely.

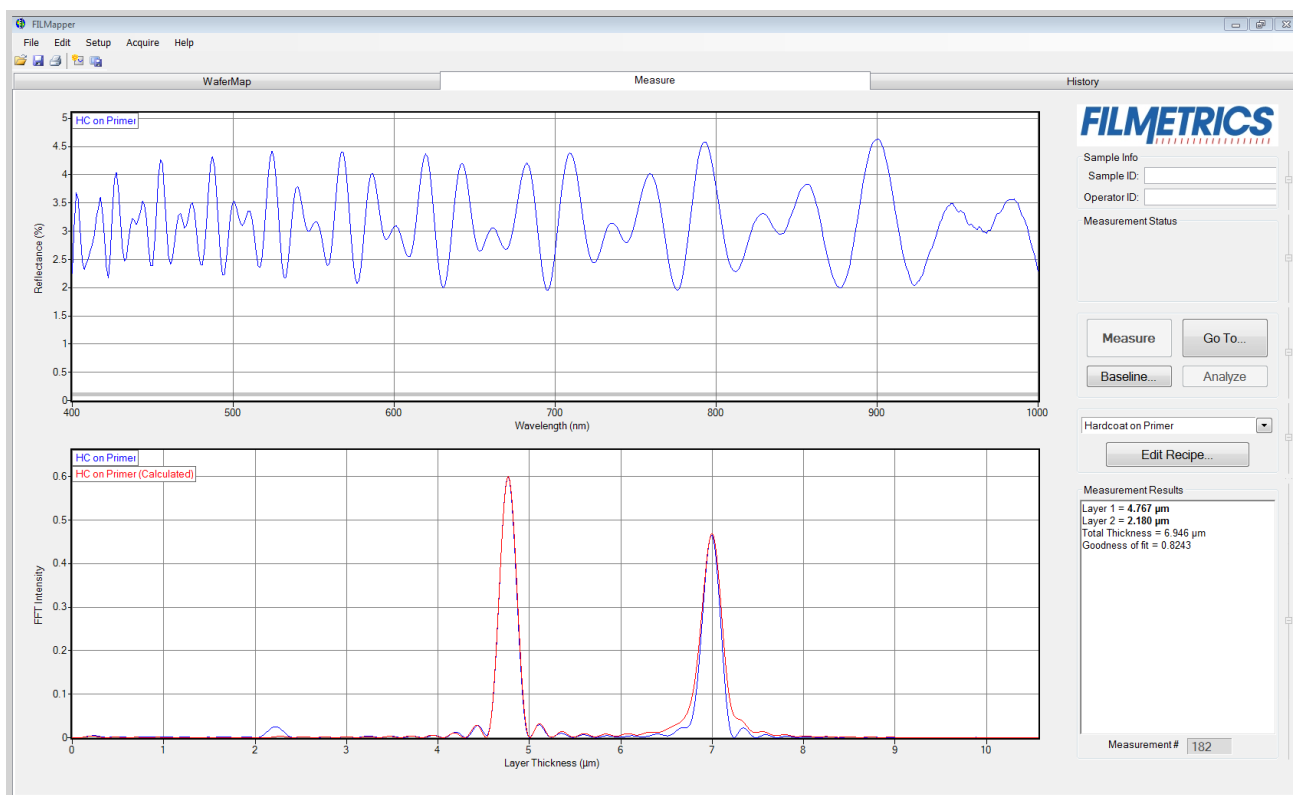
- b) **Incorrect Structure Definition** – If the refractive index of one or more layers in the structure is different from what is described in the recipe, then there will be some mismatch between the blue curve and the red curve.

c) **Graded Interfaces** – The amplitude of the peaks in the spectrum depends on both the size of the change in refractive index at each interface in the layer structure and the sharpness of the interface. For example, in many hardcoat samples there is some degree of layer intermixing at the interface, leading to a weaker than expected reflectance at that interface. In severe cases the peaks may disappear entirely.

4.3 Fast Fourier Transform Mode (FFT mode)

The FFT mode tends to be more robust when measuring very thick films or thick multi-layer stacks, where the total thickness is greater than 5 microns.

To activate FFT mode, select the [FFT \(thickness only\)](#) button located on the [Analysis Options > Analysis Method](#) tab in the [Edit Recipe](#) box.



The **Measure Tab** shows a split screen with the measured spectrum on the top graph and the FFT spectrum on the bottom graph.

In FFT mode, instead of matching the measured reflectance spectrum with a calculated reflectance spectrum, FILMapper identifies the peaks in the FFT Spectrum and uses them to compute the layer thicknesses. The number of possible FFT peaks is $n*(n+1)/2$ where n is the number of layers. Thus, for a two layer structure, we expect to see three peaks in the FFT spectrum.

The image above shows the screen just after measurement of a two layer stack using FFT mode. The upper graph shows a blue curve representing the reflectance spectrum of the sample. The lower graph shows a blue and red FFT spectrum. The blue FFT spectrum is computed from the measured reflectance. The red FFT spectrum is computed from the theoretical reflectance spectrum of a layer stack with the measured layer thicknesses. The small side lobes visible on either side of the two tall peaks are artifacts of the FFT process and can generally be ignored. The only time the side lobes will cause a problem is if a weak peak from a multi-layer sample is very close to a much stronger peak. If this case occurs FILMapper may lock onto one of the side lobes by mistake and it may not be possible to measure the layer thickness associated with the weak peak. Reducing the **Constraint** and/or increasing the guess for the thickness for the layer with the weak peak may be helpful in getting FILMapper to lock onto the weak peak. If the peak is too weak to reliably measure it is best to change the layer structure definition so that the layer corresponding to the weak peak is eliminated.

Along with the measured layer thicknesses, the **Results** text box displays important information about the measurement. This important information includes the [Goodness Of Fit \(GOF\)](#) and a description of which peaks were used to determine the measured layer thicknesses. In the figure above layer 1 thickness is determined based on the position of the peak located at 4.780 microns and layer 2 thickness is determined using the peak corresponding to layers 1+2 (7.011 microns). Notice that the thickness of layer 2 is not exactly equal to $7.011 - 4.780 = 2.231$ microns. FILMapper computes a thickness for layer 2 of 2.113 microns because it precisely accounts for the fact that layer 2 has a different refractive index than layer 1.

Discussion of GOF:

A perfect match between measured and theoretical FFT spectra will result in a **GOF** of 1. To ensure accurate results the user may set a minimum acceptable **GOF** value by entering a number between 0 and 1 into **GOF Error** on the [Alarms](#) settings in **Edit Recipe**. A warning message will be displayed after each measurement where the **GOF** falls below the user-specified **GOF Error**. If the **GOF** is less than 1 there are several possible causes as follows:

a) **Nonuniformity** – Any variation of layer thickness within the measurement spot will result in a reduction in the FFT peak heights. In order to permit easy visual interpretation of the FFT results FILMapper always scales the amplitude of the red curve so that it matches the blue curve. However, if the scaling factor is not 1.0, FILMapper reports a reduced GOF even if the red curve appears to exactly match the blue curve on the screen.

b) **Incorrect Structure Definition** – If the refractive index of one or more layers in the structure is different from what is described in the layer structure, then the FFT peak amplitudes in the blue curve will not match the peak heights in the red curve. The software will attempt to scale the red curve, but if there is more than one FFT peak present, the scaling will only result in one correct peak height. If you wish to view the impact of changing the refractive index of one or more layers, simply change the refractive index in the **Edit Recipe** dialog box and click **Analyze**. If there is only a single layer you will notice that the GOF will change, but the red curve should not change much. If there are multiple layers in the structure you will notice that the relative peak heights in the red curve will change when you click **Analyze**.

c) **Graded Interfaces** – The amplitude of the peaks in the FFT spectrum depends on both the difference in refractive index at each interface in the layer structure and the sharpness of the interface. In many common samples you will find that there is some degree of layer intermixing at the interface, leading to a weaker than expected reflectance at that interface. The FFT peak(s) associated with the intermixed interface will suffer a reduced amplitude and in severe cases the peaks may disappear entirely.

5. Advanced Features

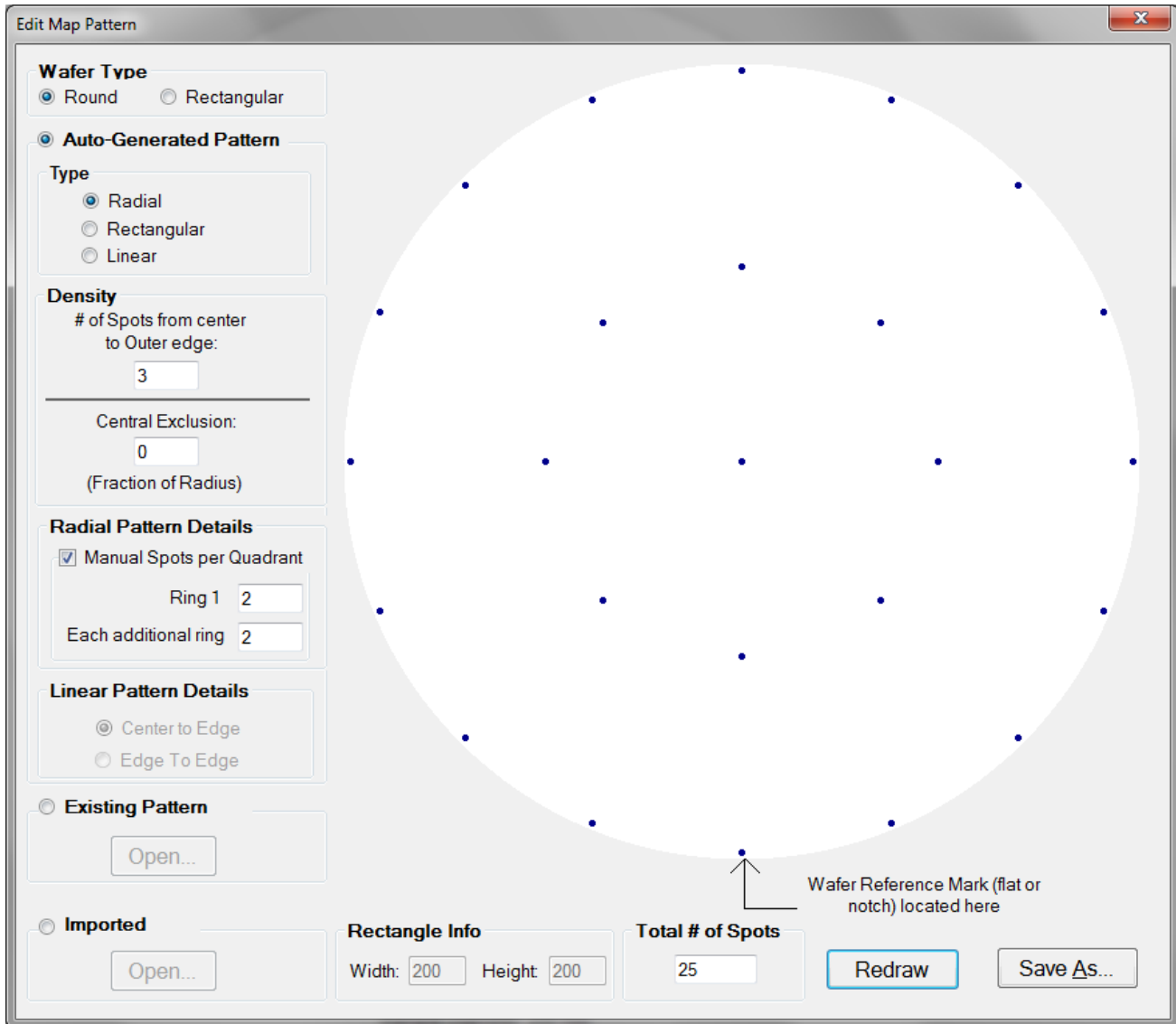
This section describes several advanced features available within FILMapper. This includes the creation of new map files, editing those files within Windows Excel, and how to create and edit n and k files.

[Editing Map Files Using Excel](#)

[Creating and Editing \$n\$ and \$k\$ Files](#)

5.1 Creating New Map Patterns

The **Edit Map Pattern** tool is best used for simpler maps on blanket wafers. For more complex maps, see the Recipe Tab. To create a new wafer map pattern, go to the [Wafer Map Tab](#) and select [Edit > Map Pattern...](#) Once selected, a new window appears which allows parameters to be adjusted to create a custom wafer map.



1. Select the shape of the wafer to be either **Round** or **Square**.
2. Select how the measurement points are distributed on the sample. The alignment can be **Radial (Polar)**, **Rectangular**, or **Linear**.
3. Control the measurement point density. The **# of Spots from Center to Outer Edge** specifies how many points are placed in a line between center and edge. The **Central Exclusion** specifies how much of the center (if any) should be excluded from measurement.
4. Select how many spots are in each quarter section of the ring (when the **Radial** pattern type is selected). When **Manual Spots per Quadrant** is not selected, **Ring 1** is automatically set to 1, and **Each additional ring** is automatically set to 2.

5. Select whether the measurement points should span the **Center to Edge**, or the **Edge to Edge** (only available when the Linear pattern type is selected).
6. Use **Redraw** to refresh the wafer map based on the current settings to make sure the map is correct.
7. **Save** the wafer map to a file, for subsequent use in a **Recipe**.

The user can also open an **Existing Pattern** for editing, or **Import** one that has been [created using Excel](#).

5.2 Editing Map Files Using Excel

Map files can be edited further using Microsoft Excel in order to create more complex patterns. The *.pat file created by FILMapper can be imported into Excel for editing and saved as a comma-delimited file. The newly edited file can then be opened using FILMapper to create more intricate map patterns. The example below shows how to create an “X” pattern starting with the default pattern.

Example: Creating an “X” map pattern starting with the default map pattern

Step 1: Create a new map file

In the map window, go to [Edit > Map Pattern...](#) Using a **Round** wafer type and a **Radial** pattern type, select 3 for # **Spots from center to Outer Edge**. Select **Manual Spots per Quadrant** and use 2 for **Ring 1** and **Each additional ring**.

Save this default map pattern as **Custom**.

Step 2: Import the map pattern into Excel

Using Excel, open the file **Custom.pat**. This file can be found in **C:\Program Files\FILMapper\Patterns\Custom**. (Note: If the file does not appear, in the **Open** dialog box, choose **All Files (*.*)** under File Type.)

You will be prompted to import this file; when prompted select **Delimited** and click **Next**. When prompted, only select **Comma** for the **Delimiters**.

Step 3: Edit map pattern in Excel

Starting in the fourth row, the values are stored as x-y coordinate values, as a fraction of the radius of the wafer. When generating new maps, values can be entered as either a fraction of the radius of the wafer or a discrete number as long as all values are to the same scale. To create the “X” pattern, delete the highlighted rows shown in Figure 4.1, so that there are no empty rows between values. Also delete the first two rows by selecting rows 1 and 2 and selecting **Delete** from the **Edit** menu.

	A	B	C	D	E
1	Version	1			
2	GUID	9edf4a33d97a4c2183ce5f2dfd471ca8			
3	25				
4	0	0			
5	0.5	0			
6	0.353553	0.353553			
7	3.06E-17	0.5			
8	-0.35355	0.353553			
9	-0.5	6.12E-17			
10	-0.35355	-0.35355			
11	-9.18E-17	-0.5			
12	0.353553	-0.35355			
13	1	0			
14	0.92388	0.382683			
15	0.707107	0.707107			
16	0.382683	0.92388			
17	6.12E-17	1			
18	-0.38268	0.92388			
19	-0.70711	0.707107			
20	-0.92388	0.382683			
21	-1	1.22E-16			
22	-0.92388	-0.38268			
23	-0.70711	-0.70711			
24	-0.38268	-0.92388			
25	-1.84E-16	-1			
26	0.382683	-0.92388			
27	0.707107	-0.70711			
28	0.92388	-0.38268			

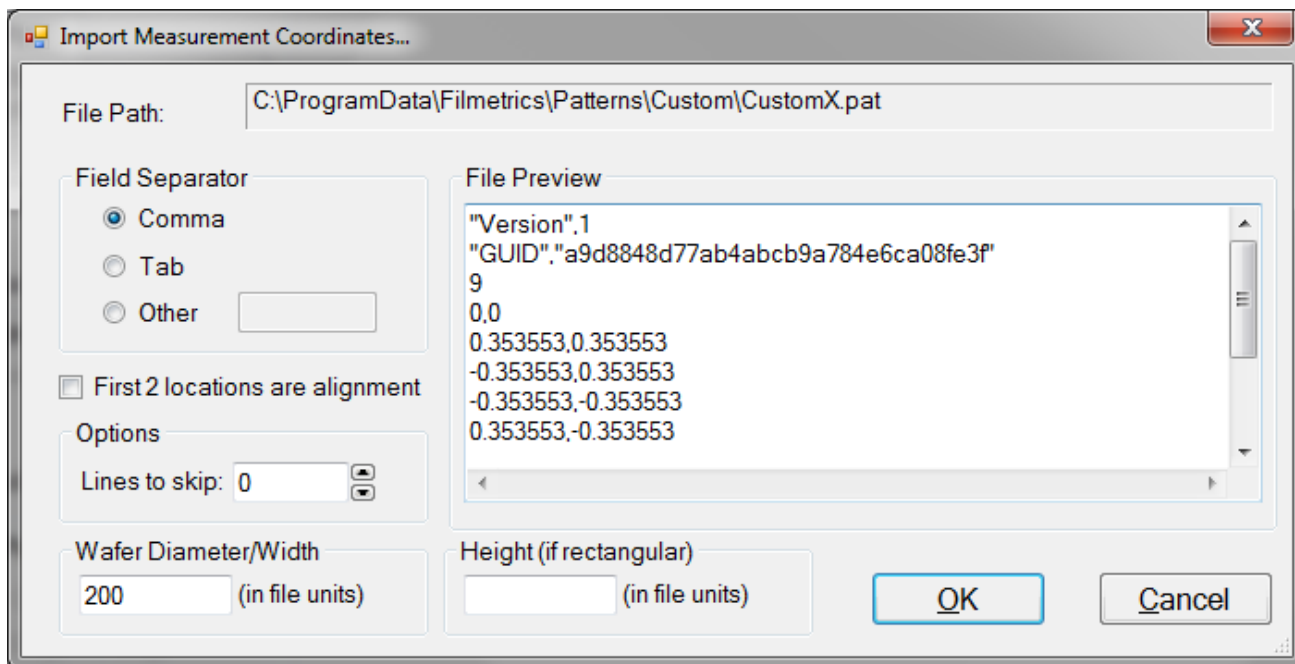
Delete the highlighted cells to leave the desired coordinates.

Step 4: Save map pattern

After the modifications have been made, select **File>Save**. Check to make sure that the **File Name** box is "**CustomEdit.pat**" (note that quotation marks must be used to enclose the filename in Excel to force the extension to **.pat**) and that the **File Type** is **CSV (Comma delimited) (*.csv)**. Then click **Save**.

Step 5: Import the Map Pattern

In FILMapper, click on the **Edit** menu and select **Map Pattern....** Enable the radio button for **File-Imported Pattern**, and then switch to the **Imported Pattern** tab and click **Open....** The following dialog will open.



Increase the **Options > Line to skip** value until the first value visible in the list is the first coordinate in the series. The **Wafer Diameter/Width** and **Height** must also be set here according to the values you used for the coordinate scale you used. If you used fractional values, set the Wafer Diameter/Width, and Height for rectangular samples, to 2 (-1 to 1). If you used whole values, simply enter the dimensions of your sample. Click **OK** when finished.

Step 6: Save the Pattern File

The new pattern file should now be displayed in the **Edit Map Pattern** Window. Confirm it matches the expected pattern, and then save the new pattern using the **Save As** button.

Note: If the wafer map does not show up as described, open the file **C:\Program Files\FILMapper\Patterns\custom\Custom.pat** using a text editor, such as Microsoft Notepad. Check to see that the first row does not contain a comma. If it does, delete the comma and save the file.

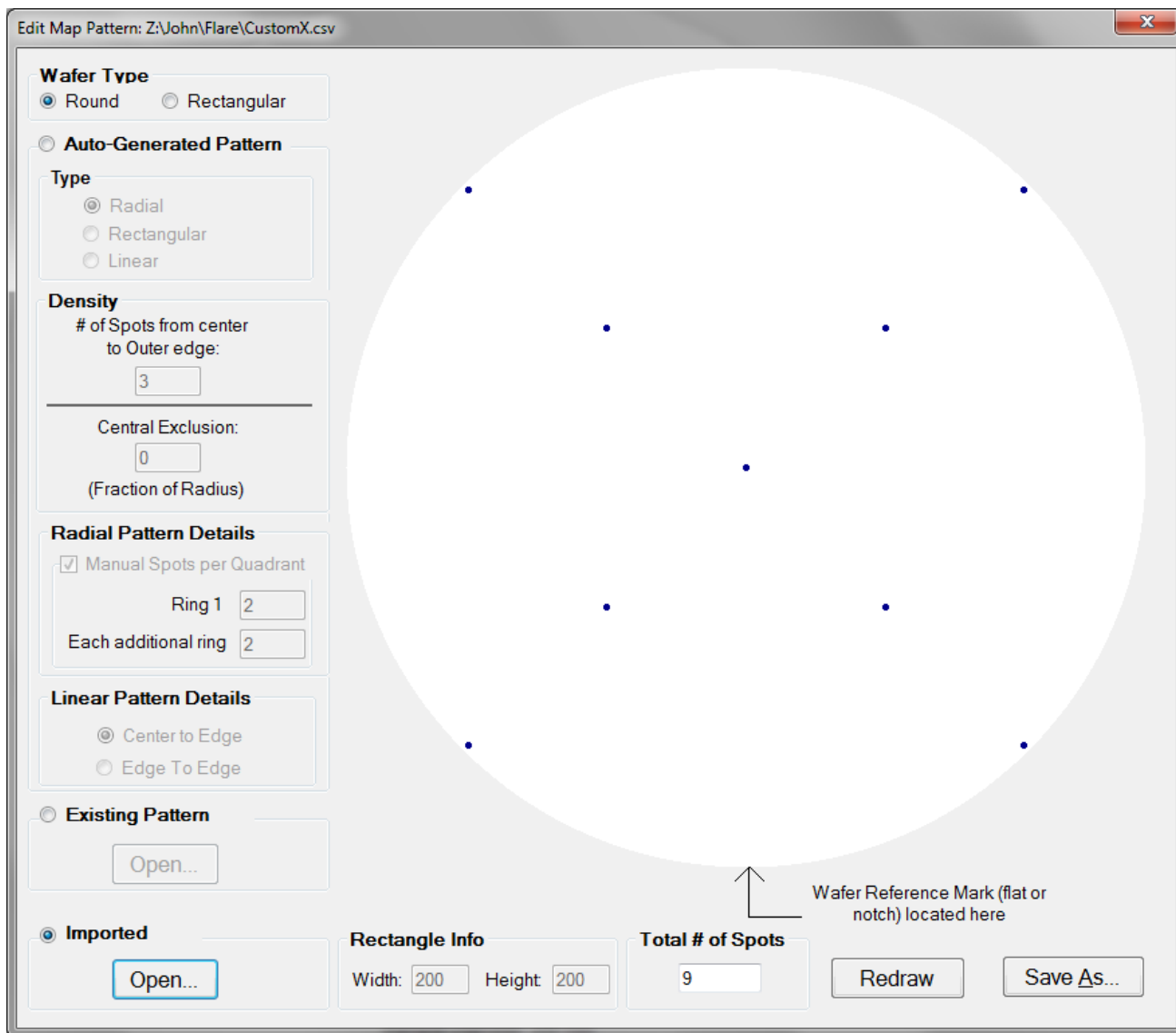


Figure: "X" pattern created using Excel.

Step 7: Load map pattern in FILMapper

In FILMapper, click the **Edit...** button next to the **Recipe** pull-down menu if you are in the Wafer Map Tab, or **Edit Recipe** if you are in the Measure Tab. Click the **Wafer Map** tab and select **Custom** for the **Coordinate System**. Under **Custom Name**, all the names of custom map files will be listed. Here, select **Custom Edit**, and then click **OK**. In the Wafer Map Tab, you should now see the "X" pattern you created. FILMapper is capable of automatically resizing the map pattern after it has originally been created, so there is no need to create multiple versions of the same file. Simply adjust the wafer size underneath the **Wafer Map** tab.

5.3 Creating and Editing n and k Files

Creating new n and k files

New n and k files can be created by going to [Edit > Material Library...](#) Clicking the **New** button will allow the user to define a new material file. Once clicked, while the **Default Model** is selected, the user can manually enter wavelength versus n or wavelength versus k values. It is also possible to copy and paste values into the columns if the data is available.

The user can also select **Custom Model**. While this is selected, clicking on the **Model...** button allows the user to create n and k files using predefined mathematical models.

Once completed, clicking **Save As...** will save the new file as a custom material for later use.

Creating n and k files from a calculated spectrum

Files for n and k can be created directly from a calculated spectrum, where n and k are measured. Once a spectrum is analyzed, go to **File>Save Measured n and k ...** This will save your n and k files as a custom material which can be loaded into the user recipe.

Editing n and k files

Existing material files can be edited by going to [Edit > Material Library...](#) There, the user can load a material file by clicking **Open**. Values can then be changed manually. Clicking **Save** will save over the original file for later use. Use **Save As** to save the edited file under a new name.

Converting Microsoft Excel files into FILMapper n and k files

For wavelength versus n or wavelength versus k data saved in Excel (*.xls) format, the data can be directly saved as material files that can be read by FILMapper.

For .nnn and .kkk files.

For both n and k files, the data should follow the format shown below, where the wavelength values, in units of nanometers, are in the first column, and the n or k values are in the second. Note that the version number (cell B1) refers to version of the file. For this cell, you can use 1. The material number (cell B2) refers to what material category the file corresponds to. The material categories (and their corresponding numbers) are: Metal (1), Semiconductor (2), Dielectric (3), Other (4), and Photoresist (6). By putting the correct value for the material number, the file will automatically be sorted into the correct category when selecting the material in the [Edit Recipe](#) window.

To save the file created by Microsoft Excel, go to **File>Save As...** For **Save as Type:** choose **CSV (Comma delimited) (*.csv)**. For n files, save the file as "**FILENAME.nnn**", and for k files, save the file as "**FILENAME.kkk**" (FILENAME represents the name you wish to call the file; note that quotation marks must be used to enclose the filename in Excel to force the extension to **.nnn** or **.kkk**). The file can then be saved to the desktop, and [Imported](#) using the **File > Import > Material File** option

	A	B
1	Version	1
2	Material	3
3	206.6	1.543
4	226.7	1.5228
5	248.3	1.5084
6	265.2	1.5
7	280.3	1.494
8	302.2	1.4872
9	330.3	1.4805
10	361.1	1.4751

For .fitnk files.

The data should follow the format of shown below, where the wavelength values, in units of nanometers, are in the first column, index of refraction (n) in the second, and extinction coefficient (k) if present, in the third.

The first few columns of the file should be identical to the figure below the only exception being cell B3 which should contain a number describing the material category. The material categories (and their corresponding numbers) are: Metal (1), Semiconductor (2), Dielectric (3), Other (4), and Photoresist (6).

To save the file created by Microsoft Excel, go to **File > Save As...** For **Save as Type:** choose **CSV (Comma delimited) (*.csv)**. Save the file as "FILENAME.fitnk" (FILENAME represents the name you wish to call the file; note that quotation marks must be used to enclose the filename in Excel to force the extension to .fitnk). The file can then be saved to the desktop, and [Imported](#) using the **File > Import > Material File** option

	A	B	C
1	Version	1	
2	Compat. Version	1	
3	Material	3	
4	File Information		
5	Wavelength (nm)	n	k
6	206.6	1.543	0
7	226.7	1.5228	0
8	248.3	1.5084	0
9	265.2	1.5	0
10	280.3	1.494	0
11	302.2	1.4872	0
12	330.3	1.4805	0
13	361.1	1.4751	0

6. Theory of Operation

This section describes how the instruments work and includes the theory the measurements are based on, specifics about the hardware, and more detail about the baseline measurement.

[Measurement Theory](#)

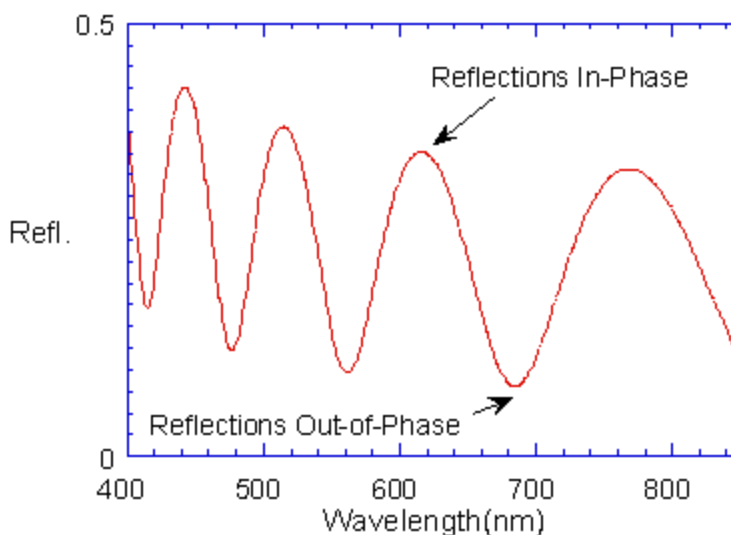
[Thickness Measurement Details](#)

[Hardware Operation](#)

[The Baseline Measurement](#)

6.1 Measurement Theory

Our instruments measure thin-film characteristics by either reflecting light from, or transmitting light through the sample, and then analyzing this light over a range of wavelengths. Because of its wave-like properties, light reflected from the top and bottom interfaces of a thin film can be in-phase so that reflections add, or out-of-phase so that reflections subtract. Whether the reflections are in- or out-of-phase (or somewhere in between) depends on the wavelength of the light, as well as the thickness and properties of the film (e.g., reflections are in-phase when $\lambda = (2*n*d)/i$, where λ is the wavelength, n is the refractive index, d is the film thickness, and i is an integer). The result is characteristic intensity oscillations in the reflectance spectrum (see Figure below). In general, the thicker the film, the more oscillations there are in a given wavelength range.



Example of reflectance spectrum with oscillations.

The amplitude of the oscillations is determined by the refractive index and extinction coefficient of the films and substrate. Therefore, by analyzing the period and amplitude of these oscillations, our instruments can determine thickness of multiple thin films.

6.2 Thickness Measurement Details

Optical thin-film thickness measurements require the successful completion of two tasks: acquisition and then analysis of an accurate reflectance spectrum. To determine film thickness, FILMapper calculates a reflectance spectrum that matches as closely as possible the measured spectrum. FILMapper begins with an initial guess for what the reflectance spectrum should look like theoretically, based on the user's input of a film structure for the sample. Then FILMapper varies the parameters it is solving for until the calculated reflectance spectrum matches the measured data. Mathematically, this procedure is complicated by the fact that as the thickness of the films in the calculation is varied there can be many near matches. Therefore, an approach that simply homes in on a solution by finding successively better approximations will not work unless the starting guess for optical thickness is within approximately 1000 Å if the actual thickness.

FILMapper avoids homing in on a false solution by searching the entire acceptable thickness range to determine the thickness that gives the best possible match between the measured and calculated spectra. The thickness range searched is determined by the initial guess for thickness together with the thickness constraint. Since the time to find a solution is proportional to the range of thicknesses being searched it is beneficial to provide an initial guess close to the thickness of the films to be measured.

6.3 F50 Hardware Operation

The F50 performs two distinct functions: data acquisition and data analysis. Data analysis specifics are discussed in the [Software Overview](#) section. In this section we describe how the F50 acquires accurate spectral reflectance data.

Light is supplied by a tungsten-halogen bulb that generates light from approximately 375 nm to 3000 nm. This light is delivered to and collected from the sample through a fiber-optic cable bundle and a lens. The intensity of the reflected light is measured at 512 different wavelengths with a spectrometer. The F50 spectrometer uses a diffraction grating to disperse the light and a linear photodiode array to measure the light at the different wavelengths. The photodiode array operates by integrating the current generated by light falling on each of the 512 pixels. After a user-selectable integration time, the accumulated charge in each photodiode is read by the computer. Because a longer integration time results in a larger charge, it is the integration time that determines the sensitivity of the spectrometer. Adjustment of the integration time is used to obtain the proper signal level. Too short an integration time results in a weak, noisy signal, while too long of an integration time results in a saturated signal.

6.4 The Baseline Measurement

The baseline measurement allows the FILMapper software to take into account the response inherent to the reflectance measurement hardware. It does this by measuring a reflectance standard and by taking a “dark” reading. In any optical system there are many components whose characteristics vary with wavelength (e.g., the output of the light source and the sensitivity of the spectrometer). However, when reflectance measurements are made, only variations in reflectance vs. wavelength due to the sample under test are of interest. Therefore, FILMapper must perform a calibration to determine the spectral response of the system. This is done by making a measurement of a reflectance standard that has known reflectance characteristics. Note that it is not necessary for the reflectance standard to be the same as the substrate upon which films to be measured reside. The only purpose served by the reflectance standard is to permit calibration of the optical system. For example, it is possible to use a Si wafer as the reflectance standard and then measure films on GaAs, InP, glass, plastic, etc.

After the reference measurement is made a dark reading is taken. A non-zero dark level is due to current leakage inherent to photodiodes, which causes each photodiode in the array to slowly charge up even when no light enters the spectrometer. Thus, in order to make an accurate measurement of the light entering the spectrometer, it is necessary to subtract this “dark” current contribution. This is the purpose of the background reading, which measures the magnitude of the dark current for a given integration time. When a “dark” measurement is made, a spectrum is measured that represents the signal generated by the spectrometer when a sample of zero reflectance is measured. To simulate a sample with zero reflectance during a “dark” measurement, a specularly reflecting sample can be held at an angle with the light source turned on, or in the case of the UV light source, the shutter may simply be closed.

Due to drift in the light source and temperature of the spectrometer electronics, it is a good idea to take a baseline periodically.

How to Contact Us

We welcome suggestions from our users on ways to improve our software and hardware. Please send us any suggestions you may have for improvements in the help file or new features you would like to see in the software.

We may be reached by phone at +1-858-573-9300, by fax at +1-858-573-9400, by the Contact Us Now form on [our website](#), or by e-mail at support@filmetrics.com.

7. Appendices

This section contains information on various topics as listed below:

[Performance Specifications](#)

[How to Replace the Light Bulb](#)

[Application Note: Silicon Nitride](#)

[Automation and Data](#)

[Software License Agreement](#)

7.1 Performance Specifications

	F50-UV	F50-UVX	F50	F50-EXR	F50-NIR	F50-XT	F50-s1310
Wavelength Range:	190-1100 nm	190-1700 nm	380-1050 nm	380-1700 nm	950-1700 nm	1440-1690 nm	1280-1340 nm
Thickness Measurement Range*:	5 nm-40 μ m	5 nm-250 μ m	20 nm-70 μ m	20 nm-250 μ m	100 nm-250 μ m	0.2 μ m-450 μ m	7 μ m-2 mm
Minimum Thickness to Measure n and k *:	50 nm		100 nm		500 nm	-	-
Accuracy*: The greater of	0.2% or 1 nm		0.2% or 2 nm		0.4% or 3 nm	0.4% or 4 nm	0.4% or 50 nm
Precision:	0.02 nm ¹				0.1 nm ¹	1 nm ¹	5 nm ²
Stability:	0.05 nm ³				0.12 nm ³	1 nm ³	5 nm ⁴
Spot Size:	Standard 1.5mm, Optional down to 20 μ m					600 μ m	10 μ m
Light Source MTBF:	D2: 2000 Hour, Halogen: 1200 Hour		Halogen: 1200 Hour				SLED: >10 year

Power Requirements:

100-240 VAC, 50-60 Hz, 100 Watts

Dimensions:

14W x 19D x 11H (in).

35.5W x 48.3D x 28H (cm).

Weight:

35 lbs. (16 kg).

Speed (typical, with vacuum chuck):

	200 mm Chuck	300 mm Chuck
Sample Size:	≤ 200 mm diameter	≤ 300 mm diameter
Speed:	5 points - 5 sec. 25 points - 14 sec. 56 points - 29 sec.	5 points - 8 sec. 25 points - 21 sec. 56 points - 43 sec.

* Material dependent.

¹ 1 σ of 100 measurements of 500 nm SiO₂-on-Si. Average of 1 σ over 20 successive days.

² 1 σ of 100 measurements of 100 μ m SiO₂-on-Si. Average of 1 σ over 20 successive days.

³ 2 σ of daily average of 100 measurements of 500 nm SiO₂-on-Si over 20 successive days.

⁴ 2 σ of daily average of 100 measurements of 100 μ m SiO₂-on-Si over 20 successive days.

Specifications subject to change without notice.

7.2 Application Note - Si₃N₄

Theoretical Underpinnings

The refractive index of a single layer film is related primarily to the depth of the minima found in the measured reflectance. The reflectance at the interference fringe minima of a film deposited onto Si is zero when the refractive index is near 1.97. The reflectance at the fringe minima for a film with a refractive index of 2.00 is the same as that for a film with a refractive index of 1.94. Therefore, it can be difficult to unambiguously determine the refractive index from a reflectance measurement. However, for most films the user knows that the refractive index is either always greater than or always less than 1.97 so there is no uncertainty. Silicon nitride is one of the few rare films whose refractive index spans this critical range. Fortunately, there is a solution for silicon nitride that allows us to determine which of the two possible refractive index values is correct. This is done by measuring both n and k for silicon nitride and by realizing that silicon nitride with a refractive index larger than 1.97 has measurable absorption (non-zero k) at wavelengths less than 420 nm. Thus, to get good results for n the widest possible wavelength range should be used (especially going down to short wavelengths) and the user should simultaneously measure both n and k .

[Continue to Discussion of \$n\$ and \$k\$ Measurement.](#)

Discussion of Si₃N₄ n and k Measurement

Silicon nitride is a dielectric material commonly used in semiconductor fabrication processes. The refractive index of stoichiometric Silicon Nitride is 2.05 at 633 nm. However, in practice the refractive index of deposited films can vary from 1.7 or less (films containing excess hydrogen or oxygen) to as high as 2.5 or more (Si rich films). The measurement of n and k is complicated by the fact that this refractive index range (1.7 to 2.5) spans a critical range for films deposited on Si substrates. In order to get an unambiguous result for measurement of n , the structure description should be set by choosing "Si₃N₄ (Si Rich)" as the material for the silicon nitride layer. To confirm that the proper model is chosen, go to the options tab and note that the model displayed is "Si₃N₄". If the Si₃N₄ model is not displayed in the [nk Model](#) list and Si₃N₄ is not in the list of models, then newer software is required. It is important that both n and k be measured simultaneously (put a check mark for n and for k in the [Edit Recipe>Film Stack](#) dialog box). When using the Si₃N₄ model the constraints for n and k should be set to large values (at least 5). If the film is very thin (less than 50 nm), it may be necessary to set the material to "Si₃N₄" or "Si₃N₄-thin", instead of "Si₃N₄ (Si Rich)", to get reproducible results, but this should only be used as a last resort.

[Continue to Step by Step Instructions for measuring Si₃N₄.](#)

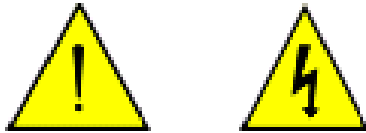
Step-by-step instructions for measuring silicon nitride on Si

1. Start FILMapper and click the [Edit Recipe](#) button.
2. Set the material for the **Medium** to "Air".

3. Set the material for **Layer 1** to “Si₃N₄ (Si Rich)”.
4. Enter a guess for the layer thickness of the silicon nitride into the thickness box for **Layer 1**.
5. Put check marks in the d, n, and k check boxes for **Layer 1**.
6. Set the constraint for d to 75%.
7. Set the constraint for n to 5 and the constraint for k to 5.
8. Set the material for the **Substrate** to “Si”.
9. Select **Grid** from thickness solver options pull down menu under **Thickness**.
10. Go to the [Analysis Options](#) tab.
11. Make sure there is no check mark for **Compensate for: > Unmodelled Back-side reflections**.
12. Under [Advanced Analysis Options](#), set the number of **Iterations** to “600” and set **GOF greater than** to “0.999”.
13. Under [Data Selection](#) select **Fixed Range** and enter “From: 200” and “To: 1100”.
14. Click **Save As** and give the recipe a name.
15. Follow the instructions in [Example B](#) for measuring thickness and optical constants.

Light Bulb Replacement

NOTE: These instructions apply to VIS, NIR, and EXR systems only. For UV and UVX systems, please see the separate users manual for the external light source.



*** * Warning: * * Hazardous voltages are present within the unit. Never attempt any maintenance without disconnecting the power cord.**

Step by step:

1. Exit FILMapper program and turn off your computer.
2. Disconnect power cable from the F50 from the back of the unit.
3. The U-shaped cover is held down with eight #6-32 button-head cap screws (four on either side of the lid). Unscrew them with a 5/64 hex wrench.
4. Gently lift and separate the cover and slide it out from below the stage.

*** * Warning: * * Caution, avoid touching any interior components, other than the lamp, lamp base, and housing.**

5. Loosen lamp set screw (counter clockwise).
6. Insert new lamp fully into lamp housing. Do not touch the lamp glass.
7. Secure lamp with setscrew (clockwise). Do not over tighten.
8. Plug new lamp into the lamp power connector. Do not test lamp with lid removed.
9. Replace the lamp housing and screws. This is imperative, as the cover should NOT be left off during use. Insert cord into wall supply and restore power to the unit.

10. The lamp should illuminate and the fan should turn when power is restored. The light switch on the front of the F50 box must be turned on.

7.3 Software Automation

Measurements can be automated and additional data analysis can be performed by user-supplied software. The mechanism by which this occurs is either by using the `FIRemote` class, which is part of `FILMapper.exe` or by using the `FIRemoteMapCOM` dll (standard 32-bit version of `FILMapper`). Accessing the `FIRemote` class directly using a .NET programming language such as C# offers the most flexibility and is the recommended approach. Alternatively, the `FIRemoteMapCOM` dll can be referenced from Microsoft Office programs and simple software procedures can be implemented there instead. The `FIRemoteMapCOM` dll includes fewer methods than `FIRemote`. Documentation for `FIRemoteMapCOM` dll is located at the end of this section.

FIRemote Class

`FIRemote` is exposed as a public assembly and is accessible using the Microsoft .NET programming environment. The best way to learn how to use the `FIRemote` class is to look at the example program and source code which are automatically installed as part of the `FILMapper` software. Assuming that the `FILMapper` program is installed in the default location, the example software can be found in `C:\Program Files\Filmetrics\FILMapper\SourceCode\FIRemoteTest\` (look in `c:\Program Files (x86)` if 64-bit operating system and using the 32-bit version of `FILMapper`). Additionally an executable, `FIRemoteTest.exe`, is located in the `FILMapper` folder. All the available commands can be tested using `FIRemoteTest.exe`.

In order to set up a development environment for running and debugging code, the file system must be set up so that the `FILMapper.exe` is located in the same folder as the client program that is being developed. Since `FILMapper` expects to find its dependent files in the same directory as the executable, this means that the entire contents of the `FILMapper` folder must be copied to the build output folder. For example, if the software development environment output folder is located in `C:\SourceCode\TestSln\TestPrj\bin\Debug\`, then all the files and subfolders from `C:\Program Files\Filmetrics\FILMapper\` must be copied to `C:\SourceCode\TestSln\TestPrj\bin\Debug\`.

Some of the methods listed in the following reference a `SystemGuid`. In the terminology used in this document, a Measurement System is an object comprising one or more measurement channels, but with operations that can be performed simultaneously on all the channels in the system. The `SystemGuid` is used to distinguish between multiple, simultaneously-connected measurement systems. Examples of measurement systems with multiple measurement channels include the F32. Documentation for methods applying only to such measurement systems can be found in the `Less Commonly Used Methods` section. In addition, some methods will accept either a `SystemGuid` or a `ChannelGuid`. Such methods thus will execute an operation either on a single channel, or simultaneously on all channels of a system.

Note that the `FIMeasResults` object which is returned by the `Measure` and `AnalyzeSpectrum` methods has a large number of member functions and properties. Since the names are all self-explanatory, we have not attempted to list all of the members here. The reader should use the Object Browser which is built into Microsoft Visual Studio in order to discover the available properties and methods.

FILMapper 7 and 8 are based on the Microsoft .NET 4.0 Client Profile Framework. FILMapper 6 was based on the .NET 2.0 Framework. Executable client programs and source code projects that were built for FILMapper 6 will need to be recompiled, targeting the .NET 4 Client Profile Framework. The Visual Studio development environment will display a warning message if you reference an assembly that is targeting a framework different from that targeted by your development project. You must use Visual Studio 2010 or newer, because the .NET 4 Framework was released with Visual Studio 2010. Do not attempt to use Visual Studio 2008 or older because it will not work. The FIRemoteTest source code is compatible with Visual Studio 2010. The FIRemoteTest solution file can be opened with newer versions of Visual Studio, which will automatically upgrade the solution and project.

32-bit vs 64-bit Client Software

To maintain backward compatibility, the 32-bit version of FILMapper is shipped by default. If your client software must interact with software modules which are only available in 64-bit versions, then you must use a 64-bit version of FILMapper instead. Contact Filmetrics for access to an installer for the 64-bit version of FILMapper.

Reference for FIRemote Class

Methods, Property and Events:

[New](#)

[AcquireSpectrum](#)

[ActivateChannelDisplayTab](#)

[AnalyzeSpectrum](#)

[AuthenticateRefBac](#)

[BaselineAcquireBackgroundAfterRef](#)

[BaselineAcquireReference](#)

[BaselineAcquireReferenceT](#)

[BaselineAcquireReferenceUsingOldSampleReflectance](#)

[BaselineAcquireSpectrumFromSample](#)

[BaselineCommit](#)

[BaselineSetRefMat](#)

[BaselineShowDialog](#)

[GUIVisible](#)

[HistoryDeleteAllResults](#)

[IntegrationCycles](#)

[IntegrationTime_ms](#)

[MaximumSamplingTime](#)

[MeasurementTimingMode](#)

[MeasChannelGuid](#)

[MeasChannelGuids](#)

[MeasChannelHWName](#)

[MeasChannelHWSerialNumber](#)

[MeasChannelName](#)

[Measure](#)

[NumberOfChannels](#)

[NumberOfSpectrometers](#)

[NumberOfSubSystems](#)

[OpticsConfiguration](#)

[OpenSpectrum](#)

[OpenSpectrumFromBuffer](#)

[OperatorID](#)

[RecipeInfo](#)

[SampleID](#)

[SaveSpectrum](#)

[SaveSpectrumToBuffer](#)

[SetAnalysisWavelengthRange](#)

[SetMaterial](#)

[SetN](#)

[SetRecipe](#)

[SetRoughness](#)

[SetThickness](#)

[SetThicknessRange](#)

[SpectrometerDiagnostics](#)
[SpectrometerType](#)

Less-Commonly-Used Methods

The following methods are only rarely used. Methods which refer to a System are used with the F32 and F37 thin film monitoring systems. Many methods accept either a measSystem or a measChannel guid. However, some methods are relevant only to a single channel. If you supply a measSystem guid as the argument for one of these methods, an exception will be thrown.

[ActivateMonitorDisplayTab](#)
[BaselineHardwareAdjustInhibit](#)
[BaselineExistsAndIsAuthenticated](#)
[GeneralPurposeIOIsSupported](#)
[GeneralPurposeIOReadValue](#)
[GeneralPurposeIOSetValue](#)
[GetBaselineHardwareAdjustStatus](#)
[MaterialPath](#)
[MaterialPathCustom](#)
[MeasSystemGuid](#)
[MeasSystemGuids](#)
[MeasSystemHWName](#)
[MeasSystemName](#)
[NumberOfSystems](#)
[RecipePath](#)
[RecipePathCustom](#)
[SaveImage](#)
[SetAutoFocus](#)
[SetRecipeModeToSpectrumAnalysis](#)
[SetRecipeSpectrumAnalysis](#)
[ShutdownRequestedHandler](#)
[ShuttingDown](#)
[SystemAutoSave](#)
[SystemAutoSaveBaseFileNameAndPath](#)
[SystemMeasure](#)
[SystemStartMonitoring](#)
[SystemStopMonitoring](#)
[SystemMeasurementCompletedEventHandler](#)

FILMapper-Related Methods

[GetStageMotionParams](#)
[ModuleHasMotorizedZStage](#)
[SetStageMotionParams](#)
[WaferMapAllFinished](#)
[WaferMapClearHistoryWhenMapStarts](#)
[WaferMapCreateMapFile](#)
[WaferMapCreatePattern](#)

[WaferMapCurrentFileName](#)
[WaferMapCurrentWaferID](#)
[WaferMapDisableMapButtons](#)
[WaferMapGetCurrentStageLocation](#)
[WaferMapGetVacuumIsOn](#)
[WaferMapGetUsableHeightAndWidth](#)
[WaferMapInitXMotion](#)
[WaferMapInitYMotion](#)
[WaferMapInitZMotion](#)
[WaferMapMeasurementControlsPanelLocation](#)
[WaferMapMoveStage](#)
[WaferMapMoveToLoadPosition](#)
[WaferMapMoveToRestPosition](#)
[WaferMapNew](#)
[WaferMapNextFileName](#)
[WaferMapNextWaferID](#)
[WaferMapOpen](#)
[WaferMapRecipeAutoFocusInCenterOnly](#)
[WaferMapRecipeAutomaticAlignmentSampleOrigin](#)
[WaferMapRecipeAutomaticAlignmentSampleRotation](#)
[WaferMapRecipeGetPattern](#)
[WaferMapRecipeSampleCoordinateSystemOrigin](#)
[WaferMapRecipeSaveResultsToDisk](#)
[WaferMapRecipeSetEdgeExclusion](#)
[WaferMapRecipeSetPattern](#)
[WaferMapRecipeSetSampleSize](#)
[WaferMapSetVacuum](#)
[WaferMapResultsFolder](#)
[WaferMapSetCurrentLocationAsSampleOrigin](#)
[WaferMapStart](#)
[WaferMapStateChangedHandler](#)
[WaferMapStop](#)
[ZGetLimitsSampleCoordMm](#)

New

```

Public Sub New(ByVal showFILMeasureGUI As Boolean) (deprecated)
Public Sub New(ByVal showFILMeasureGUI As Boolean, ByRef
theConstructorWarning As ConstructorWarning, ByRef warningMessage As
String) (deprecated)

```

```

Public Sub New(ByVal guiType As GraphicalUserInterfaceType, ByVal
guiStartupState As GraphicalUserInterfaceStartupState, ByVal
guiWindowStartupState As FormWindowState, ByRef theConstructorWarning
As ConstructorWarning, ByRef warningMessage As String)

```

guiType – Determines if the FIRemote user interface and associated objects will be constructed at startup. If *guiType* is set to `None`, then the startup process is accelerated and memory usage is minimized. However, the user interface cannot be displayed at a later time if it is not constructed during the startup process. If *guiType* is set to `Standard`, then the normal graphical user interface is constructed during the startup process.

guiStartupState – Determines whether or not the FIRemote user interface is displayed at startup. Note that this argument has no effect if *guiType* = `None`. If *guiStartupState* is set to `Hidden`, then the user interface will not be visible on screen at the completion of the startup process. If the user interface was constructed at startup, it can be displayed at a later time by setting `GUIVisible = True`.

guiWindowStartupState – If *guiStartupState* is set to `Shown` then the FIRemote User interface window will appear on the screen at the completion of the startup process. Note that this argument has no effect if *guiType* = `None`. The state of the window is controlled by *guiWindowStartupState*. You can set the state to `Maximized`, `Normal`, or `Minimized`.

theConstructorWarning – Returned value of type `ConstructorWarning` (`None` or `StartupRecipeLoadFailure`).

warningMessage – Returned warning message string. Empty if `None`.

Remarks: You can suppress the display of the FIRemote user interface by setting *guiType* appropriately. Typically, you would show the user interface during software development in order to aid in the testing and debugging process. However, there are some applications where it is useful to be able to show and hide the user interface while the software is running. This is accomplished with the `GUIVisible` Property. The constructor warns if the startup recipe has problems loading and a default recipe is loaded instead.

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AcquireSpectrum

```
Public Sub AcquireSpectrum(ByRef spectrumWavelengths() As Single,
ByRef spectrumData() As Single)
Public Sub AcquireSpectrum(ByRef spectrumWavelengths() As Single,
ByRef spectrumData() As Single, ByVal flushPipeline As Boolean)
Public Sub AcquireSpectrum(ByRef spectrumWavelengths() As Single,
ByRef spectrumData() As Single, ByRef secondarySpecWavelengths() As
Single, ByRef secondarySpecData() As Single, ByRef
primarySpecIsReflectance As Boolean)
Public Sub AcquireSpectrum(ByRef spectrumWavelengths() As Single,
ByRef spectrumData() As Single, ByVal secondarySpecWavelengths() As
Single, ByRef secondarySpecData() As Single, ByVal flushPipeline As
Boolean, ByRef primarySpecIsReflectance As Boolean)
```

```

Public Sub AcquireSpectrum(ByVal measChannelGuid As Guid, ByRef
spectrumWavelengths() As Single, ByRef spectrumData() As Single)
Public Sub AcquireSpectrum(ByVal measChannelGuid As Guid, ByRef
spectrumWavelengths() As Single, ByRef spectrumData() As Single,
ByVal flushPipeline As Boolean)
Public Sub AcquireSpectrum(ByVal measChannelGuid As Guid, ByRef
primarySpecIsReflectance As BooleanByRef spectrumWavelengths() As
Single, ByRef spectrumData() As Single)
Public Sub AcquireSpectrum(ByVal measChannelGuid As Guid, ByRef
spectrumWavelengths() As Single, ByRef spectrumData() As Single,
ByVal flushPipeline As Boolean, ByRef primarySpecIsReflectance As
Boolean)

```

measChannelGuid – The GUID of the measurement channel for which a spectrum should be acquired. If multiple measurement channels exist, the *measChannelGuid* must be specified.

spectrumWavelengths – Array to contain wavelengths of measured spectrum data points.

spectrumData – Measured reflectance or transmittance data points.

secondarySpecWavelengths – For systems that can simultaneously acquire reflectance and transmittance such as the F10-RT, array to contain wavelengths of measured secondary spectrum data points. For all other systems, the returned argument is Nothing.

secondarySpecData – For systems that can simultaneously acquire reflectance and transmittance such as the F10-RT, array to contain the measured secondary spectrum data points. For all other systems, the returned argument is Nothing.

flushPipeline – If set to True (default), any data currently being acquired is ignored and new data is acquired. If set to False, data currently being acquired is returned when acquisition is finished.

primarySpecIsReflectance – Indicates whether the primary spectrum data is Reflectance or Transmittance.

Remarks: It is important that you catch exceptions which may occur as a result of calling this method. See the example program for details.

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ActivateChannelDisplayTab

```

Public Sub ActivateChannelDisplayTab(ByVal measChannelGuid As Guid)

```

measChannelGuid – The GUID of the measurement channel of the corresponding Measurement Tab to be selected.

Remarks: After execution, the active tab in the FILMapper GUI will be the specified Measurement Tab. This method should only be executed if multiple measurement channels exist.

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AnalyzeSpectrum

```
Public Function AnalyzeSpectrum(ByVal formatSummaryAsRtf As Boolean)
As FIMeasResults
Public Function AnalyzeSpectrum(ByVal formatSummaryAsRtf As Boolean,
ByVal addToHistory As Boolean) As FIMeasResults
Public Function AnalyzeSpectrum(ByVal measChannelGuid As Guid, ByVal
formatSummaryAsRtf As Boolean) As FIMeasResults
Public Function AnalyzeSpectrum(ByVal measChannelGuid As Guid, ByVal
formatSummaryAsRtf As Boolean, ByVal addToHistory As Boolean) As
FIMeasResults
```

measChannelGuid – The GUID of the measurement channel for which a spectrum should be analyzed and optionally added to history. If multiple measurement channels exist, the *measChannelGuid* must be specified.

formatSummaryAsRtf – The measurement summary returned by the *.ResultsSummary* property of the *FIMeasResults* object can be formatted as either plain text or as rtf. Formatting the summary as rtf is advantageous if it will be displayed to the user because then the full set of information including bold font and colors will be included.

addToHistory – Normally, each analysis result is added to the collection of results displayed in the History area of FILMapper. In some cases, it may be advantageous to suppress the addition of a result to the History area. One example where this may be needed is the case where you wish to analyze a spectrum with two different measurement recipes and then add only the best result to the History.

Remarks: The most-recently acquired spectrum can be analyzed by calling this function.

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AuthenticateRefBac

```
Public Sub AuthenticateRefBac()
Public Sub AuthenticateRefBac(ByVal measChannelOrSystemGuid As Guid)
```

measChannelOrSystemGuid – The GUID of the measurement channel for which a baseline should be recovered. If multiple measurement channels exist, the *measChannelGuid* must be specified.

Remarks: Calling this method is equivalent to clicking *Baseline...* to display the Baseline dialog and then clicking *Recover Last Baseline...* to recover an old baseline spectrum. Note that there are many situations where an exception may be generated by calling this method. See the example program for details.

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BaselineAcquireBackgroundAfterRef

```
Public Sub BaselineAcquireBackgroundAfterRef()
Public Sub BaselineAcquireBackgroundAfterRef(ByVal
measChannelOrSystemGuid As Guid)
```

measChannelOrSystemGuid – The GUID of the measurement channel for which a background should be acquired. If multiple measurement channels exist, the measChannelGuid must be specified.

Remarks: This method provides a means to automate what is most commonly called step #3 of the Baseline procedure (step #4 for F10-RT, “Reflection Only” or “Reflection and Transmittance”. step #2 for F10RT“Transmittance Only”). As the name of this method implies, you must have previously acquired a reference spectrum.

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BaselineAcquireReference

```
Public Sub BaselineAcquireReference()
Public Sub BaselineAcquireReference(ByVal measChannelOrSystemGuid As
Guid)
```

measChannelOrSystemGuid – The GUID of the measurement channel for which a reference should be acquired. If multiple measurement channels exist, the measChannelGuid must be specified.

Remarks: This method provides a means to automate what is most commonly called step #2 of the Baseline procedure. Calling BaselineAcquireReference may generate an exception. There are a number of rules required for successful execution of this method. Unless the acquisition timing mode in the recipe is set to Manual, you must first call BaselineAcquireSpectrumFromSample. Alternatively, you could call the variant of this method which accepts a user-supplied reflectance value if you know the sample reflectance and wish to skip step #1.

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BaselineAcquireReferenceT

```
Public Sub BaselineAcquireReferenceT()
Public Sub BaselineAcquireReferenceT(ByVal measChannelOrSystemGuid As
Guid)
```

measChannelOrSystemGuid – The GUID of the measurement channel for which a Transmittance reference should be acquired. If multiple measurement channels exist, the *measChannelGuid* must be specified.

Remarks: This method should only be called for the F10-RT. It provides a means to automate step #3 of the Baseline procedure for “Reflectance Only” or “Reflectance and Transmittance” modes, or step #1 of the Baseline procedure for “Transmittance Only” mode. No sample should be positioned on stage when called.

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BaselineAcquireReferenceUsingOldSampleReflectance

```
Public Sub BaselineAcquireReferenceUsingOldSampleReflectance ()
Public Sub BaselineAcquireReferenceUsingOldSampleReflectance (ByVal
measChannelOrSystemGuid As Guid)
```

measChannelOrSystemGuid – The GUID of the measurement channel for which a reference should be acquired. If multiple measurement channels exist, the *measChannelGuid* must be specified.

Remarks: This method provides a means to automate steps 1 and 2 of the Baseline procedure by assuming that the sample reflectance is unchanged from what it was the last time a baseline procedure was performed. Note that an exception may be thrown in some situations including the case where no prior baseline spectrum exists.

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BaselineAcquireSpectrumFromSample

```
Public Sub BaselineAcquireSpectrumFromSample ()
Public Sub BaselineAcquireSpectrumFromSample (ByVal
measChannelOrSystemGuid As Guid)
```

measChannelOrSystemGuid – The GUID of the measurement channel for which a sample spectrum should be acquired. If multiple measurement channels exist, the *measChannelGuid* must be specified.

Remarks: This method provides a means to automate what is most commonly called step #1 of the Baseline procedure.

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BaselineCommit

```
Public Sub BaselineCommit ()
Public Sub BaselineCommit (ByVal measChannelOrSystemGuid As Guid)
```

measChannelOrSystemGuid – The GUID of the measurement channel for which a new baseline should be committed. If multiple measurement channels exist, the *measChannelGuid* must be specified.

Remarks: Call this method to finalize the baseline procedure and commit the acquired spectra for use as a new baseline measurement.

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BaselineSetRefMat

```
Public Sub BaselineSetRefMat (ByVal theRefMat As String)
Public Sub BaselineSetRefMat (ByVal measChannelOrSystemGuid As Guid,
ByVal theRefMat As String)
```

measChannelOrSystemGuid – The GUID of the measurement channel for which the reference material should be assigned. If multiple measurement channels exist, the *measChannelGuid* must be specified.

theRefMat – The reference material as it would normally appear in the list of reference materials shown in the Baseline dialog.

Remarks: This method should be called prior to acquiring a reference spectrum

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BaselineShowDialog

```
Public Sub BaselineShowDialog (ByRef dialogCanceled As Boolean)
```

dialogCanceled – True if user has canceled the dialog.

Remarks: Calling this method will cause the baseline dialog box to be displayed on the screen

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GUIVisible

```
Public Property GUIVisible As Boolean
```

Remarks: Setting this property to `True` will cause the FIRemote user interface to be displayed on the screen. Note that this will normally cause the user interface window to appear on top of any other windows. If you wish to keep another window on top of the FIRemote user interface window, it may be necessary to call `.BringToFront` on that other window. If the FIRemote object is constructed with `guiType` set to `None` then an exception will be thrown if `GUIVisible` is set to `True`.

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HistoryDeleteAllResults

```
Public Sub HistoryDeleteAllResults()
```

Remarks: All measurement results in the History tab are deleted. If the FIRemote object has no user interface (`guiType = None` in `New()`), then there is no measurement history and this function has no effect.

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IntegrationCycles

```
Public Property IntegrationCycles() As Integer
Public Property IntegrationCycles(ByVal measChannelGuid As Guid) As Integer
Public Property IntegrationCycles(ByVal specIndex As SpectrometerIndex) As Integer
Public Property IntegrationCycles(ByVal measType As SubsystemMeasType) As Integer
Public Property IntegrationCycles(ByVal measChannelGuid As Guid,
ByVal specIndex As SpectrometerIndex) As Integer
Public Property IntegrationCycles(ByVal measChannelGuid As Guid,
Byval measType As SubsystemMeasType, specIndex As SpectrometerIndex)
As Integer
```

measChannelGuid – The GUID of the measurement channel for which to set or get IntegrationCycles.

measType – Specifies which measurement subsystem (Reflectance, Transmittance, etc.).

specIndex – Specifies which spectrometer (Short or Long Wavelengths).

Remarks: The IntegrationCycles parameter is visible in the dialog Edit Recipe->Acquisition Settings tab in the Measurement Timing group under the Use manually set parameters Radio Button. Calling the variants of this property without a measChannelGuid is acceptable unless this does not unambiguously measurement channel. If there is only a single measurement channel, then it is unnecessary to call the variants of this property that include the measChannelGuid. If a measurement channel includes multiple measTypes, but the measType is not supplied, then the Reflectance measType will be addressed. If a MeasurementType includes multiple spectrometers, but the specIndex is not supplied, then the ShortWavelength spectrometer will be addressed.

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IntegrationTime_ms

```
Public Property IntegrationTime_ms() As Double
Public Property IntegrationTime_ms(ByVal measChannelGuid As Guid) As Double
Public Property IntegrationTime_ms(ByVal specIndex As SpectrometerIndex) As Double
Public Property IntegrationTime_ms(ByVal measType As SubsystemMeasType) As Double
Public Property IntegrationTime_ms(ByVal measChannelGuid As Guid,
ByVal specIndex As SpectrometerIndex) As Double
Public Property IntegrationTime_ms(ByVal measChannelGuid As Guid,
Byval measType As SubsystemMeasType, specIndex As SpectrometerIndex)
As Double
```

measChannelGuid – The GUID of the measurement channel for which to set or get IntegrationTime_ms.

measType – Specifies which measurement subsystem (Reflectance, Transmittance, etc.).

specIndex – Specifies which spectrometer (Short or Long Wavelengths).

Remarks: The IntegrationTime_ms parameter is visible in the dialog Edit Recipe->Acquisition Settings tab in the Measurement Timing group under the Use manually set parameters Radio Button. See discussion in [IntegrationCycles](#) remarks regarding unsupplied arguments.

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MaximumSamplingTime

```
Public Property MaximumSamplingTime() As Double
Public Property MaximumSamplingTime(ByVal measChannelOrSystemGuid As Guid) As Double
```

measChannelOrSystemGuid – The GUID of the measurement channel or measurement system for which to set or get MaximumSamplingTime.

Remarks: The MaximumSamplingTime parameter is visible in the dialog Edit Recipe->Acquisition Settings tab in the Measurement Timing group under the Use maximum sampling time Radio Button. See discussion in [IntegrationCycles](#) Remarks regarding unsupplied arguments.

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MeasurementTimingMode

```
Public Property MeasurementTimingMode() As MeasurementTimingModes
```

```
Public Property MeasurementTimingMode (ByVal measChannelOrSystemGuid
As Guid) As MeasurementTimingModes
```

measChannelOrSystemGuid – The GUID of the measurement channel or measurement system for which to set or get MeasurementTimingMode.

Remarks: The MeasurementTimingMode parameter is visible in the dialog Edit Recipe->Acquisition Settings tab in the Measurement Timing group. Available choices are Recommended, Maximum, and Manual. See discussion in [IntegrationCycles](#) Remarks regarding unsupplied arguments.

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MeasChannelGuid

```
Public ReadOnly Property MeasChannelGuid (ByVal measChannelIndex As
Integer) As Guid
Public ReadOnly Property MeasChannelGuid (ByVal measSystemGuid As
Guid, ByVal measChannelIndex As Integer) As Guid
```

measSystemGuid – The GUID of a measurement system.

measChannelIndex – The zero-based index of the measurement channel.

Remarks: Returns the GUID of the specified channel. Note this can be used to obtain the GUID used by all methods requiring a measChannelGUID. Also note that the relationship between measChannelIndex and MeasChannelGuid is not static. Future versions of FILMapper will dynamically reorder this list in response to an equipment connect/disconnect event. You should not rely on the order of the channels in the list when attempting to perform a command on a certain channel.

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MeasChannelGuids

```
Public ReadOnly Property MeasChannelGuids () As Collection (Of Guid)
```

Remarks: Returns a collection of GUID for each measurement channel that exists.

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MeasChannelHWName

```
Public ReadOnly Property MeasChannelHWName (ByVal measChannelGuid As
Guid) As String
```

measChannelGuid – The GUID of the measurement channel for which the channel hardware name should be returned.

Remarks: The hardware name is composed of a system name string and a serial number string separated by a colon. Example: F20:09A006.

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MeasChannelHWSerialNumber

```
Public ReadOnly Property MeasChannelHWSerialNumber (ByVal
measChannelGuid As Guid) As String
Public ReadOnly Property MeasChannelHWSerialNumber (ByVal
measChannelGuid As Guid, ByVal spectrometerIndex As Integer) As
String
Public ReadOnly Property MeasChannelHWSerialNumber (ByVal
measChannelGuid As Guid, ByVal subsystemIndex As Integer, ByVal
spectrometerIndex As Integer) As String
```

measChannelGuid – The GUID of the measurement channel.

spectrometerIndex – The spectrometer index (to specify which of multiple spectrometers in the channel).

subsystemIndex – The subsystem index (to select among multiple subsystems in the channel).

Remarks: Returns the controller hardware serial number of the specified spectrometer. If the spectrometer or subsystem are not specified, the default index = 0 will be used. If there are multiple subsystems, a hyphen followed by the subsystem ID is appended to the hardware serial number. Example for single subsystem: 09A006. Example for multiple subsystem: 09A007-1

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MeasChannelName

```
Public ReadOnly Property MeasChannelName (ByVal measChannelGuid As
Guid) As String
```

measChannelGuid – The GUID of the measurement channel for which the channel name should be returned.

Remarks: By default the channel name is the empty string.

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Measure

```
Public Function Measure (ByVal formatSummaryAsRtf As Boolean) As
FIMeasResults
```

```
Public Function Measure(ByVal formatSummaryAsRtf As Boolean, ByVal
addToHistory As Boolean) As FIMeasResults
Public Function Measure(ByVal measChannelGuid As Guid, ByVal
formatSummaryAsRtf As Boolean) As FIMeasResults
Public Function Measure(ByVal measChannelGuid As Guid, ByVal
formatSummaryAsRtf As Boolean, ByVal addToHistory As Boolean) As
FIMeasResults
```

measChannelGuid – The GUID of the measurement channel for which a spectrum should be acquired and analyzed. If multiple measurement channels exist, the *measChannelGuid* must be specified.

formatSummaryAsRtf – The measurement summary returned by the *.ResultsSummary* property of the *FIMeasResults* object can be formatted as either plain text or as rtf. Formatting the summary as rtf is advantageous if it will be displayed to the user because then the full set of information including bold font and colors will be included.

addToHistory – Normally, each analysis result is added to the collection of results displayed in the History area of *FILMapper*. In some cases, it may be advantageous to suppress the addition of a result to the History area. One example where this may be needed is the case where you wish to analyze a spectrum with two different measurement recipes and then add only the best result to the History.

Remarks: Calling this function is equivalent to clicking the Measure button in *FILMapper*. Note that if the Measure button is disabled when you call this function, an exception will be thrown.

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NumberOfChannels

```
Public ReadOnly Property NumberOfChannels() As Integer
```

Remarks: Number of measurement channels that exist.

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NumberOfSpectrometers

```
Public ReadOnly Property NumberOfSpectrometers(ByVal measChannelGuid
As Guid) As Integer
Public ReadOnly Property NumberOfSpectrometers(ByVal measChannelGuid
As Guid, ByVal subsystemIndex As Integer) As Integer
```

measChannelGuid – The GUID of the measurement channel.

subsystemIndex – The subsystem index (to specify which of multiple subsystems in the channel).

Remarks: The number of spectrometers in the specified subsystem. If subsystemIndex is not provided, the default index = 0 will be used.

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NumberOfSubSystems

```
Public ReadOnly Property NumberOfSubSystems (ByVal measChannelGuid As Guid) As Integer
```

measChannelGuid – The GUID of the measurement channel.

Remarks: The number of subsystems that compose the specified measurement channel.

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OpticsConfiguration

```
Public Property OpticsConfiguration() As OpticsConfigSystemTypes [Get/Set]
Public Property OpticsConfiguration(ByVal measChannelGuid As Guid) As OpticsConfigSystemTypes [Get/Set]
```

measChannelGuid – The GUID of the measurement channel for which the OpticsConfiguration is to be get/set. If multiple measurement channels exist, the measChannelGuid must be specified.

Remarks: If the OpticsConfigSystemTypes is not be compatible with the hardware an exception will be thrown.

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OpenSpectrum

```
Public Sub OpenSpectrum(ByVal filenameAndPath As String)
Public Sub OpenSpectrum(ByVal filenameAndPath As String, ByVal measChannelGuid As Guid)
```

filenameAndPath – The full path and filename (including extension) of the spectrum. If the file cannot be opened, an exception will be thrown.

measChannelGuid – The GUID of the measurement channel for a spectrum is to be opened. If multiple measurement channels exist, the measChannelGuid must be specified.

Remarks: Unlike the behavior when a spectrum is opened in FILMapper, the software will not automatically analyze the spectrum after opening it. If analysis of the spectrum is desired, then the Analyze function must be called.

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OpenSpectrumFromBuffer

```
Public Sub OpenSpectrumFromBuffer(ByVal theBuffer As Byte())
Public Sub OpenSpectrumFromBuffer(ByVal theBuffer As Byte(), ByVal
measChannelGuid As Guid)
```

theBuffer – Byte array containing spectrum. Data in this array must have been created by SaveSpectrumToBuffer method.

measChannelGuid – The GUID of the measurement channel for a spectrum which is to be opened. If multiple measurement channels exist, the measChannelGuid must be specified.

Remarks: See remarks after [SaveSpectrumToBuffer](#)

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OperatorID

```
Public Property OperatorID() As String
```

Remarks: Get or Set the Operator ID that is visible in the user interface.

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RecipeInfo

```
Public ReadOnly Property RecipeInfo() As FIRecipeInfo
Public ReadOnly Property RecipeInfo(measChannelOrSystemGuid) As Guid)
As FIRecipeInfo
```

measChannelGuid - The GUID of the measurement channel associated with a measurement recipe. If multiple measurement channels exist the measChannelOrSystemGuid must be specified.

Remarks: The FIRecipeInfo object contains an assortment of information about the recipe including information about the film stack, if appropriate..

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SampleID

```
Public Property SampleID() As String
```

Remarks: Get or Set the Sample ID that is visible in the user interface.

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SaveSpectrum

```
Public Sub SaveSpectrum(ByVal filenameAndPath As String)
Public Sub SaveSpectrum(ByVal filenameAndPath As String, ByVal
ifTextFormatWriteYDataAsPercent As Boolean)
```

filenameAndPath – The full path and filename (including extension) of the spectrum. The file format is determined by the extension. Valid file extensions are the same as the extensions listed in the Save Spectrum dialog windows accessed via the File->Save Measured Spectrum menu item in FILMapper.

ifTextFormatWriteYDataAsPercent – If this version of SaveSpectrum without this parameter is called, the result is the same as calling the version with this parameter and setting its value to True. Thus, the only reason to call the second variant of the function is if the spectrum is being saved as a text format (either .txt or .csv) and the value of this parameter is set to False

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SaveSpectrumToBuffer

```
Public Sub SaveSpectrumToBuffer( As Byte())
```

Remarks: This function allows the caller to rapidly retrieve the complete set of data contained in a spectrum, thereby avoiding the time that would be consumed if the spectrum were saved to a file. This may be useful in cases where the caller wishes to rapidly acquire a number of spectra and store them up for later saving to file or analysis. The contents of the buffer should be considered opaque. Any changes to the data in the buffer may render the data unusable and/or may not be compatible with future versions of FILMapper.

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SetAnalysisWavelengthRange

```
Public Sub SetRecipeSetAnalysisWavelengthRange(ByVal
measChannelGuidmeasChannelOrSystemGuid As Guid, ByVal
startWavelength_nm As Single, ByVal endWavelength_nm As Single)
Public Sub SetAnalysisWavelengthRange(ByVal startWavelength_nm As
Single, ByVal endWavelength_nm As Single)
```

measChannelOrSystemGuid – The GUID of the measurement channel or system. If multiple measurement channels exist, the measChannelOrSystemGuid must be specified (since each measurement channel has its own active recipe).

startWavelength_nm – Starting wavelength for spectrum analysis.

endWavelength_nm – Ending wavelength for spectrum analysis.

Remarks: Setting the wavelength range will also switch the recipe into using a specified wavelength range instead of using the entire wavelength range visible on the spectrum graph.

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SetMaterial

```
Public Sub SetMaterial(ByVal measChannelOrSystemGuid As Guid, ByVal
layerNumber As Integer, ByVal materialName As String)
Public Sub SetMaterial(ByVal layerNumber As Integer, ByVal
materialName As String)
```

measChannelOrSystemGuid – The GUID of the measurement channel or system. If multiple measurement channels exist, the *measChannelOrSystemGuid* must be specified (since each measurement channel has its own active recipe).

layerNumber – The layer number for which to modify the material.

materialName – String containing name of the material.

Remarks: You can alter the material of a layer in the current recipe using the method. An exception will be thrown if the layer number is out-of-bounds or the material does not exist.

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SetN

```
Public Sub SetN(ByVal measChannelOrSystemGuid As Guid, ByVal
layerNumber As Integer, ByVal refractiveIndex As Single)
Public Sub SetN(ByVal layerNumber As Integer, ByVal refractiveIndex
As Single)
```

measChannelOrSystemGuid – The GUID of the measurement channel or system. If multiple measurement channels exist, the *measChannelOrSystemGuid* must be specified (since each measurement channel has its own active recipe).

layerNumber – The layer number for which to set the refractive index.

refractiveIndex – New refractive index value for layer.

Remarks: You can alter the material of a layer in the current recipe using the method. An exception will be thrown if the layer number or refractive index are out-of-bounds.

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SetRecipe

```
Public Sub SetRecipe(ByVal measChannelOrSystemGuid As Guid, ByVal
recipeName As String)
Public Sub SetRecipe(ByVal recipeName As String)
```

measChannelOrSystemGuid – The GUID of the measurement channel or system. If multiple measurement channels exist, the *measChannelOrSystemGuid* must be specified (since each measurement channel has its own active recipe).

recipeName – The recipe name to be selected must exist in the list of recipes. Note that you can select recipes contained in subfolders by specifying the relative path, using the backslash character '\ ' to separate folder names as is conventional in path naming.

Remarks: The current spectrum will not be automatically reanalyzed when a new recipe is selected. To reanalyze the spectrum you must call [AnalyzeSpectrum](#).

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SetRoughness

```
Public Sub SetRoughness(ByVal measChannelOrSystemGuid As Guid, ByVal
layerNumber As Integer, ByVal roughness_nm As Single)
Public Sub SetRoughness(ByVal layerNumber As Integer, ByVal
roughness_nm As Single)
```

measChannelOrSystemGuid – The GUID of the measurement channel or system. If multiple measurement channels exist, the *measChannelOrSystemGuid* must be specified (since each measurement channel has its own active recipe).

layerNumber – The layer number for which to modify the roughness.

roughness_nm – Roughness value which will appear in the Layers tab of the recipe for the specified layer. Units are nanometers.

Remarks: You can alter the roughness of a layer in the current recipe using the method. An exception will be thrown if the layer number or roughness are out-of-bounds.

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SetThickness

```
Public Sub SetThickness(ByVal measChannelOrSystemGuid As Guid, ByVal
layerNumber As Integer , ByVal thickness_nm As Single)
Public Sub SetThickness(ByVal layerNumber As Integer, ByVal
thickness_nm As Single)
```

measChannelOrSystemGuid – The GUID of the measurement channel or system. If multiple measurement channels exist, the *measChannelOrSystemGuid* must be specified (since each measurement channel has its own active recipe).

layerNumber – The layer number for which to modify the thickness.

thickness_nm – Thickness value which will appear in the Layers tab of the recipe for the specified layer. Units are nanometers.

Remarks: You can alter the thickness of a layer in the current recipe using the method. An exception will be thrown if the layer number or thickness is out-of-bounds.

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SetThicknessRange

```
Public Sub SetThicknessRange(ByVal layerNumber As Integer, ByVal
layerNumber As Integer , ByVal thicknessRange As Double)
Public Sub SetThicknessRange(ByVal measChannelOrSystemGuid As Guid,
ByVal layerNumber As Integer, ByVal thicknessRangePercent As Double)
```

measChannelOrSystemGuid – The GUID of the measurement channel or system. If multiple measurement channels exist, the *measChannelOrSystemGuid* must be specified (since each measurement channel has its own active recipe).

layerNumber – The layer number for which to modify the thickness.

thicknessRangePercent – Thickness range which will appear in the Layers tab of the recipe for the specified layer. Note that the value accepted by this function is always a percentage, regardless of the setting in the recipe editor which shows the range as either a percentage or a thickness. Minimum value is zero. There is no maximum value.

Remarks: You can alter the thickness range setting for a layer in the current recipe using the method. An exception will be thrown if the layer number or thickness range are out-of-bounds.

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SpectrometerDiagnostics

```
Public ReadOnly Property SpectrometerDiagnostics()
    As FISpecDiagnosticsInfo()
Public ReadOnly Property SpectrometerDiagnostics(ByVal
    measChannelGuid As Guid) As FISpecDiagnosticsInfo()
Public ReadOnly Property SpectrometerDiagnostics(ByVal
    measChannelGuid As Guid, ByVal subsystemIndex As Integer) As
    FISpecDiagnosticsInfo()
```

measChannelGuid – The GUID of the measurement channel.

subsystemIndex – The subsystem index (to select among multiple subsystems in the channel).

Remarks: Returns an array of objects containing information about the spectrometers. Information includes integration time, peak raw signal intensities of reference and background spectra, etc.

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SpectrometerType

```
Public Property SpectrometerType() As SpectrometerTypes
Public Property SpectrometerType(ByVal measChannelOrSystemGuid
    As Guid) As SpectrometerTypes
Public Property SpectrometerType(ByVal measType As SubsystemMeasType)
    As SpectrometerTypes
Public Property SpectrometerType(ByVal measChannelOrSystemGuid As
    Guid, ByVal measType As SubsystemMeasType) As SpectrometerTypes
```

measChannelOrSystemGuid – The GUID of the measurement channel or measurement system for which to set or get SpectrometerType.

measType – Specifies which measurement subsystem (Reflectance, Transmittance, etc.).

Remarks: The SpectrometerType parameter is visible in the dialog Edit Recipe->Acquisition Settings tab in the Measurement Timing group. Available choices are All, ShortwavelengthsOnly, LongWavelengthsOnly, and ExtendedWavelengths. The All and ExtendedWavelengths values select the corresponding options in the Acquisition Settings in the Recipe, but these two options result in the same behavior. See discussion in [IntegrationCycles](#) Remarks regarding unsupplied arguments.

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ActivateMonitorDisplayTab

```
Public Sub ActivateMonitorDisplayTab()
Public Sub ActivateMonitorDisplayTab(ByVal measSystemGuid As Guid)
```

measSystemGuid – The GUID of the measurement System. If multiple measurement channels exist, the *measChannelGuid* must be specified (since each measurement channel has its own active recipe).

Remarks: This function is provided to permit synchronization of the FILMapper user interface with the user interface of a client program.

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BaselineExistsAndIsAuthenticated

```
Public Function BaselineExistsAndIsAuthenticated(ByRef
authenticationIsPossible As Boolean) As Boolean
Public Function BaselineExistsAndIsAuthenticated
(measChannelOrSystemGuid As Guid, ByRef authenticationIsPossible As
Boolean) As Boolean
```

authenticationIsPossible – If baseline is not authenticated, it is possible to authenticate it when *authenticationIsPossible* = True.

Remarks: In some cases, it is desirable to check whether the baseline is already authenticated and if not whether it is possible to authenticate it. The client software has the option of automatically authenticating the baseline if that is desirable.

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BaselineHardwareAdjustInhibit

```
Public Property BaselineHardwareAdjustInhibit() As Boolean
Public Function BaselineHardwareAdjustInhibit(measChannelOrSystemGuid
As Guid) As Boolean
```

measChannelOrSystemGuid – The GUID of the measurement channel or system. If multiple measurement channels exist, the *measChannelOrSystemGuid* must be specified.

Remarks: Some measurement systems include hardware that must be periodically adjusted. The adjustment procedure happens automatically during the baseline process unless it is inhibited. The adjustment process may take several minutes to complete. This property allows the client software to control when the adjustment process is accomplished so that it can be performed at a convenient time. See [GetBaselineHardwareAdjustStatus\(\)](#) for additional information.

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GeneralPurposeIOIsSupported

```
Public ReadOnly Property GeneralPurposeIOIsSupport() As Boolean
```

Remarks: Primary purpose of this property is to permit the example program to hide or show the General Purpose IO controls. This property will be True for equipment that has the General Purpose IO hardware.

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GeneralPurposeIOReadValue

```
Public Function GeneralPurposeIOReadValue() As Byte
```

Remarks: Returns a single byte containing the current values of the general purpose IO logic input signals. Bit value of 1 means that the input voltage is in the logic high state. These input signals are only available on certain types of equipment.

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GeneralPurposeIOSetValue

```
Public Sub GeneralPurposeIOSetValue(newValue As Byte)
```

newValue - New values for the output bits.

Remarks: Sets the output state of the general purpose IO logic output signals. Setting a bit to 1 will set the corresponding output to the logic high state. These output signals are only available on certain types of equipment.

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GetBaselineHardwareAdjustStatus

```
Public Function GetBaselineHardwareAdjustStatus() As  
BaselineHardwareAdjustStatus
```

```
Public Function GetBaselineHardwareAdjustStatus
(measChannelOrSystemGuid As Guid) As BaselineHardwareAdjustStatus
```

measChannelOrSystemGuid – The GUID of the measurement channel or system. If multiple measurement channels exist, the *measChannelOrSystemGuid* must be specified.

Remarks: See [BaselineHardwareAdjustInhibit\(\)](#) for additional information. Members of the *GetBaselineHardwareAdjustStatus* Class include:

NeedsPeriodicAdjustment (Boolean) – True if the hardware is of a type that will need to be adjusted periodically.

AdjustmentRequiredNow (Boolean) – True if adjustment is required before Baseline can be completed; if adjustment is required, but inhibited, then Baseline methods will throw an exception when called.

AdjustmentRecommendedNow (Boolean) – True if adjustment is recommended.

AdjustmentPeriodHours (Single) – time period in hours between recommended adjustments.

TimeToNextRecommendedAdjustmentHours (Single) – time until the next recommended adjustment; a negative number represents the amount of time that has passed since an adjustment has become recommended.

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MaterialPath

```
Public ReadOnly Property MaterialPath() As String
```

Remarks: Reports the currently effective path for Material Files.

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MaterialPathCustom

```
Public Property MaterialPathCustom() As String
```

Remarks: This property allows a client to set/get a custom path for Material Files. If this property is set to an empty value or an invalid path, then the effective path will be the default path.

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MeasSystemGuid

```
Public ReadOnly Property MeasSystemGuid(ByVal measSystemIndex As
Integer) As Guid
```

measSystemIndex – The zero-based index of the system.

Remarks: Returns the GUID of the specified system. Note this can be used to obtain the GUID used by all methods requiring a *measSystem* GUID. Also note that the relationship between *measSystemIndex* and *MeasSystemGuid* is not static. Future versions of FILMapper will dynamically reorder this list in response to an equipment connect/disconnect event. You should not rely on the order of the systems in the list when attempting to perform a command on a certain system.

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MeasSystemGuids

```
Public ReadOnly Property MeasSystemGuids() As Collection(Of Guid)
```

Remarks: Returns a collection of GUIDs containing one item for each measurement system that exists.

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MeasSystemHWName

```
Public ReadOnly Property MeasSystemHWName(ByVal systemGuid As Guid)
As String
```

systemGuid – The GUID of a measurement system.

Remarks: The hardware name is composed of a system name string and a serial number string separated by a colon. Example: F37:09A006

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MeasSystemName

```
Public ReadOnly Property MeasSystemName(ByVal systemGuid As Guid) As
String
```

systemGuid – The GUID of a measurement system.

Remarks: The default system name is the empty string.

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NumberOfSystems

```
Public ReadOnly Property NumberOfSystems() As Integer
```

Remarks: Number of measurement systems that exist.

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RecipePath

```
Public ReadOnly Property RecipePath() As String
```

Remarks: Reports the currently effective path for Measurement Recipes.

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RecipePathCustom

```
Public Property RecipePathCustom() As String
```

Remarks: This property allows a client to set/get a custom path for Measurement Recipes. If this property is set to an empty value or an invalid path, then the effective path will be the default path.

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SaveImage

```
Public Sub SaveImage(ByVal filenameAndPath As String)
```

Remarks: Save image from most-recently acquired spectrum as a separate file.

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SetAutoFocus

```
Public Property SetAutoFocus As Boolean
```

Remarks: Get or set the state of the Use AutoFocus checkbox in the Acquisition Settings tab of the current recipe.

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SetRecipeModeToSpectrumAnalysis

```
Public Sub SetRecipeModeToSpectrumAnalysis()  
Public Sub SetRecipeModeToSpectrumAnalysis(ByVal  
measChannelOrSystemGuid As Guid)  
Public Sub SetRecipeModeToThickness()
```



```
Public Sub SetRecipeModeToThickness (ByVal measChannelOrSystemGuid As Guid)
```

measChannelOrSystemGuid – The GUID of one of the measurement channels in a multiple channel system or the GUID of the system. If multiple measurement channels exist, the *measChannelGuid* must be specified.

Remarks: If Spectrum Analysis recipes are supported by the hardware or add-on licenses, then the Measure tab in the user interface will display a tab control that allows the user to switch modes. The tab associated with the Spectrum Analysis recipe mode is labeled “AR” or “Spectrum”. The other tab is labeled “HC” or “Thickness” or “Thickness, n, k, r”. Calling *SetRecipeModeToSpectrumAnalysis* or *SetRecipeModeToThickness* is the same as clicking on the Spectrum or Thickness tab in the user interface.

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ShutdownRequestedHandler

```
Public Delegate Sub ShutdownRequestedHandler (ByVal e As Windows.Forms.FormClosingEventArgs)
Public Event ShutdownRequested As ShutdownRequestedHandler
```

e – The standard argument type for a form about to close.

Remarks: The client software can prohibit closing of the software by setting *e.Cancel* to *True*. Alternatively, the client software may wish to perform certain actions prior to allowing the *FIRemote* class to shut down.

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SetRecipeSpectrumAnalysis

```
Public Sub SetRecipeSpectrumAnalysis (ByVal recipeName As String)
Public Sub SetRecipeSpectrumAnalysis (ByVal measChannelOrSystemGuid As Guid, ByVal recipeName As String)
Public Sub SetRecipeThickness ()
Public Sub SetRecipeThickness (ByVal measChannelOrSystemGuid As Guid, ByVal recipeName As String)
```

measChannelOrSystemGuid – The GUID of one of the measurement channels in a multiple channel system or the GUID of the system. If multiple measurement channels exist, the *measChannelGuid* must be specified.

recipeName – The recipe name to be selected must exist in the list of recipes. Note that you can select recipes contained in subfolders by specifying the relative path, using the backslash character ‘\’ to separate folder names as is conventional in path naming.

Remarks: Same as [SetRecipeModeToSpectrumAnalysis](#) or [SetRecipeModeToThickness](#), but caller specifies name of recipe to load during recipe mode switch.

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ShuttingDown

```
Public Event ShuttingDown()
```

Remarks: Client software can add an event handler for this event in order to facilitate performing any necessary shut-down actions. This event is primarily used in order to permit client software to react to closing of the FIREmote user interface.

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SystemAutoSave

```
Public Property SystemAutoSave() As Boolean
Public Property SystemAutoSave(ByVal systemGuid As Guid) As Boolean
```

systemGuid – The GUID of a measurement system.

Remarks: You can set or get the state of the AutoSave setting using this property. Note that setting a new state for SystemAutoSave will not affect an on-going monitor process, but will take effect the next time a new set of data starts being collected.

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SystemAutoSaveBaseFileNameAndPath

```
Public Property SystemAutoSaveBaseFileNameAndPath() As String
Public Property SystemAutoSaveBaseFileNameAndPath(ByVal systemGuid As
Guid) As String
```

systemGuid – The GUID of a measurement system.

Remarks: You can set or get the base filename and path for the AutoSave file using this property. The full filename is generated by appending a date and time stamp to the base filename. Note that setting a new filename will not affect an on-going monitor process, but will take effect the next time a new set of data starts being collected.

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SystemMeasure

```
Public Function SystemMeasure() As FIMeasResultValuesOnly
Public Function SystemMeasure(ByVal
deleteAccumulatedDataBeforeMeasure As Boolean) As
FIMeasResultValuesOnly
Public Function SystemMeasure(ByVal systemGuid As Guid) As
FIMeasResultValuesOnly
Public Function SystemMeasure(ByVal systemGuid As Guid, ByVal
deleteAccumulatedDataBeforeMeasure As Boolean) As
FIMeasResultValuesOnly
```

deleteAccumulatedDataBeforeMeasure – There is no analog for this parameter in the user interface. Setting this parameter to True causes any existing accumulated data points to be deleted before the measurement is performed.

systemGuid – The GUID of a measurement system.

Remarks: Acquire and measure on all channels in a system. Measurement is performed simultaneously on all channels. Measured results are contained in an FIMeasResultValuesOnly object.

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SystemMeasurementCompletedEventHandler

```
Public Delegate Sub SystemMeasurementCompletedEventHandler(ByVal
systemGuid As Guid, ByVal theResults As FIMeasResultValuesOnly)
Public Event SystemMeasurementCompleted As
SystemMeasurementCompletedEventHandler
```

systemGuid – The GUID of a measurement system.

Remarks: This event is raised upon completion of a SystemMeasure task and after each measurement during a SystemMonitor process. You should avoid performing lengthy operations (such as writing data to a file) in the handler for this event because the monitor process will be halted until the handler function exits. If execution of a lengthy operation is needed, you should invoke a different thread to perform the operation. If the event is raised as a result of completing a SystemMeasure task, then you will need to exercise care to avoid creating a threading deadlock. A deadlock will occur if you invoke the thread which called SystemMeasure in the handler for this event because that thread will not return from SystemMeasure until all the event handlers have finished executing. See the FIRemoteTest example program to see one way to avoid the deadlock problem.

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SystemStartMonitoring

```
Public Sub SystemStartMonitoring()  
Public Sub SystemStartMonitoring(ByVal systemGuid As Guid)
```

systemGuid – The GUID of a measurement system.

Remarks: This function starts a monitoring process

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SystemStopMonitoring

```
Public Sub SystemStopMonitoring()  
Public Sub SystemStopMonitoring(ByVal systemGuid As Guid)
```

Remarks: This function stops a monitoring process.

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GetStageMotionParams

```
Public Sub GetStageMotionParams(ByRef rotaryMotorLowSpeedPercent As  
Short, ByRef linearOrXOrYMotorLowSpeedPercent As Short, ByRef  
zMotorLowSpeedPercent As Short, ByRef zUnloadHeightSampleCoordMm As  
Double)
```

<name>*MotorLowSpeedPercent* - Low speed motion movement velocity is proportional to this setting. At 100% the speed will be the same as the fast motion speed. at 0% the speed will be the minimum speed.

zUnloadHeightSampleCoordMm – Height currently set for the Unload location.

Remarks: This method works in conjunction with SetStageMotionParams.

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ModuleHasMotorizedZStage

```
Public Property ModuleHasMotorizedZStage() As Boolean
```

Remarks: Determine if the measurement system has a motorized focus mechanism.

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SetStageMotionParams

```
Public Sub SetStageMotionParams (ByVal rotaryMotorLowSpeedPercent As Short,
ByVal linearOrXOrYMotorLowSpeedPercent As Short, ByVal
zMotorLowSpeedPercent As Short, ByVal zUnloadHeightSampleCoordMm As
Double)
```

<name>MotorLowSpeedPercent - Low speed motion movement velocity is proportional to this setting. At 100% the speed will be the same as the fast motion speed. at 0% the speed will be the minimum speed.

zUnloadHeightSampleCoordMm – Height currently set for the Unload location.

Remarks: This method works in conjunction with GetStageMotionParams.

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WaferMapAllFinished

```
Public Event WaferMapAllFinished (ByVal theData As FIWaferMapData,
errorCode As FIWaferMapResultsErrCode, errorMessage As String)
```

theData – The results of the finished wafer map

errorCode - Indicates if the wafermap ended normally or there is an error.

errorMessage - A string describing any error which may have happened while measuring the wafermap

Remarks: This event is raised when a wafer map is completed, paused, or aborted. The handler of this event must check *theData* to determine if the map is actually completed. If a wafer map is paused or aborted, then *theData* will be `Nothing`. In addition, *errorCode* and *errorMessage* will contain any error information about the wafer map such as whether any of the spectra were saturated.

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WaferMapClearHistoryWhenMapStarts

```
Public Property WaferMapClearHistoryWhenMapStarts () As Boolean
```

Remarks: Get or set the state of the Clear History when map starts checkbox in the Wafer Map tab of the Setup >Options dialog.

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WaferMapCreateMapFile

```
Public Sub WaferMapCreateMapFile(ByVal theData As FIWaferMapData,
mapID As String, theFileNameAndPath As String)
```

theData – Data to be saved into the map file.

mapID - Id for the map to be saved.

theFileNameAndPath - Name of the file, including path and filename extension.

Remarks: This method creates a wafer map file (.fimap) in the specified location. Calling this method may cause the software to overwrite an existing file if the name is the same as an existing file.

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WaferMapCreatePattern

```
Public Sub WaferMapCreatePattern(ByVal theWaferType As FIWaferType,
width As Single, height As Single, x() As Single, y() As Single,
numPoints As Integer, patternFileName As String)
```

theWaferType – Specify if the shape of the wafer is round or rectangular.

width - The width of a rectangular wafer or the diameter of a round wafer.

height - The height of a rectangular wafer or the diameter of a round wafer.

x - x values of all the locations in the pattern.

y - y values of all the locations in the pattern. Should have the same number of elements as the x array.

numPoints - Total number of locations in the pattern. Should be equal to the length of x and y.

patternFileName - Name of the pattern file to be created. Not including path or filename extension.

Remarks: This method creates a pattern file (.pat) in the folder for custom pattern files. Calling this method may cause the software to overwrite an existing pattern file if the name is the same as an existing pattern filename.

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WaferMapCurrentFileName

```
Public ReadOnly Property WaferMapCurrentFileName() As String
```

Remarks: Get the filename of the current wafer map.

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WaferMapCurrentWaferID

```
Public ReadOnly Property WaferMapCurrentWaferID() As String
```

Remarks: Get the file ID of the current wafer map.

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WaferMapDisableMapButtons

```
Public Property WaferMapDisableMapButtons() As Boolean
```

Remarks: Get or set the disable state of the map buttons (Start, Stop and New) on the WaferMap tab.

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WaferMapGetCurrentStageLocation

```
Public Sub WaferMapGetCurrentStageLocation(ByRef currentX As Single,  
ByRef currentY As Single)
```

Remarks: Get the (x,y) location of the stage where x and y are reported in mm.

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WaferMapGetUsableHeightAndWidth

```
Public Sub WaferMapGetUsableHeightAndWidth(ByRef usableHeight As  
Single, ByRef usableWidth As Single)
```

Remarks: Get the maximum acceptable height and width as limited by the range of motion possible with the stage.

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WaferMapGetVacuumIsOn

```
Public Function WaferMapGetVacuumIsOn() As Boolean
```

Remarks: Report the current state of the stage vacuum valve.

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WaferMapInitXMotion

```
Public Sub WaferMapInitXMotion(btnLeftFast As Button, btnLeftSlow As Button, btnRightSlow As Button, btnRightFast As Button, useGoToSpeedsForFastMotion As Boolean)
```

BtnLeftFast, BtnLeftSlow, BtnRightSlow, BtnRightFast – Buttons in user interface of client which can be pressed and held down by user to move x-axis of stage.

Remarks: Add event handlers if FIRemote for buttons in client program which react to button press to move the stage.

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WaferMapInitYMotion

```
Public Sub WaferMapInitYMotion(btnInFast As Button, btnInSlow As Button, btnOutSlow As Button, btnOutFast As Button, useGoToSpeedsForFastMotion As Boolean)
```

BtnInFast, BtnInSlow, BtnOutSlow, BtnOutFast – Buttons in user interface of client which can be pressed and held down by user to move y-axis of stage.

Remarks: Add event handlers if FIRemote for buttons in client program which react to button press to move the stage.

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WaferMapInitZMotion

```
Public Sub WaferMapInitZMotion(btnInFast As Button, btnInSlow As Button, btnOutSlow As Button, btnOutFast As Button, useGoToSpeedsForFastMotion As Boolean)
```

BtnInFast, BtnInSlow, BtnOutSlow, BtnOutFast – Buttons in user interface of client which can be pressed and held down by user to move z-axis of stage.

Remarks: Add event handlers if FIRemote for buttons in client program which react to button press to move the stage.

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WaferMapMeasurementControlsPanelLocation

```
Public ReadOnly Property WaferMapMeasurementControlsPanelLocation()  
As Point
```

Remarks: Return the location of the center location of the rectangular area containing Start, Stop and New buttons. An exception will be thrown if the graphical user interface was not created at startup.

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WaferMapMoveStage

```
Public Sub WaferMapGetUsableHeightAndWidth(newX As Single, newY As  
Single)
```

Remarks: Move stage to specified (x,y) location where x and y are given in mm.

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WaferMapMoveToLoadPosition

```
Public Sub WaferMapMoveToLoadPosition()
```

Remarks: Move stage into the load position to facilitate loading and unloading of samples.

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WaferMapMoveToRestPosition

```
Public Sub WaferMapMoveToRestPosition()
```

Remarks: Move stage into the rest position. The location of the rest position varies with different measurement stages. Typically the rest position is defined as the location where the measurement spot is centered over the stage.

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WaferMapNew

```
Public Sub WaferMapNew()
```

Remarks: This method deletes the current wafer map and creates an empty wafer map.

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WaferMapNextFileName

```
Public Property WaferMapNextFileName() As String
```

Remarks: Get or set the wafer map name for the next measurement. Changing this value while a measurement is running will not affect WaferMapCurrentFileName until WaferMapNew method is called. However, after WaferMapNew is called, but before WaferMapStart is called, changing WaferMapNextFileName will update WaferMapCurrentFileName.

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WaferMapNextWaferID

```
Public Property WaferMapNextWaferID() As String
```

Remarks: Get or set the wafer map ID for the next measurement. Changing this value while a measurement is running will not affect WaferMapCurrentWaferID until WaferMapNew method is called. However, after WaferMapNew is called but before WaferMapStart is called, changing WaferMapNextWaferID will update WaferMapCurrentWaferID.

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WaferMapOpen

```
Public Sub WaferMapOpen(By Val fileNameAndPath As String)
```

fileNameAndPath - Name of the file, including path and filename extension.

Remarks: This method opens an existing wafer map file (.fimap).

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WaferMapRecipeAutoFocusInCenterOnly

```
Public Property WaferMapRecipeAutoFocusInCenterOnly As Boolean
```

Remarks: Get or set the state of the AutoFocus in center only checkbox in the Wafer Map tab of the current recipe.

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WaferMapRecipeAutomaticAlignmentSampleOrigin

Public Property WaferMapRecipeAutomaticAlignmentSampleOrigin As Boolean

Remarks: Get or set the state of the Automatic Alignment Sample Origin checkbox in the Advanced Rect. Map Settings dialog of the current recipe.

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WaferMapRecipeAutomaticAlignmentSampleRotation

Public Property WaferMapRecipeAutomaticAlignmentSampleRotation As Boolean

Remarks: Get or set the state of the Automatic Alignment Sample Rotation checkbox in the Advanced Rect. Map Settings dialog of the current recipe.

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WaferMapRecipeGetPattern

Public Sub WaferMapRecipeGetPattern(By Ref patternFileType As FIWaferMapPatternType, ByRef patternName As String)

patternFileType - Variable to receive the coordinate type of current pattern.

patternName - Variable to receive current pattern name. If PatternFileType is Custom, then the received value is the current pattern filename in the folder for custom pattern files without path or filename extension; Otherwise, it will be the selected number of measurement locations in that coordinate system.

.

Remarks: This method gets pattern type and filename of the pattern file (either pre-defined or customer-created) used in current recipe. patternFileType and patternName in this method follow the same format as those in method WaferMapRecipeSetPattern and hence could be supplied to that method in order to go back to a previously used pattern.

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WaferMapRecipeSampleCoordinateSystemOrigin

```
Public Sub WaferMapRecipeSampleCoordinateSystemOrigin
AsWaferCoordOriginType
```

Remarks: Get or set the Sample Coordinate System Origin setting in the Advanced Rect. Map Settings dialog of the current recipe.

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WaferMapRecipeSaveResultsToDisk

```
Public Property WaferMapRecipeSaveResultsToDisk() As Boolean
```

fileNameAndPath - Name of the file, including path and filename extension.

Remarks: Get or set the state of the "Save results to disk" checkbox in the WaferMap tab of the current recipe.

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WaferMapRecipeSetEdgeExclusion

```
Public Sub WaferMapRecipeSetEdgeExclusion(By Val edgeExclusion As
Single)
```

edgeExclusion - Edge exclusion value in mm.

Remarks: This method sets the Edge Exclusion in the current recipe.

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WaferMapRecipeSetPattern

```
Public Sub WaferMapRecipeSetPattern(ByVal patternFileType
AsFIWaferMapPatternType, ByVal patternName As String)
```

patternFileType - Specify the coordinate type of the pattern.

patternName - If PatternFileType is Custom, then patternName is the pattern filename in the folder for custom pattern files without path or filename extension; Otherwise, patternName is the number of measurement locations available for that coordinate system.

Remarks: This method sets the pattern in the current recipe from an existing pattern file. The pattern file is specified by the combined information from `patternFileType` and `patternName`. If they mismatch (which means the pattern file cannot be found in the folder for its category) then an exception will be thrown.

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WaferMapRecipeSetSampleSize

```
Public Sub WaferMapRecipeSetSampleSize(By Val width As Single, By Val height As Single)
```

Width - Width of the sample. Must be >0.

Height - Height of the sample. Must be >0.

Remarks: This method sets the size of a rectangular sample in the current recipe.

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WaferMapSetVacuum

```
Public Sub WaferMapSetVacuum(vacuumOn As Boolean)
```

Remarks: Open or close the vacuum valve.

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WaferMapResultsFolder

```
Public Property WaferMapResultsFolder() As String
```

Remarks: Get or set the name of the folder (including path) where wafer map files are automatically saved at the completion of a wafer map if `WaferMapRecipeSaveResultsToDisk` is set to `True`.

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WaferMapSetCurrentLocationAsSampleOrigin

```
Public Sub WaferMapSetCurrentLocationAsSampleOrigin()
```

Remarks: Set the current stage position as the sample origin. This method is typically used when the user desires to interactively locate the sample origin, often by viewing an image from a camera. This method is only useful if Automatic Alignment is turned off.

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WaferMapStateChangedHandler

```
Public Delegate SubWaferMapStateChangedHandler (theCommandStates As
Filmetrics.FIRemote.FIWaferMapCommandStates)
Public Event WaferMapStateChanged (theCommandStates As
FIWaferMapCommandStates)
```

theCommandStates - Lists the current states of the buttons on WaferMap panel.

Remarks: This event is raised when the state of the buttons in the wafer map operation control area (Start, Stop, New, etc.) has changed.

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WaferMapStart

```
Public Sub WaferMapStart()
```

Remarks: This method starts a new measurement of wafer map. If the wafer map has been paused, then calling this method will resume the wafer map.

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WaferMapStop

```
Public Sub WaferMapStop()
```

Remarks: This method pauses the current measurement. The paused measurement can be resumed by calling WaferMapStart().

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ZGetLimitsSampleCoordMm

```
Public Sub ZGetLimitsSampleCoordMm (ByRef lowLimit As Double, By Ref
highLimit As Double)
```

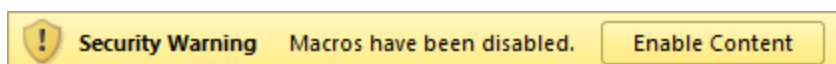
lowLimit, highLimit – Motion limits in mm for z (focus) motion.

Remarks: The focus mechanism is restricted so that it can only move in the range described by the *lowLimit* and *highLimit*. Increasing z values represent locations further from the sample stage surface.

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FIRemoteMapCOM dll

The dll is automatically included whenever FILMapper is installed. Since the dll references the corresponding .exe file it is located inside the FILMapper folder in the Program Files (or Program Files (x86) on 64-bit systems) path. The best way to learn how to use the dll is to examine the example Excel workbook that is included with the software. The workbook has the same name as the dll, but has the extension .xlsm and is located in the same folder as the dll. When you open the .xlsm file for the first time, you will see a warning banner as shown below.



You must click the Enable Content button in order to allow the code associated with the buttons on the worksheets to run. If you do not see the security warning when you open the spreadsheet, then you may need to modify settings in Excel using the Trust Center. The exact procedure varies, depending on which version of Excel you are using.

To see the example source code, click the Developer tab on the ribbon. Then click Visual Basic and double-click the ThisWorkbook object.

Reference for FIRemote Class in FIRemoteMapCOM dll:

Methods, Properties, and Events:

```
Public Sub AcquireSpectrum(ByRef spectrumWavelengths() As Single,
ByRef spectrumData() As Single)
```

arguments – Same as FIRemote Class

Remarks: See remarks for [AcquireSpectrum\(\)](#) in FIRemote Class.

```
Public Sub AuthenticateRefBac()
```

arguments – Same as FIRemote Class

Remarks: See remarks for [AuthenticateRefBac\(\)](#) in FIRemote Class.

```
Public Sub BaselineAcquireBackgroundAfterRef()
```

arguments – Same as FIRemote Class

Remarks: See remarks for [BaselineAcquireBackgroundAfterRef\(\)](#) in FIRemote Class.

```
Public Sub BaselineAcquireReference()
```

arguments – Same as FIRemote Class

Remarks: See remarks for [BaselineAcquireReference\(\)](#) in FIRemote Class.

`Public Sub BaselineAcquireSpectrumFromSample ()`
arguments – Same as FIRemote Class

Remarks: See remarks for [BaselineAcquireSpectrumFromSample\(\)](#) in FIRemote Class.

`Public Sub BaselineCommit ()`
arguments – Same as FIRemote Class

Remarks: See remarks for [BaselineCommit\(\)](#) in FIRemote Class.

`Public Sub BaselineSetRefMat ()`
arguments – Same as FIRemote Class

Remarks: See remarks for [BaselineSetRefMat\(\)](#) in FIRemote Class.

`Public Sub Measure (ByVal formatSummaryAsRtf As Boolean, ByRef measLayerThickness () As Single, ByRef measGOF As Single, ByRef summary As String)`

formatSummaryAsRtf – The measurement summary can be formatted as either plain text or as rtf. Formatting the summary as rtf is advantageous if it will be displayed to the user because then the full set of information including bold font and colors will be included.

measLayerThickness – Array containing thickness of all layers. Thickness of Layer 1 is in index 1 in the array.

measGOF – Measured Goodness Of Fit parameter.

Summary – Same as text which appears in Results area in Measure tab.

Remarks: See remarks for [Measure\(\)](#) in FIRemote Class.

`Public Sub SetRecipe (recipeName As String)`

Arguments and Remarks – See documentation for [SetRecipe](#) in FIRemote Class.

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